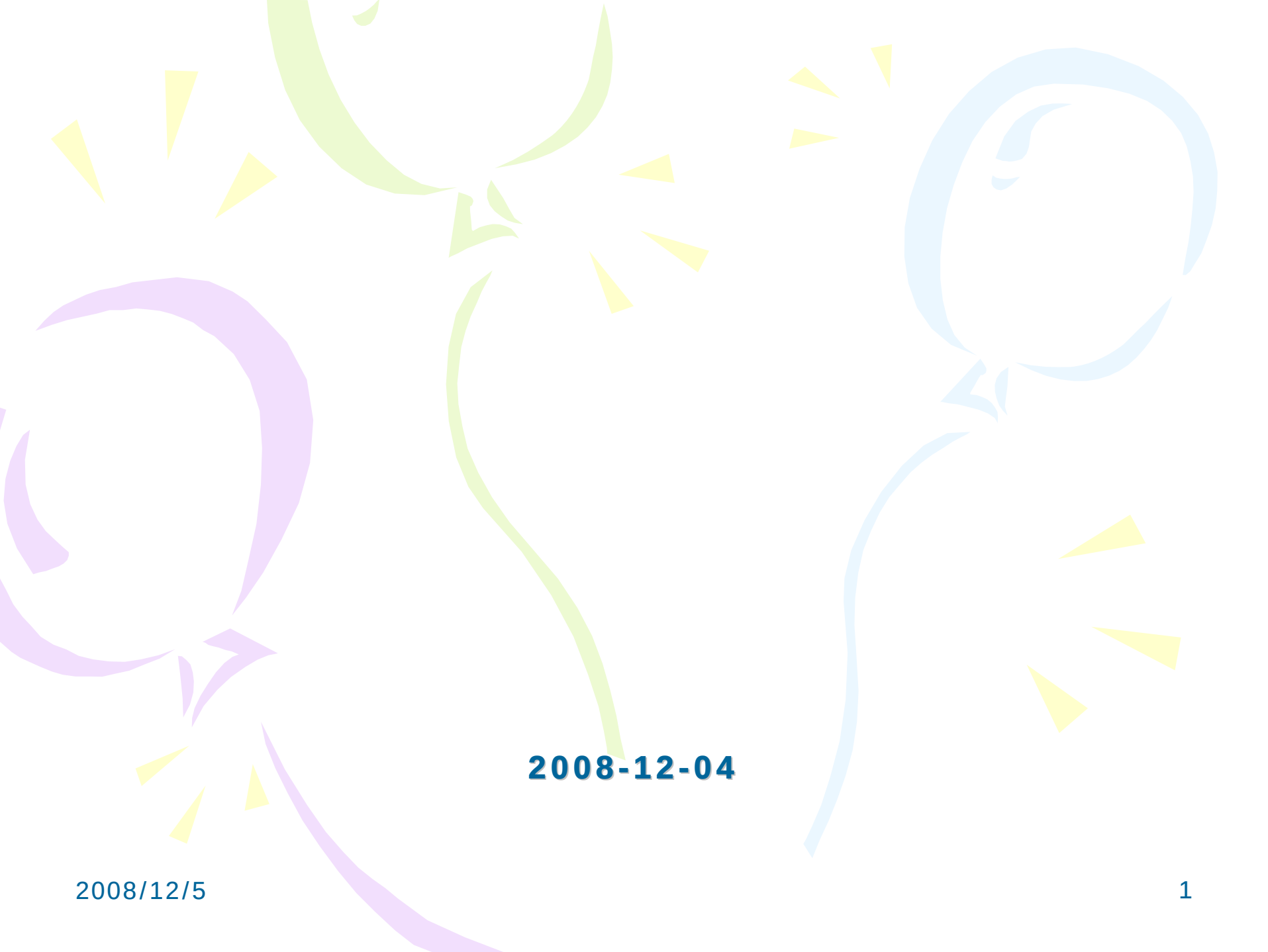
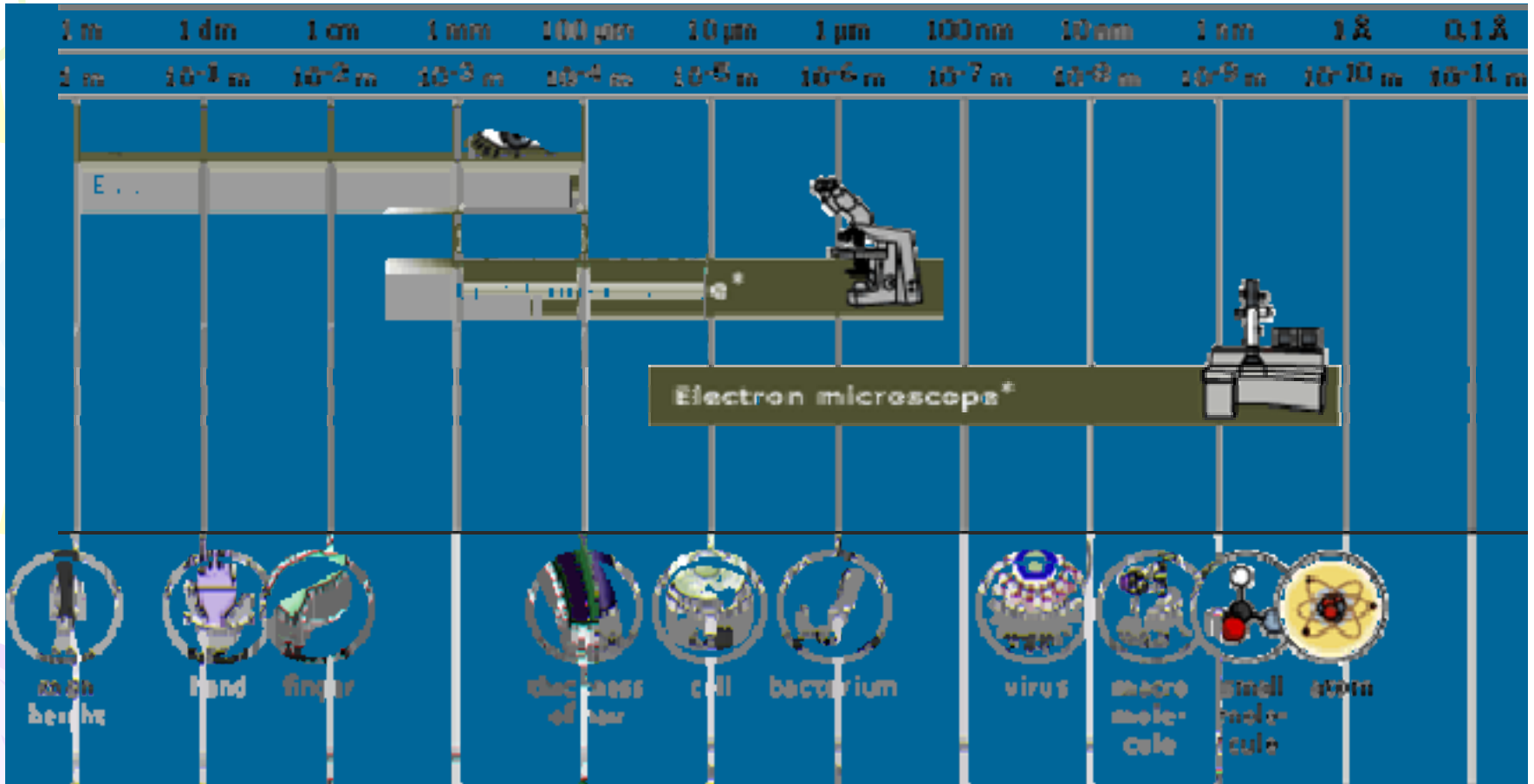
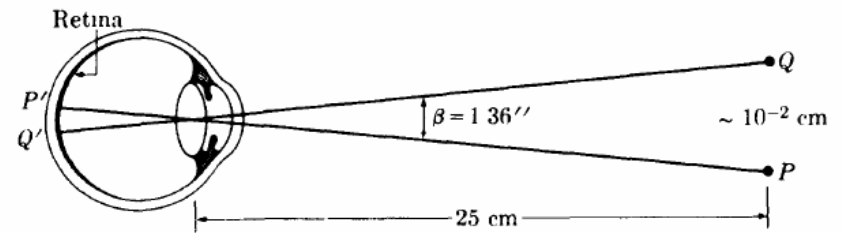




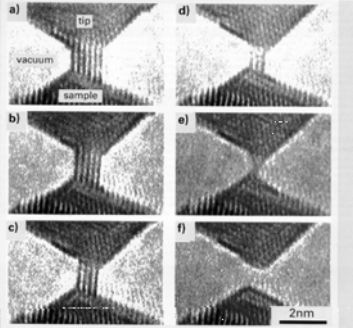
2008-12-04

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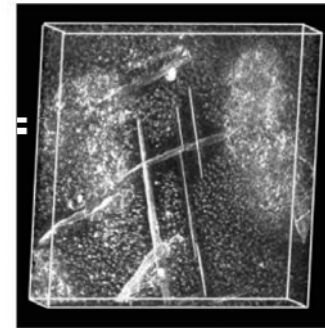
$$d = \lambda / 2n \sin \theta$$



In situ



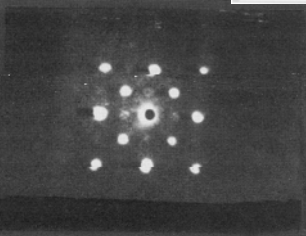
TEM



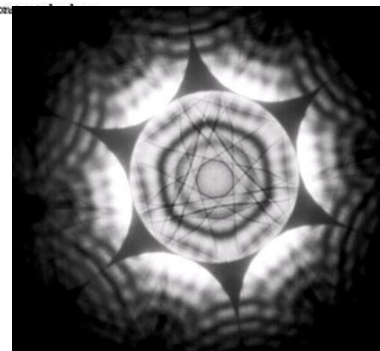
3D

Fig. 3 : Voxel projection of recon

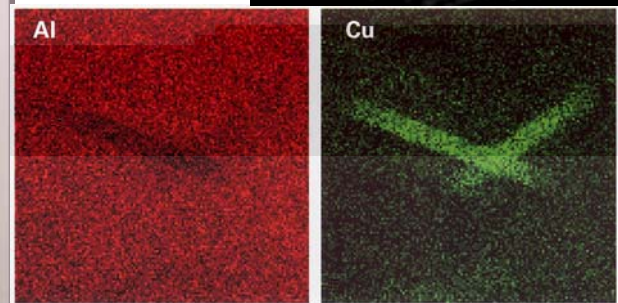
SAED



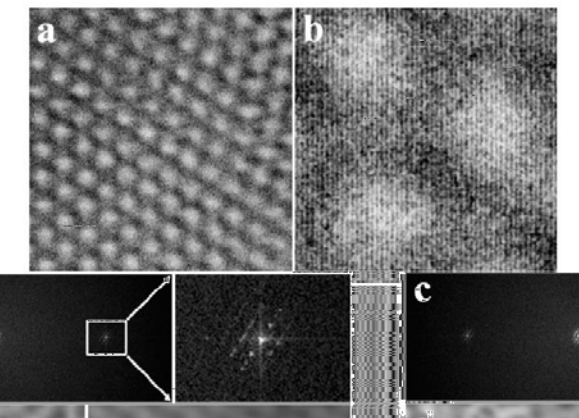
CBED



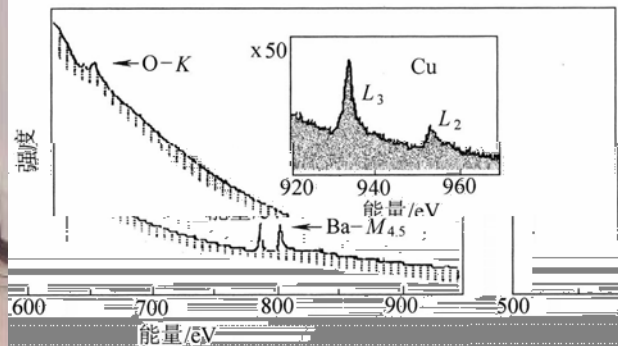
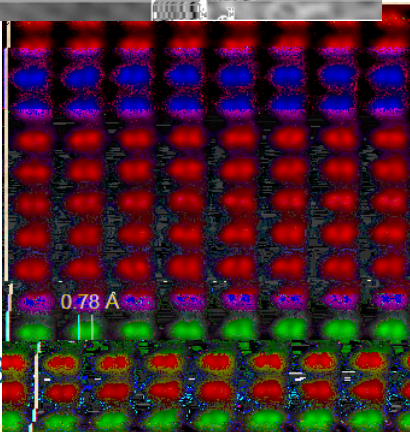
EDX



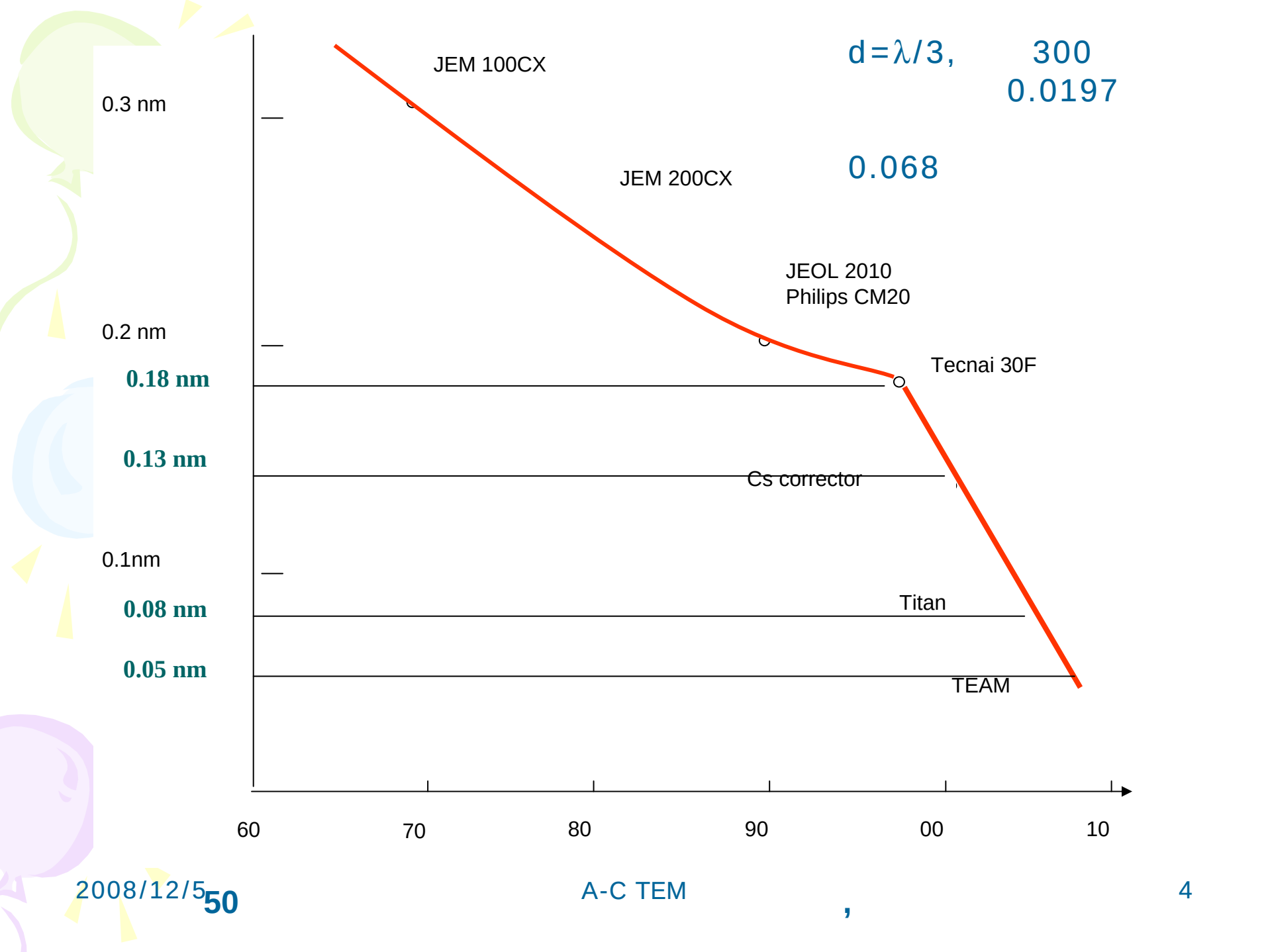
EH

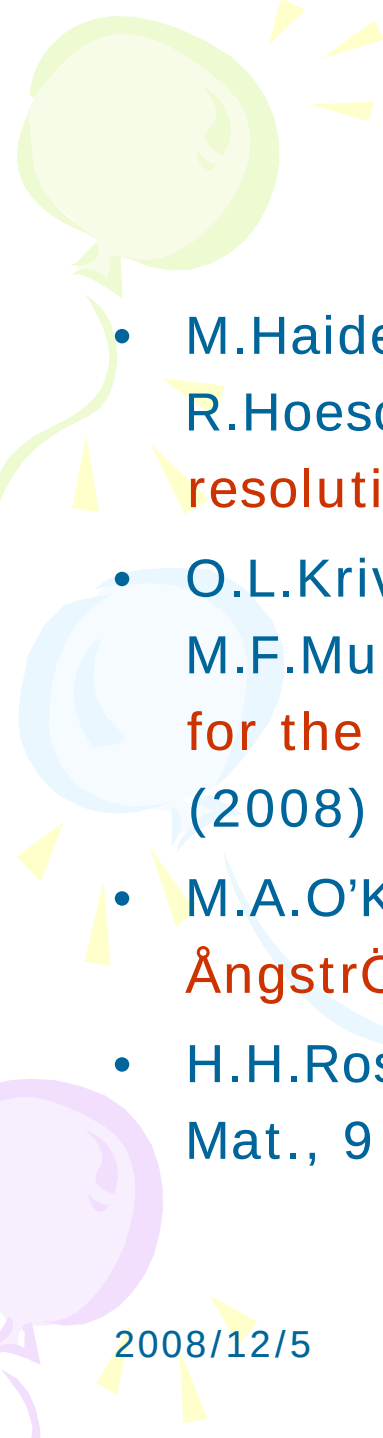


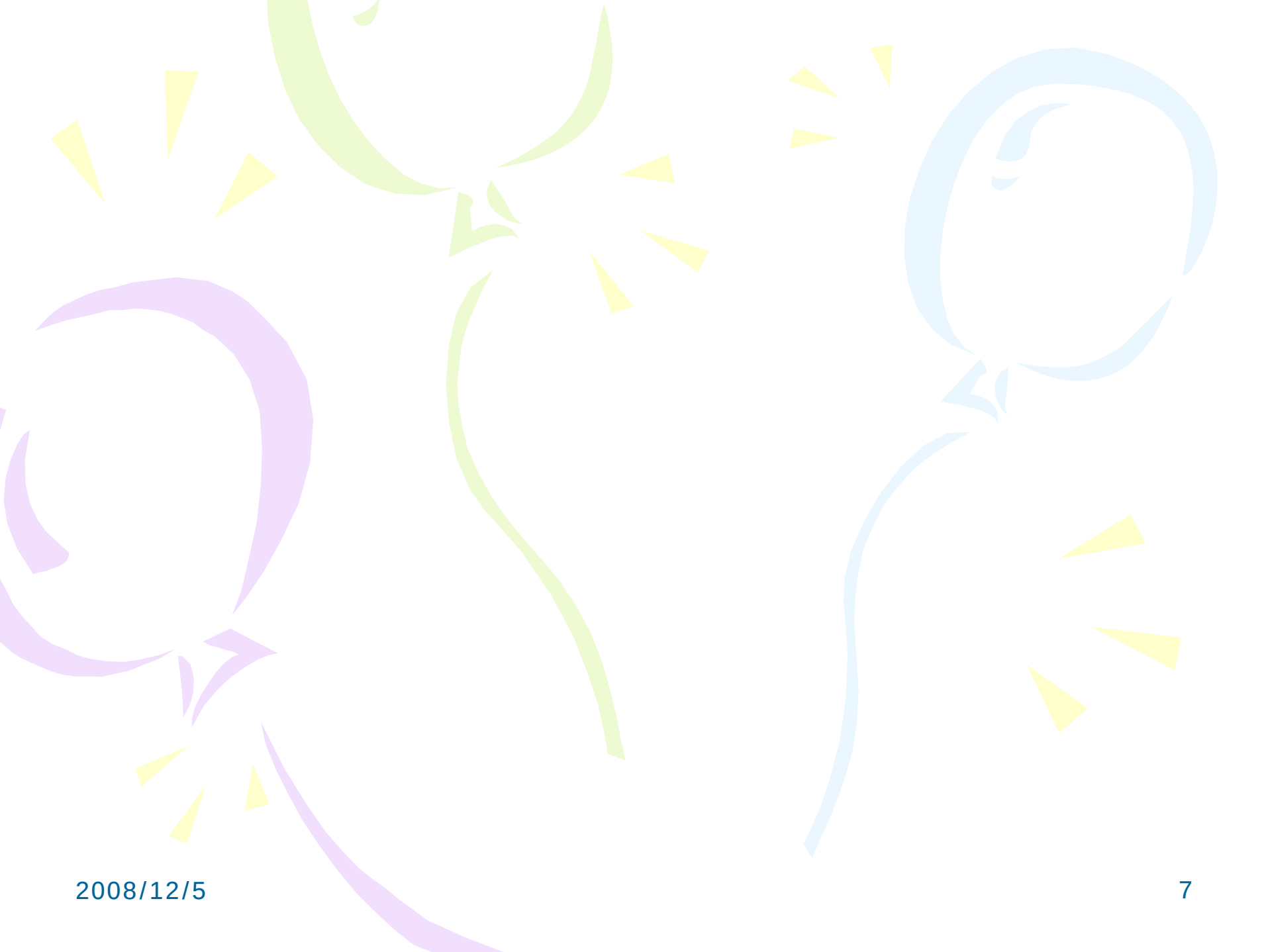
HREM
2008

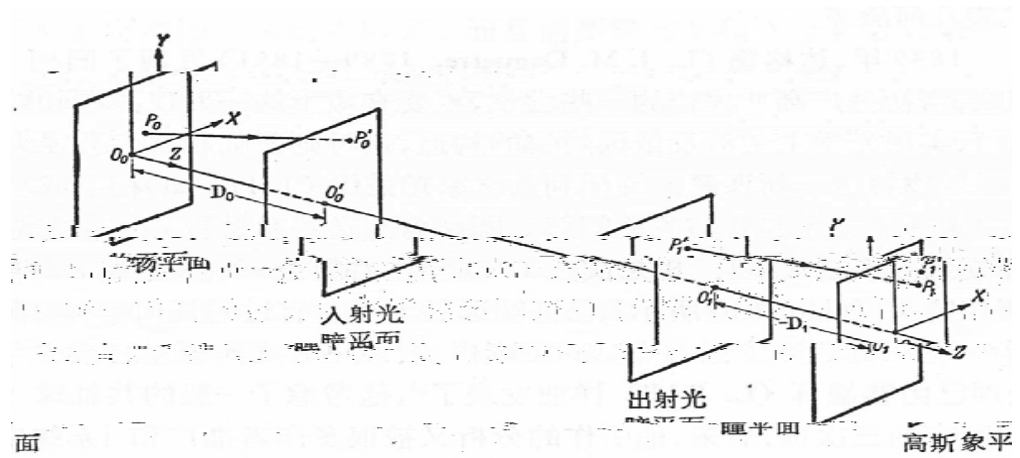
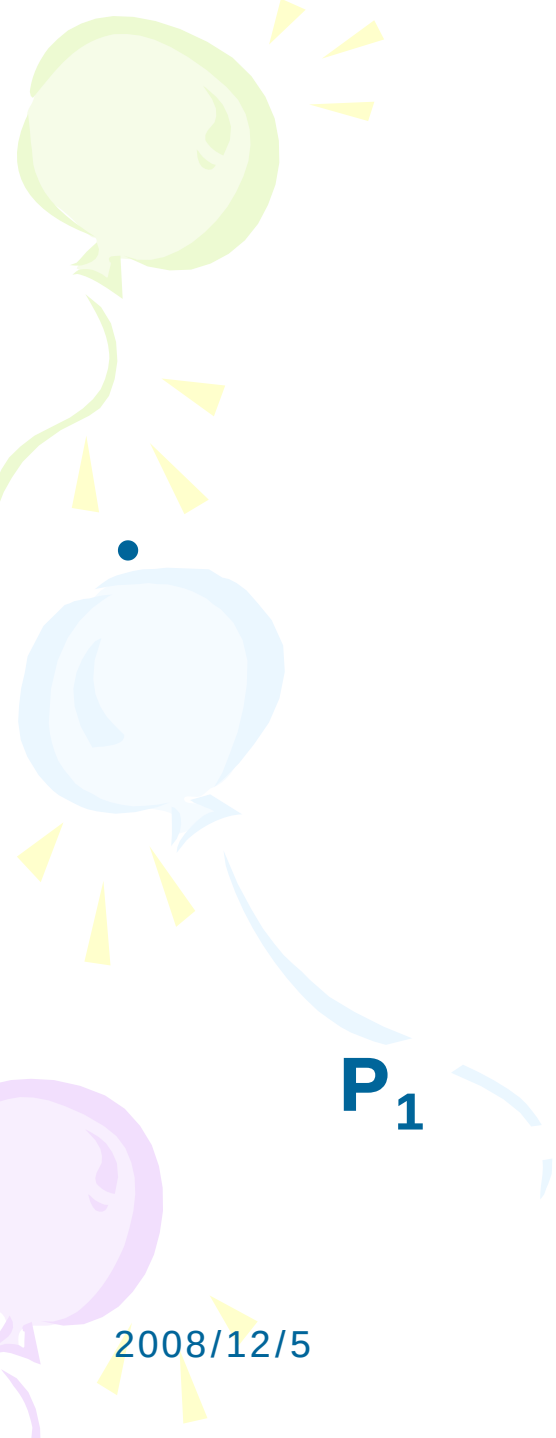


EELS



- 
- M.Haider, H.Muller, S.Uhlemann, J.Zach, U.Loebau, and R.Hoeschen: “Prerequisites for a Cc/Cs-corrected ultrahigh-resolution TEM”, Ultramicroscopy 108 (2008) 167.
 - O.L.Krivanek, G.J.Corbin, N.Dellby, B.F.Elson, R.J.Keyse, M.F.Murfitt, C.S.Own, Z.S.Szilagyi, J.W.Woodruff: “An EM for the aberration-corrected era”, Ultramicroscopy 108 (2008) 179.
 - M.A.O’Keefe: “Seeing atoms with aberration-corrected sub-Ångström EM”, Ultramicroscopy 108 (2008) 196.
 - H.H.Rose: “Optics of high-performance EM”, Sci. Tech. Adv. Mat., 9 (2008) 014107.





P_1

$\overrightarrow{P_1^* P_1}$

$P_1^* \quad P_0$



n

n

M

M

TC

T

r

θ, ϕ, ϕ'

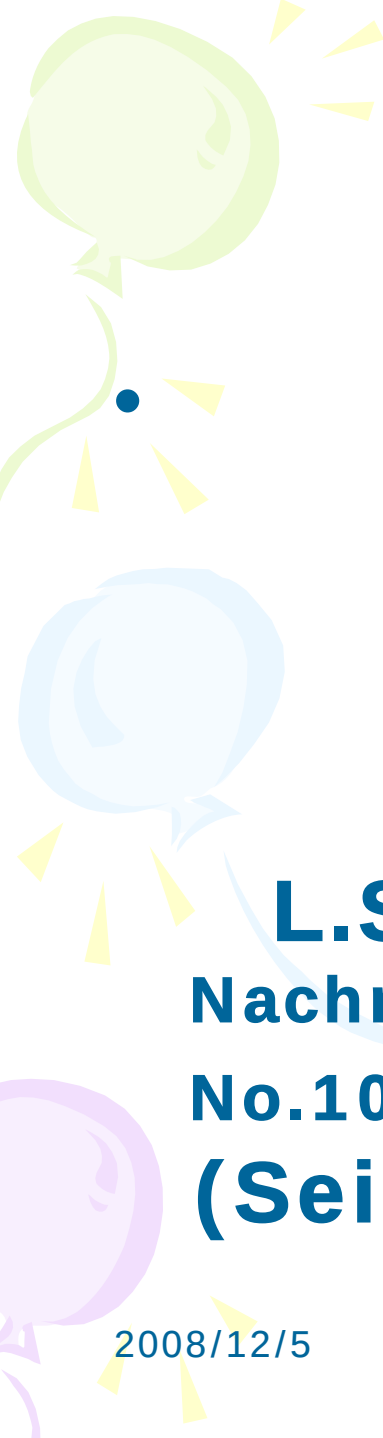
ϕ θ

ϕ

θ

ϕ

ϕ



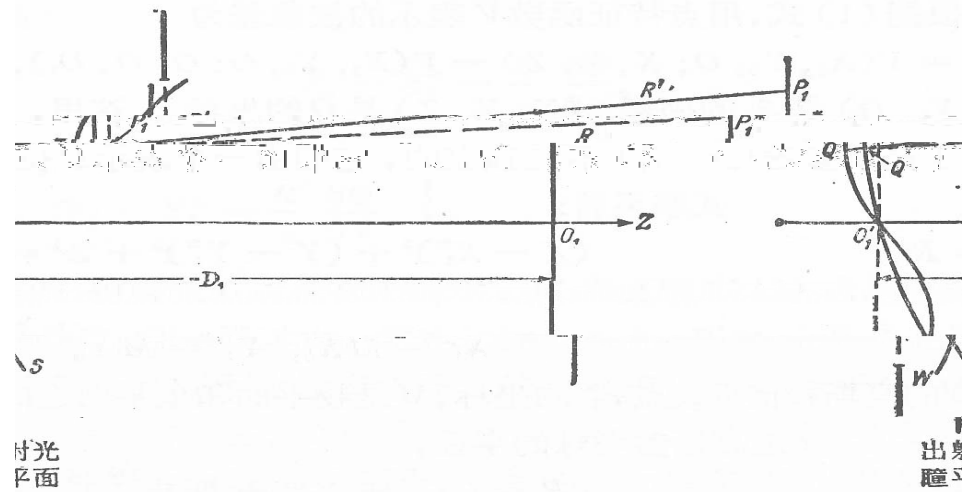
5

$$\sin \theta = \theta - \frac{\theta^3}{3} + \dots$$

$$\frac{n}{s} + \frac{n'}{s'} = \frac{n' - n}{r}$$

5

L.Seidel [L. Seidel. Astr.
Nachr., 43(1856), No.1027,289,
No.1028,305, No.1029,321.]
(Seidel' sums)



$$[P_1 \bar{Q}] = [P_1 O'_1]$$

$\bar{Q} \quad O'_1$

$$\Phi = [P_1 Q] - [P_1 O'_1]$$

$\bullet \quad x_0, y_0, 0 \quad P_0$

X, Y, Z

Q

$$X_0 X + Y_0 Y$$

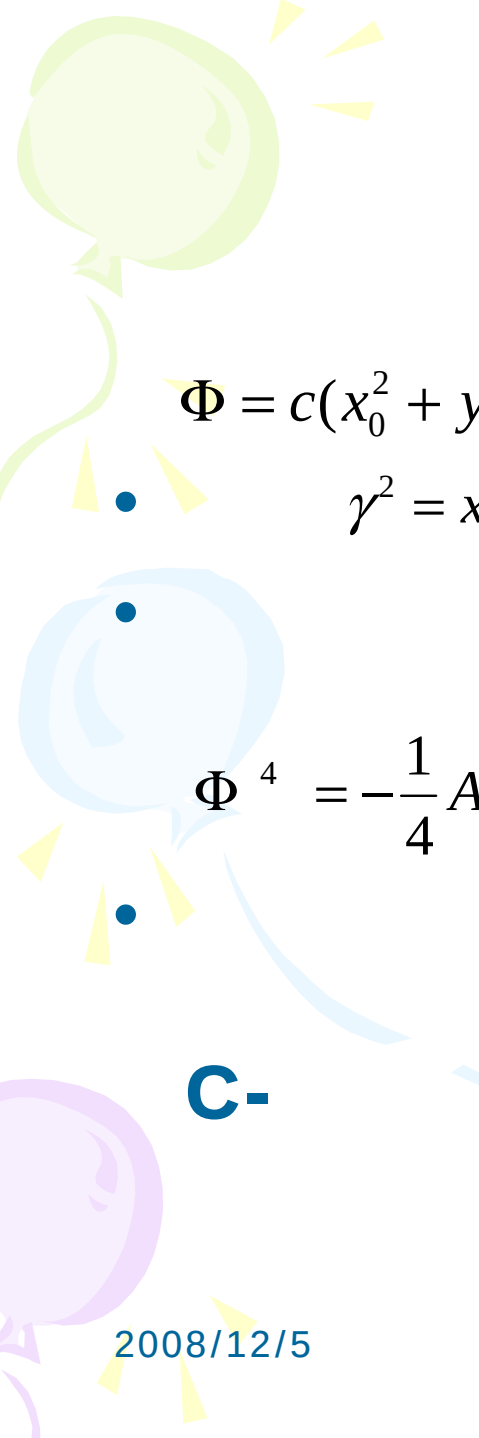
$$, \quad x_0^2 + y_0^2, \quad X^2 + Y^2$$

- (Max Born & Emil Wolf: << Principles of Optics >> (5th ed.) Pergamon Press, 1975.

2008/12/5 1978)

A-C TEM

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$$\Phi = c(x_0^2 + y_0^2) + \Phi^{(4)} + \Phi^{(6)} + \dots$$

$$\gamma^2 = x_0^2 + y_0^2 \quad , \quad \rho^2 = X^2 + Y^2 \quad , \quad \kappa^2 = x_0 X + y_0 Y$$

4

$$\Phi^4 = -\frac{1}{4}A\gamma^4 - \frac{1}{4}B\rho^4 - C\kappa^4 - \frac{1}{2}D\gamma^2\rho^2 + E\gamma^2\kappa^2 + F\rho^2\kappa^2 - \frac{1}{4}A\gamma^4$$

B-

C-

D-

E-

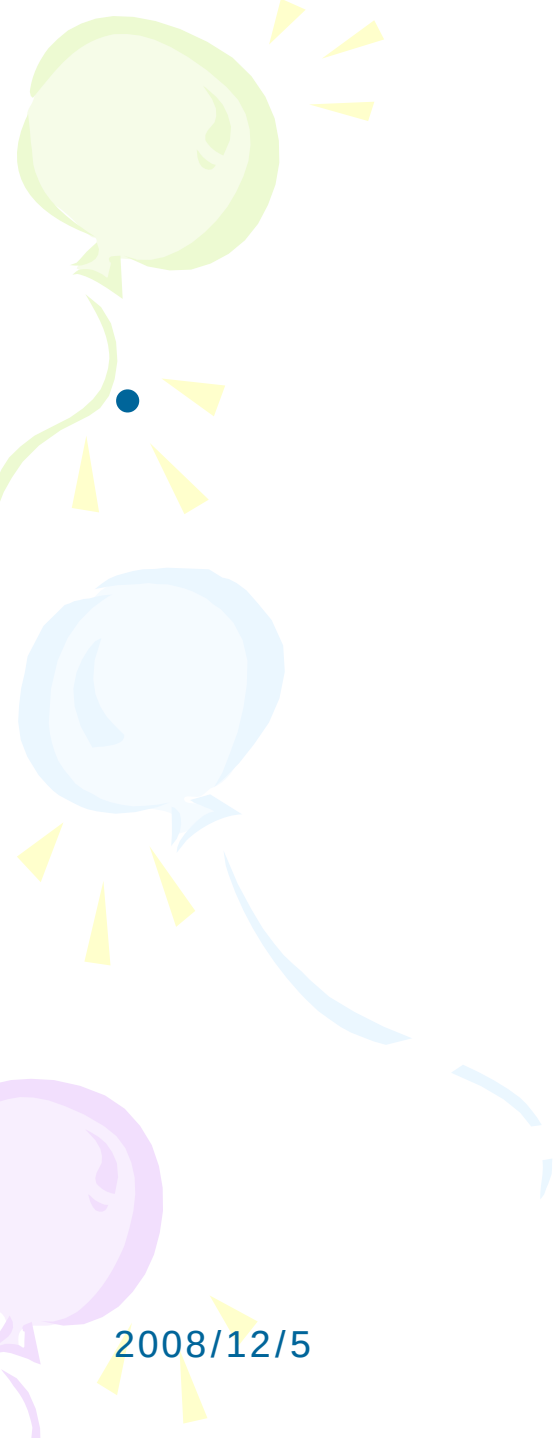
F-

, $\chi(\bar{r})$, $\chi(\bar{g})$, $\chi(\theta)$

$$\phi = c(x_0^2 + y_0^2) + \frac{1}{4}B\rho^4 \quad \rho^2 = X^2 + Y^2$$

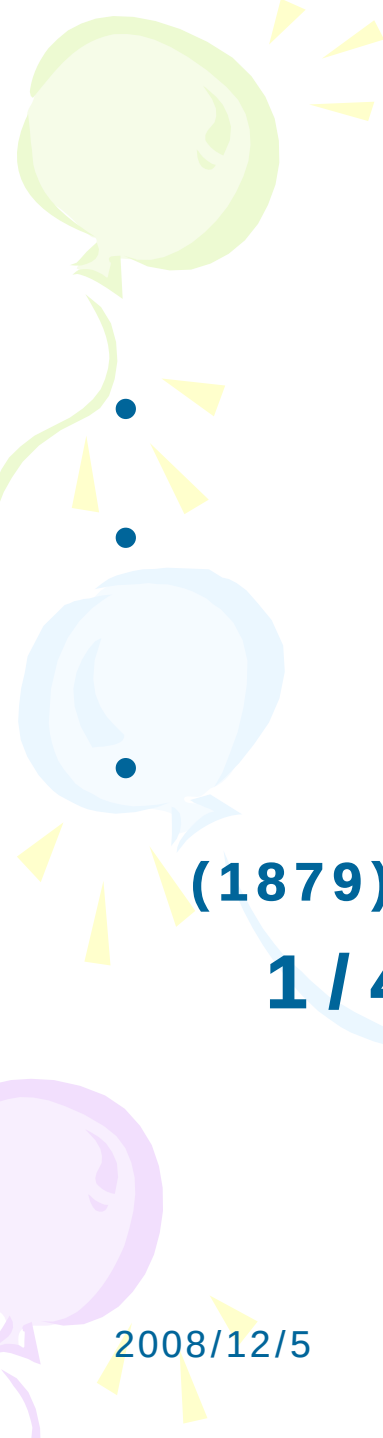
$$, \quad \chi(\bar{g}) = \frac{1}{2}\Delta f\lambda^2|\bar{g}|^2 + \frac{1}{4}C_s\lambda^4|\bar{g}|^4$$

$$, \quad \chi(\theta) = \frac{1}{2}\theta\tilde{\theta}C_1 + \frac{1}{4}(\theta\tilde{\theta})^2C_3$$



sin

- $C_1(\text{nm})$; $A_1(\text{nm})$; $A_2(\text{nm})$;
 $B_2 \text{ nm}$; $C_3, C_s(\text{ m})$;
- $A_3(\text{ m})$; $S_3(\text{ m})$;
 $A_4(\text{ m})$; $B_4(\text{ m})$; $D_4(\text{ m})$;
- $C_5(\text{mm})$; $A_5 \text{ mm}$;
 $R_5(\text{mm})$; $S_5(\text{mm})$; $A_6(\text{mm})$;
- $B_6 \text{ mm}$; $D_6(\text{mm})$;
 $F_6 \text{ mm}$; $C_7 \text{ mm}$



[Lord Rayleigh: Phil. Mag., (5)8

(1879), 463.]

1 / 4

20 %

1 / 4

1 / 4 100

nm

$$0.3 \text{ m} / 100 \text{ nm} = 3 \cdot 10^6$$

$$2.5 \text{ m} / 100 \text{ nm} = 2.5 \cdot 10^7$$

VG HB501 STEM

$$40 \text{ m} / 4 \text{ pm} = 10^7$$

$$40 \text{ m} / 1 \text{ pm} = 4 \cdot 10^7; \quad \text{STEM}$$

$$100 \text{ m}$$

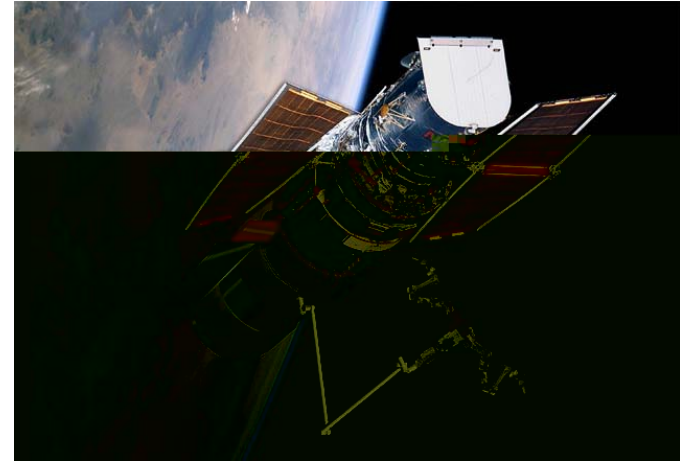
$$100 \text{ m} / 1 \text{ pm} = 1 \cdot 10^8$$

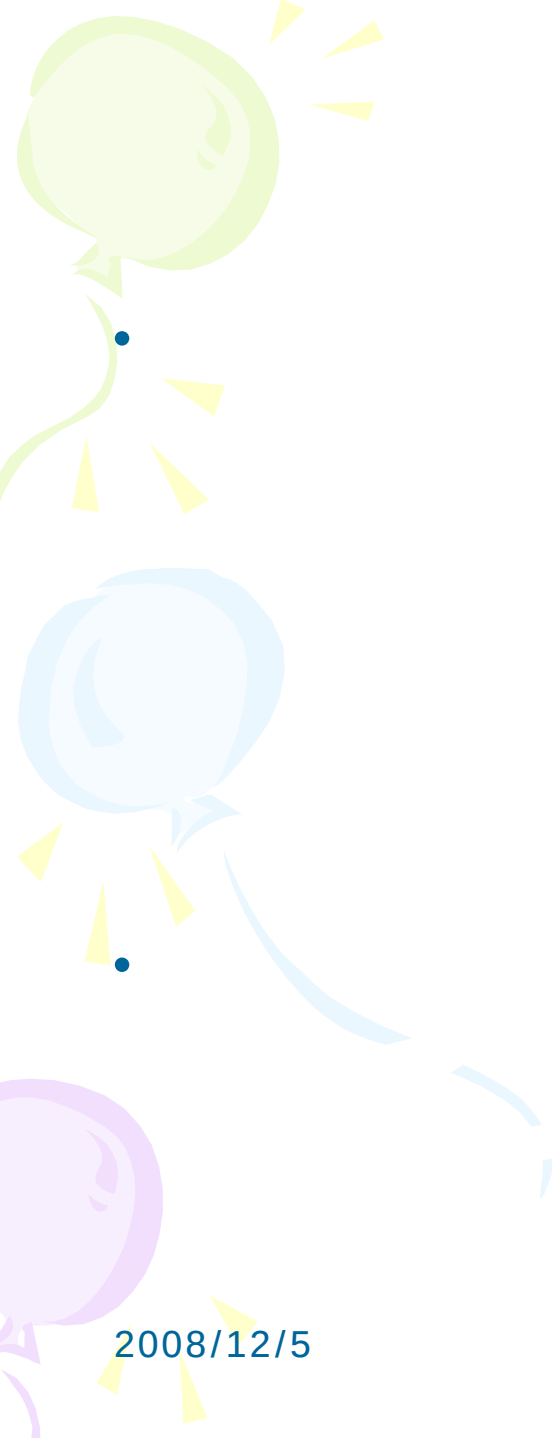
$$1.6 \cdot 10^{-4}$$

(O.L.Krivanek, P.D.Nellist,
N.Dellby, M.F.Murfitt, and
Z.Szilagyi: Ultramicroscopy 96

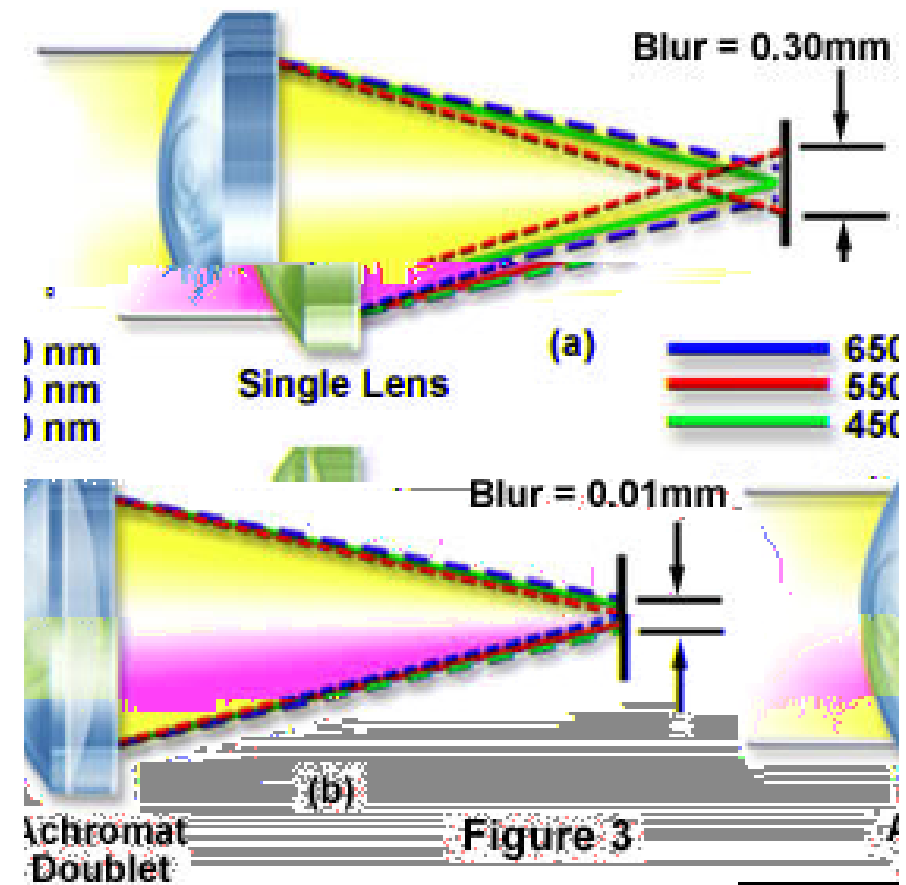
(2003) 229.)

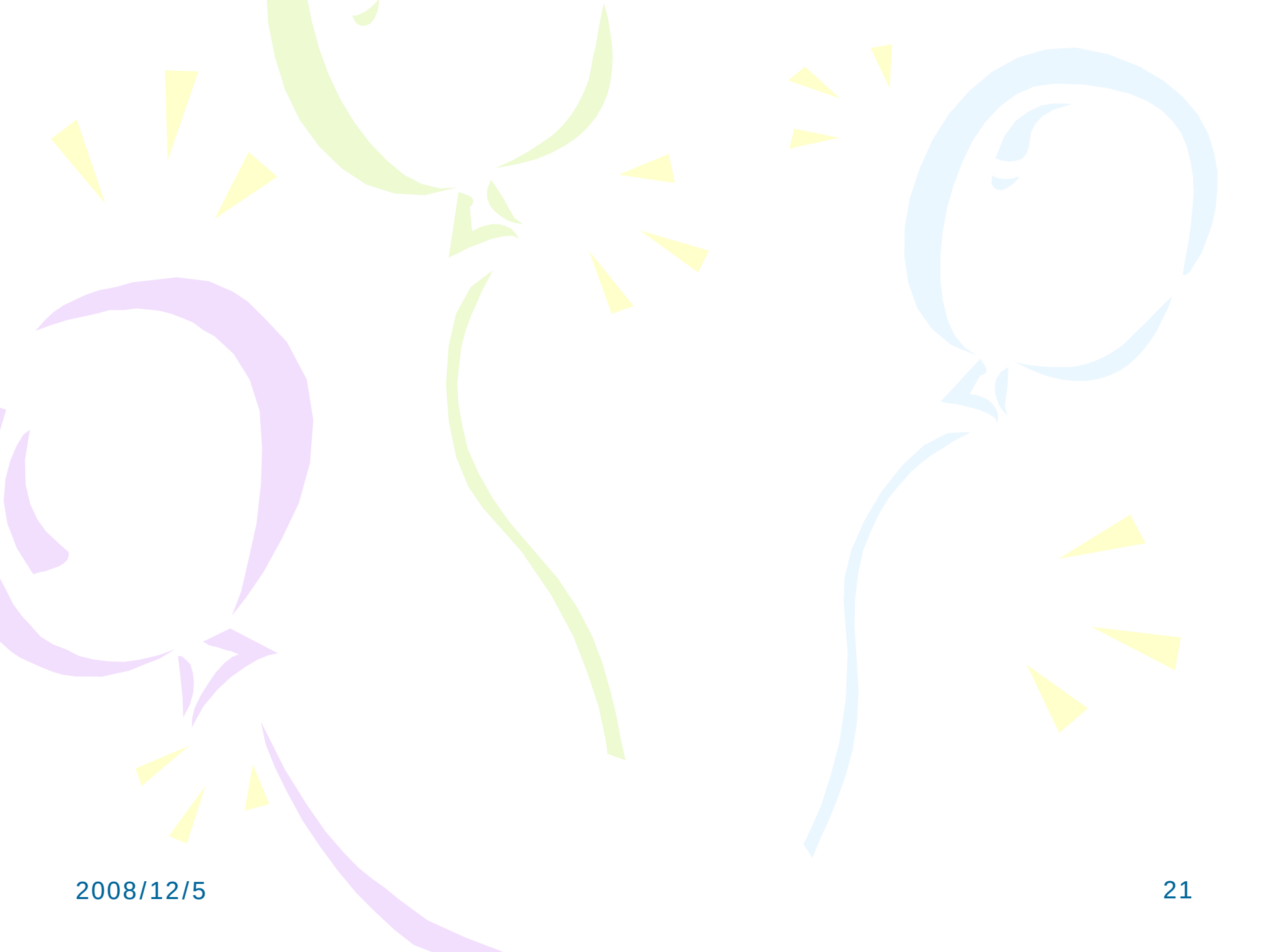
A-C TEM

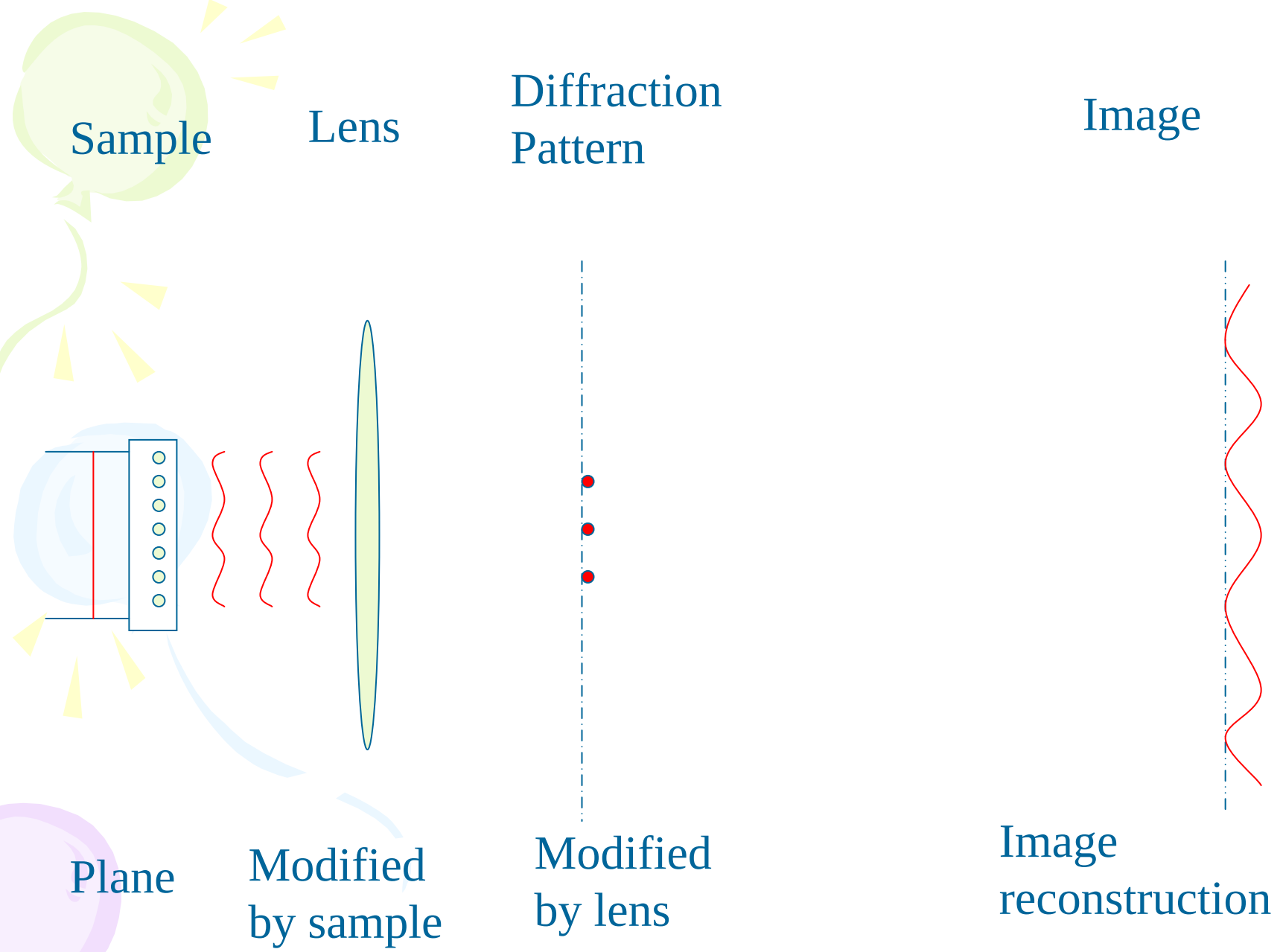


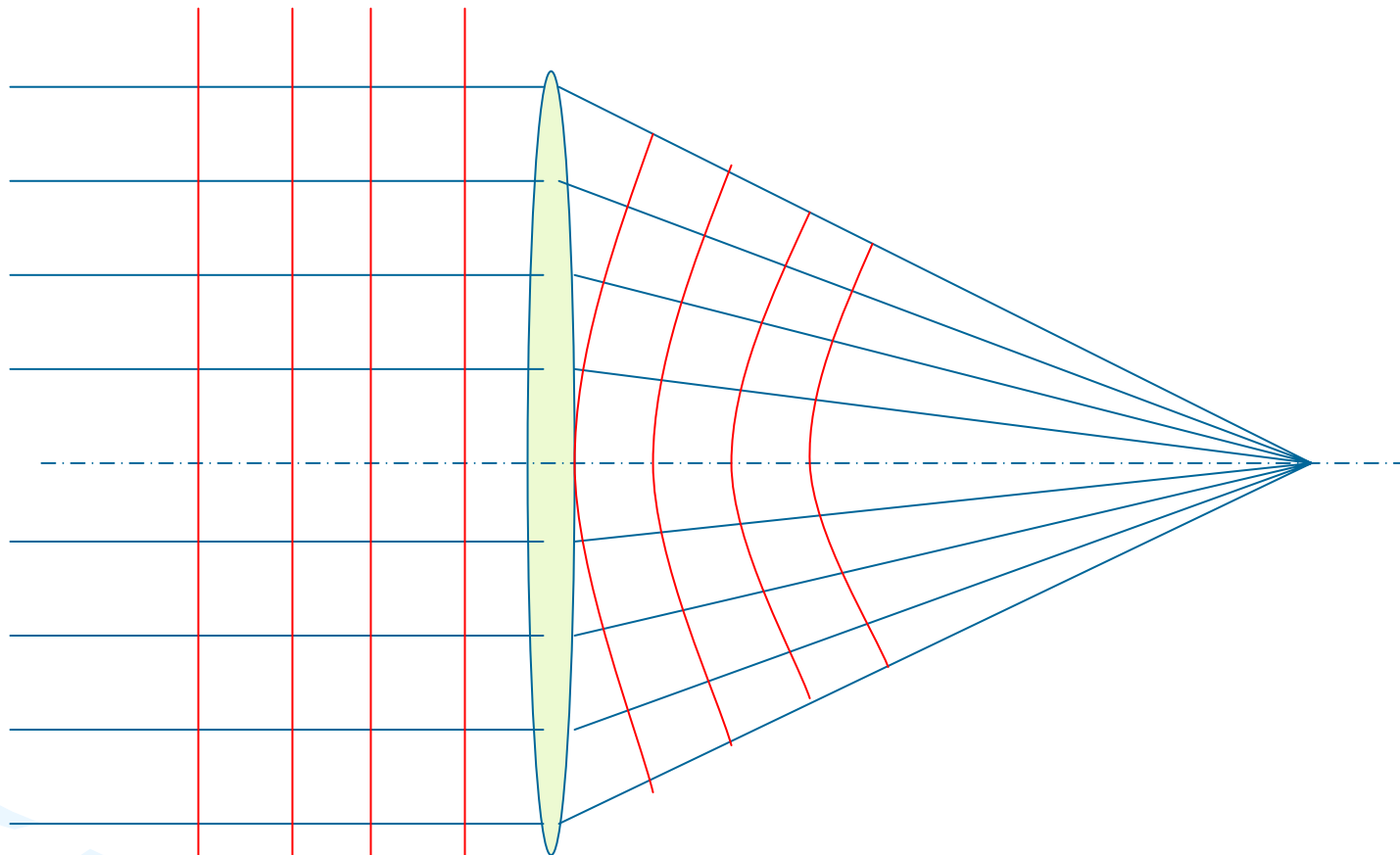


Axial Chromatic Aberration









O.Scherzer

(J.Appl. Phys. 20,20, 1949)

$$\chi = \pi [0.5 C_s \lambda^3 (u^2 + v^2)^2 + \Delta f \lambda (u^2 + v^2)]$$

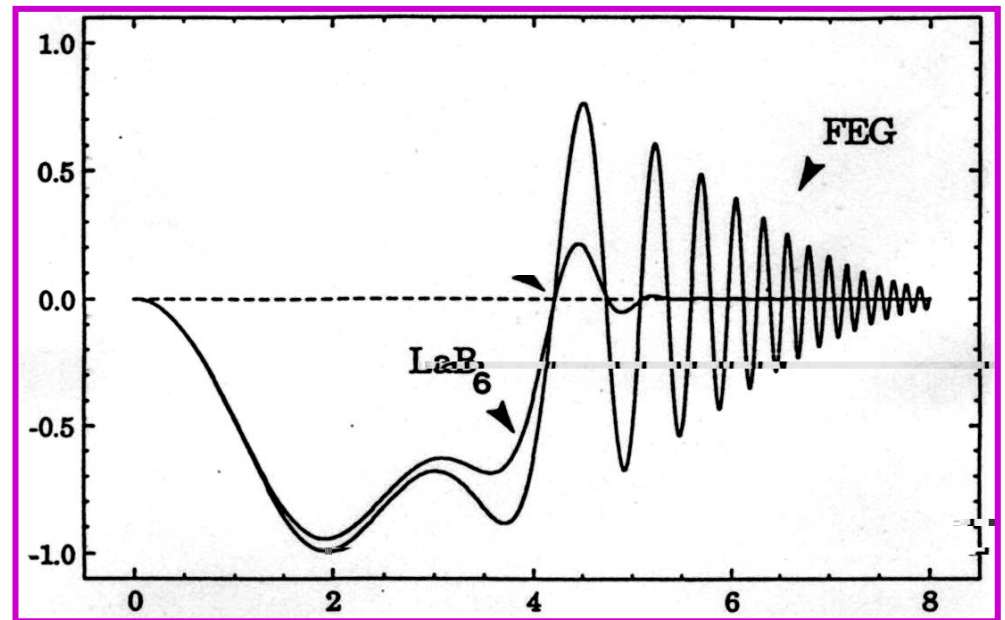
- C_s —

- λ —

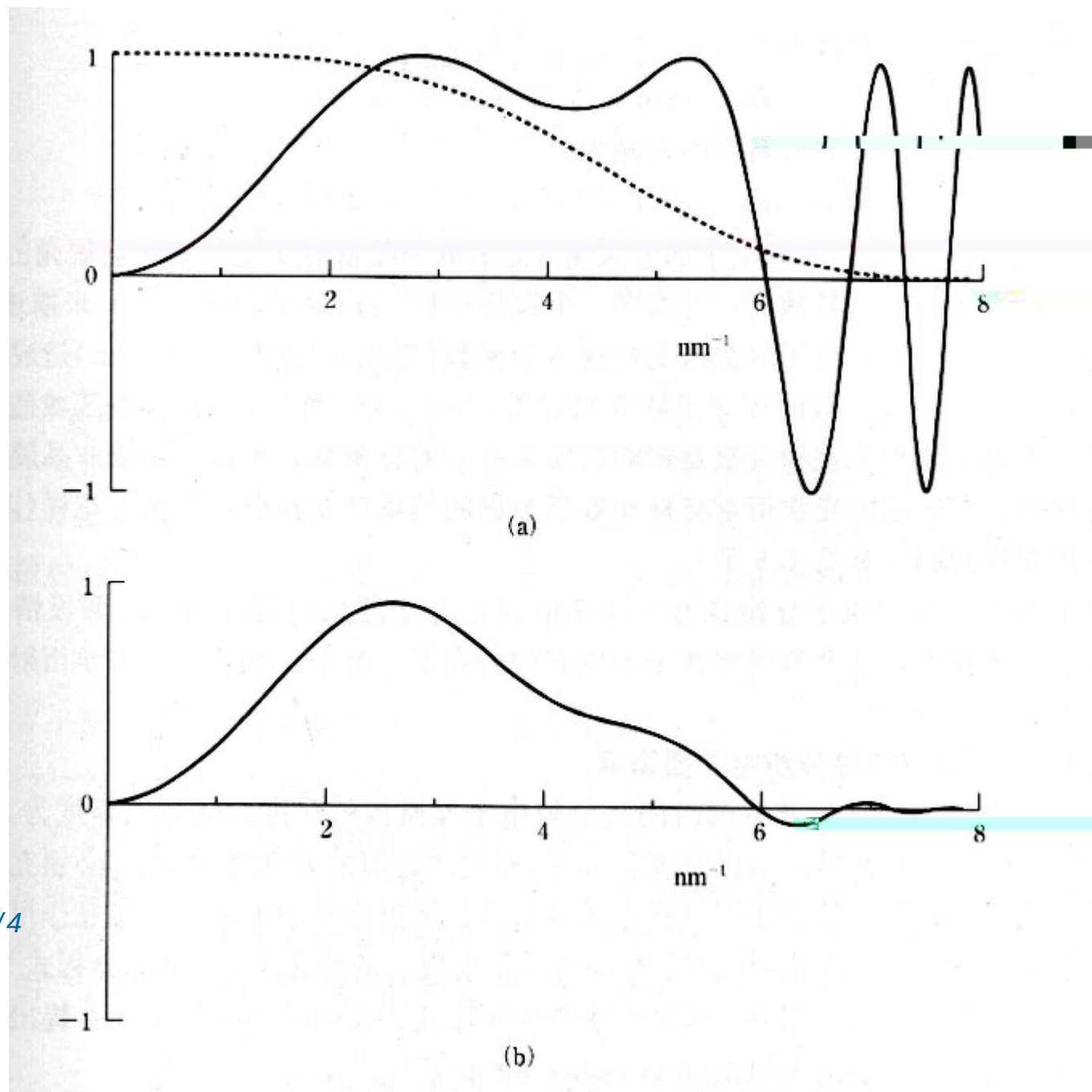
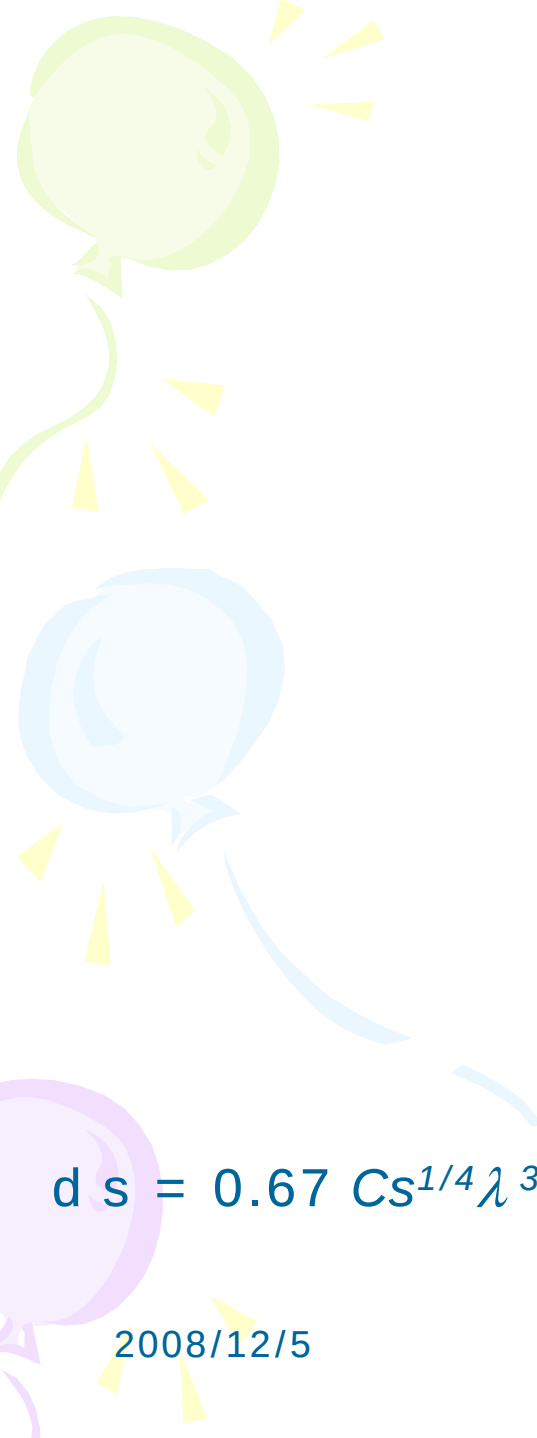
- Δ —

-

$$I(g) \sim |A(g)|^2 |E(g)|^2 |\sin \chi(g)|^2 |Q_p(g)|^2$$



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$$d s = 0.67 C s^{1/4} \lambda^{3/4}$$

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A₂

$$\chi(\mathbf{u}) = \pi e \lambda |\mathbf{u}|^2 + \pi C_S \lambda^3 |\mathbf{u}|^4 / 2$$

Limits from three-fold astigmatism $|A_2|^a$

$ A_2 $ (μm)	χ at 2 Å	χ at 1 Å	$d_{\pi/4}$ (Å)
2.25	0.73π	5.81π	2.85
1.0	0.33π	2.58π	2.18
0.5	0.16π	1.29π	1.73
0.2	0.065π	0.52π	1.27
0.1	0.033π	0.26π	1.01
0.05	0.016π	0.13π	0.80
0.03	0.010π	0.08π	0.68

^aContribution to lens phase change $\chi(\mathbf{u})$ from three-fold astigmatism $|A_2|$ at spacings of 2 and 1 Å, and the spacing $d_{\pi/4}$ at which phase change from three-fold astigmatism reaches $\pi/4$ at 300 keV. Uncorrected value of $|A_2|$ for the NCEM CM300FEG/UT is 2.25 μm. Measurements of corrected values of $|A_2|$ gave means of 0.05 and 0.03 μm.

[110]

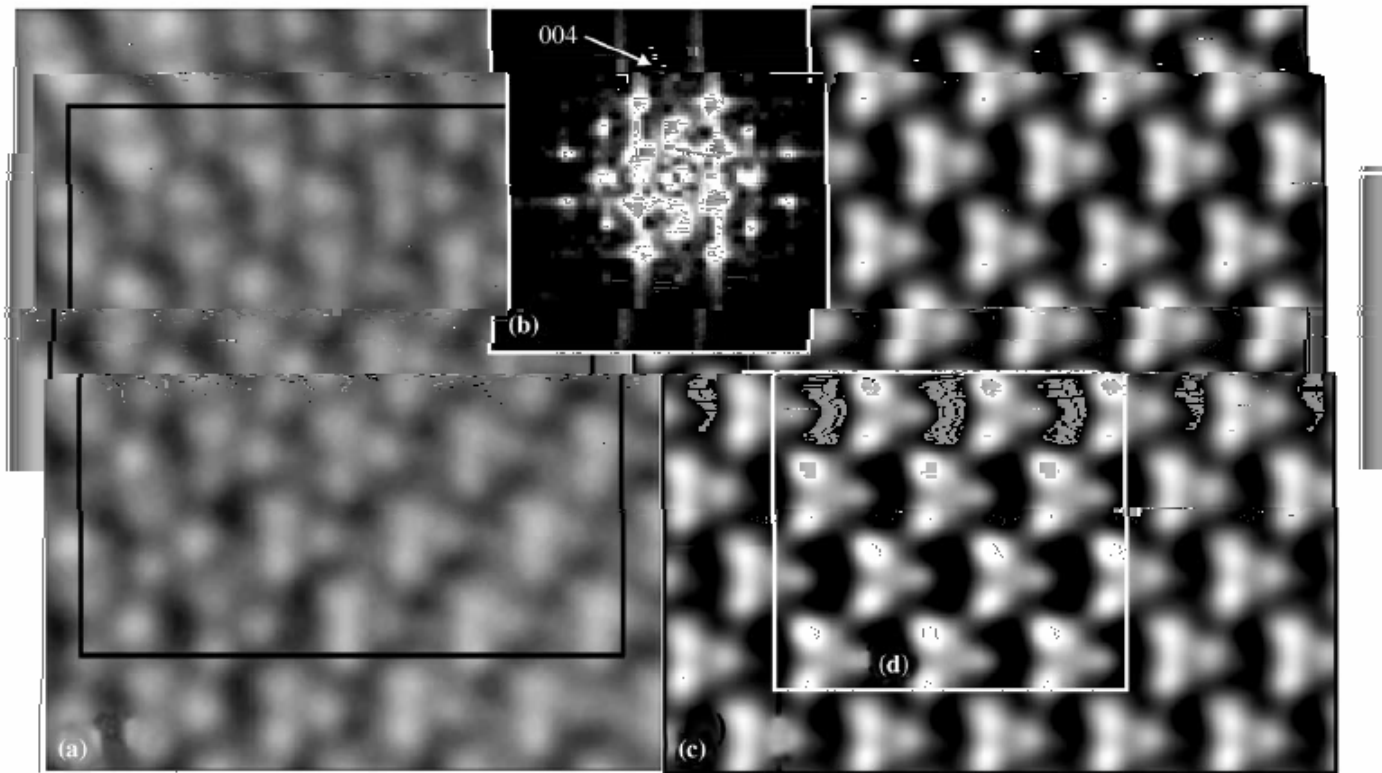


Fig. 8. (a) Experimental OAM image of CVD diamond before correction of three-fold astigmatism. (b) Diffraction pattern shows specimen in orientation is $[110]$, with strong 111 and 113 spots, weak 220 and 331 spots, and very weak 004's (arrowed). (c) Averaging (p1) shows white spots separated by approximately $|a|_{\text{diamond}}/4$, but with extra spots producing triangular white clusters. (d) Image simulated from diamond $[110]$ match best at $|A_2| = 2.25 \mu\text{m}$.

A₂

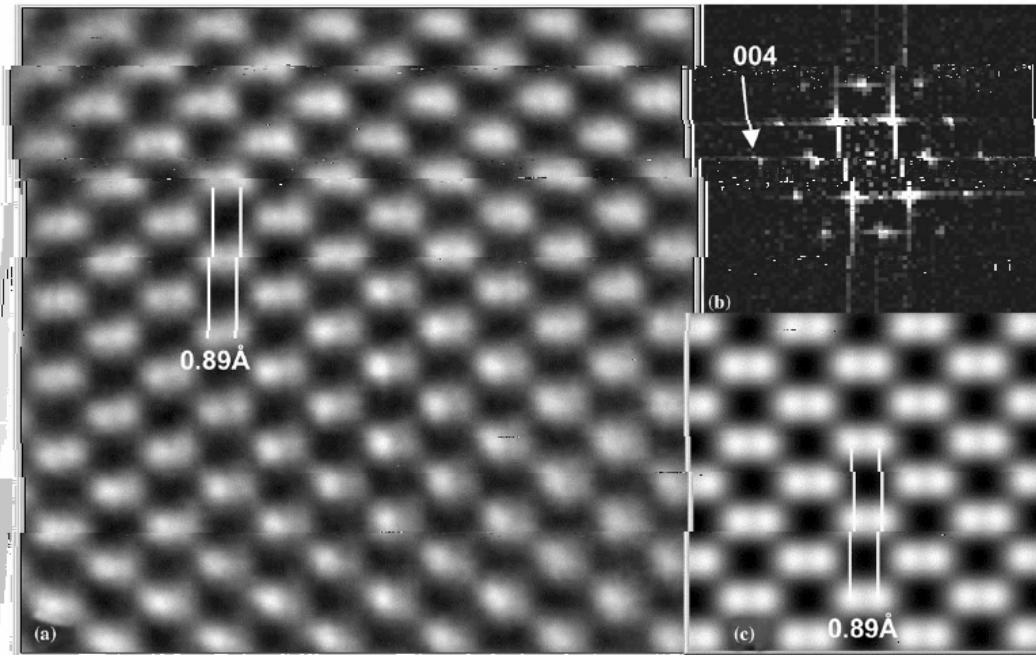


Fig. 10. (a) Experimental OAM image of CVD diamond in [110] orientation after correction of three-fold astigmatism to below 0.05 μm. (b) Experimental OAM image of CVD diamond in [110] orientation after correction of three-fold astigmatism to below 0.05 μm. (c) Experimental OAM image of CVD diamond in [110] orientation after correction of three-fold astigmatism to below 0.05 μm.

M.A. O'Keefe et al., Ultramicroscopy 89 (2001) 215–241

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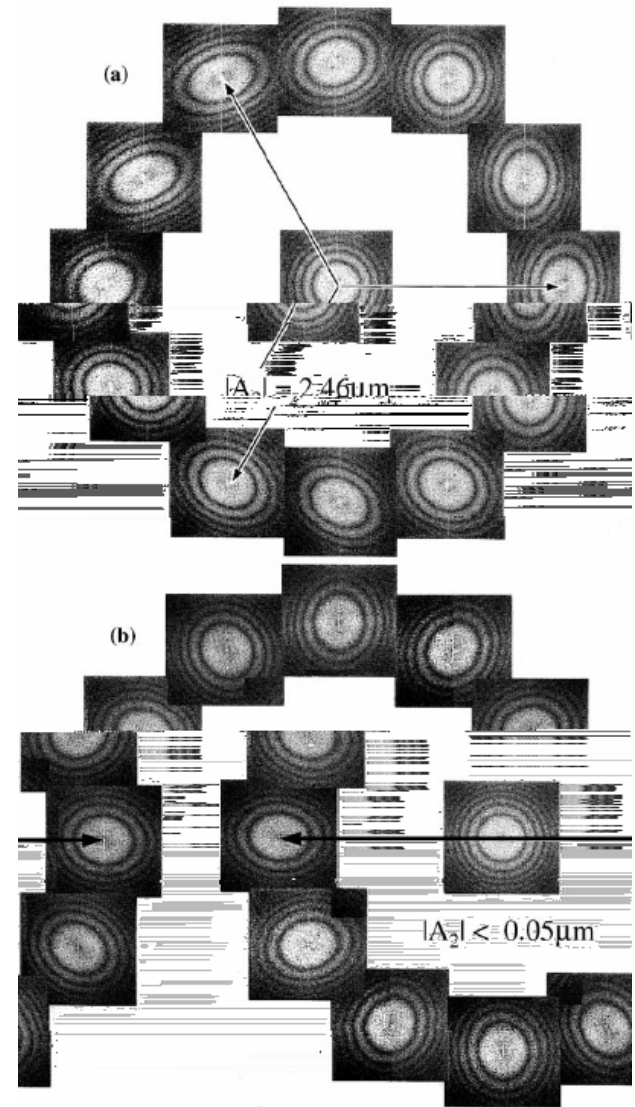


Fig. 9. OAM "clock" amorphous carbon sp measured at $|A_2| = 2$ three-fold character (ϵ 0.05 μm shows all ellipses pointing to the tilt origin).

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$$d_{A_2} = 1/|\mathbf{u}|_{A_2} = (8A_2\lambda^2/3)^{1/3}$$

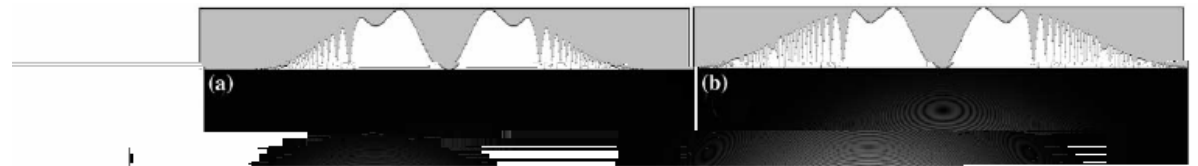
$$A_2 = 3/8u^3\lambda^2$$

List of the upper limits with respect to the $\pi/4$ criterion of all axial aberrations considering only one particular aberration coefficient

Aberration	80 kV	120 kV	200 kV		300 kV
	80 pm	65 pm	100 pm	50 pm	50 pm
Focus C_1 (nm)	0.40	0.31	1.0	0.25	0.4
Two-fold astigmatism A_1 (nm)	0.40	0.31	1.0	0.25	0.4
Three-fold astigmatism A_2 (nm)	11.50	9.2	60.0	7.5	13
Second-order coma B_2 (nm)	3.80	3.1	20.0	2.5	5.0
Third-order spherical aberr. C_3 (μm)	0.30	0.24	3.2	0.2	0.5

M. Haider, H. Muller, S. Uhlemann, J. Zach, U. Loebau, R. Hoeschen: Ultramicroscopy 108 (2008) 167–178

$$I(g) \sim |A(g)|^2 |E(g)|^2 |\sin \chi(g)|^2 |Q_p(g)|^2$$



sin

M.A. O'Keefe et al., Ultramicroscopy 89 (2001) 215–241

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球差系数 C_s 的测定,迄今为止已有几种方法。Kriv- 关于:
出的方法被公认是一种简单而巧妙的测试方法。它 anek^[3] 提

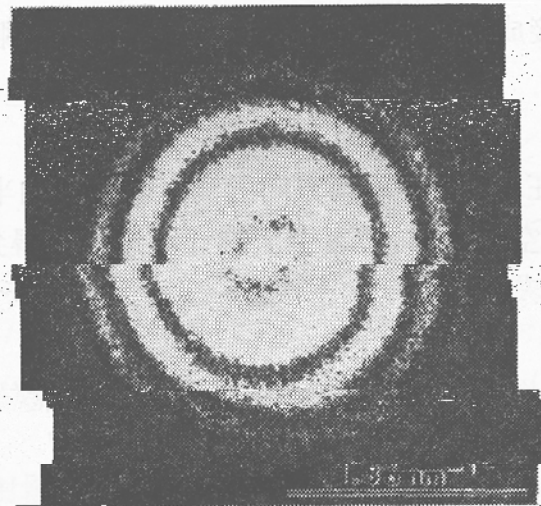


图 6.2 无定形碳膜电子显微象的光学衍射图

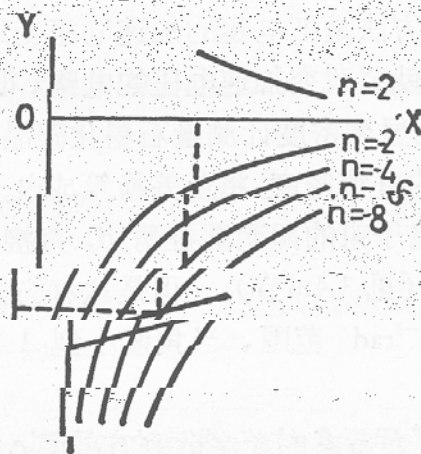


图 6.3 由图 6.2 求解 C_s 及 Δf

如果设 $u^2 = X$, 上式可写成联立方程形式

$$\begin{cases} Y = (C_s \lambda^3) X + 2\Delta f \lambda \\ Y = n/X \end{cases} \quad (6.10)$$

$$Y = n/X \quad (6.11)$$

由 X 的一次式和双曲线的交点能求出暗环的空间频率

反之,从图 6.2 的光学衍射图求得明暗环的空间频率,画在图 6.3 上,连接成直线,则直线的斜率是 $C_s\lambda^3$, 截距为 $2\Delta f\lambda$. 即

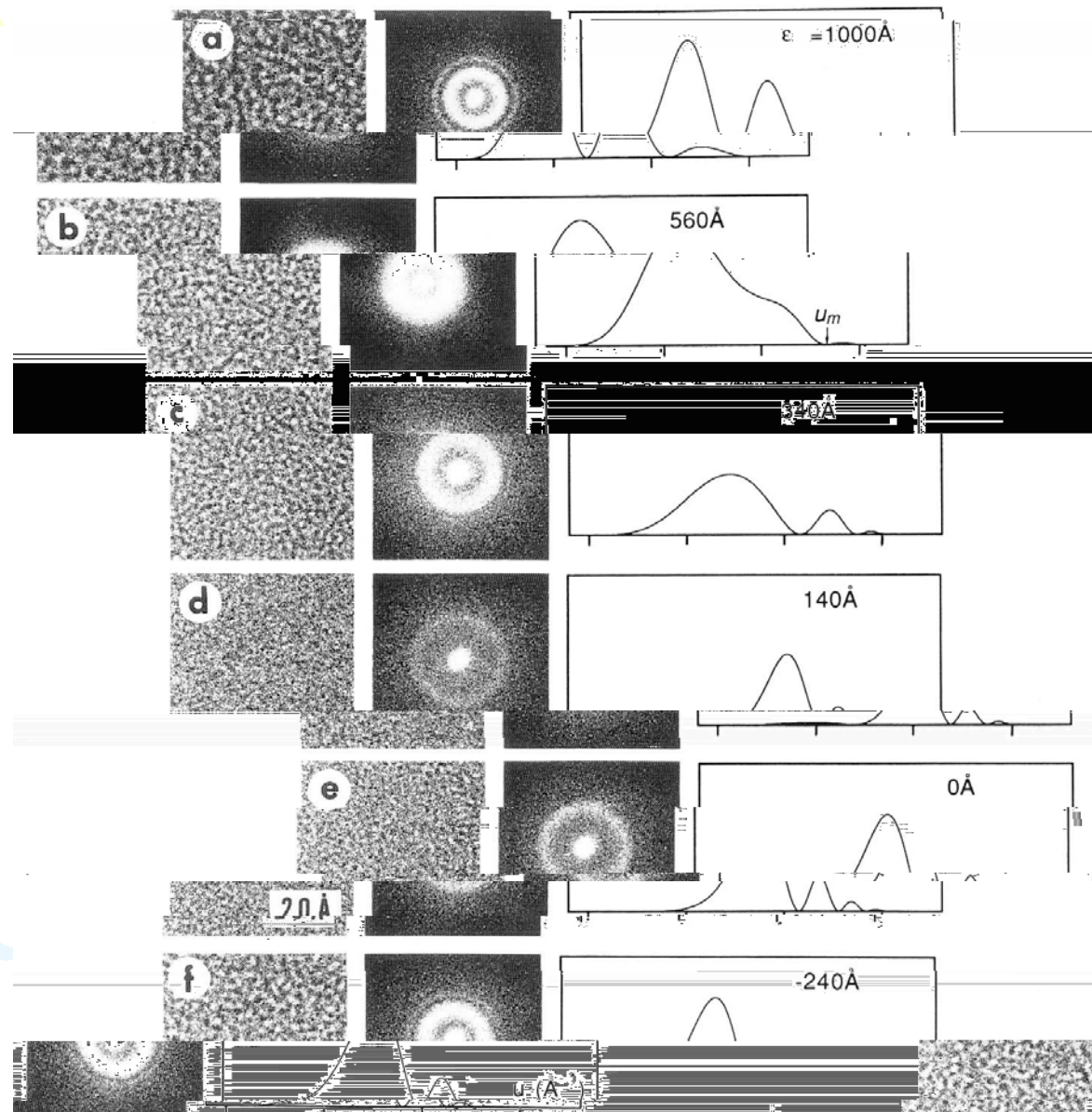
$$C_s = \text{斜率} / \lambda^3 \quad (6.12)$$

$$\Delta f = \text{截距} / 2\lambda \quad (6.13)$$

了准确,在图 6.2 的不同方向上测量明暗环的半径,并换算为对应的空间频率,重复上面的计算过程,得到一系列 C_s 和 Δf , 再求它们的算术平均值,就得到我们要测定的 C_s 和 Δf .

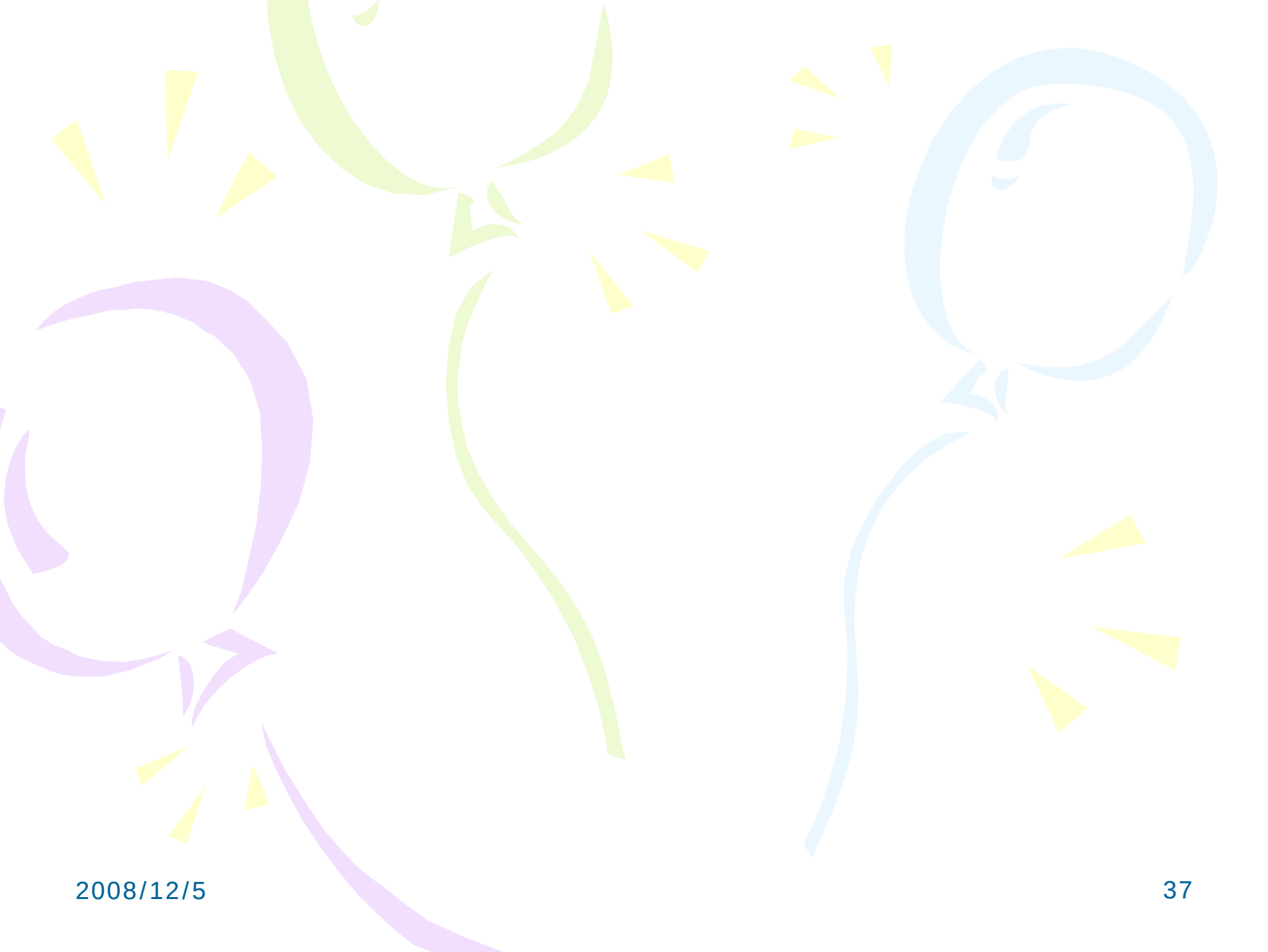
从一张图各方向的 Δf 值中,取椭圆长轴与短轴方向的 Δf 值,可以得到象散量

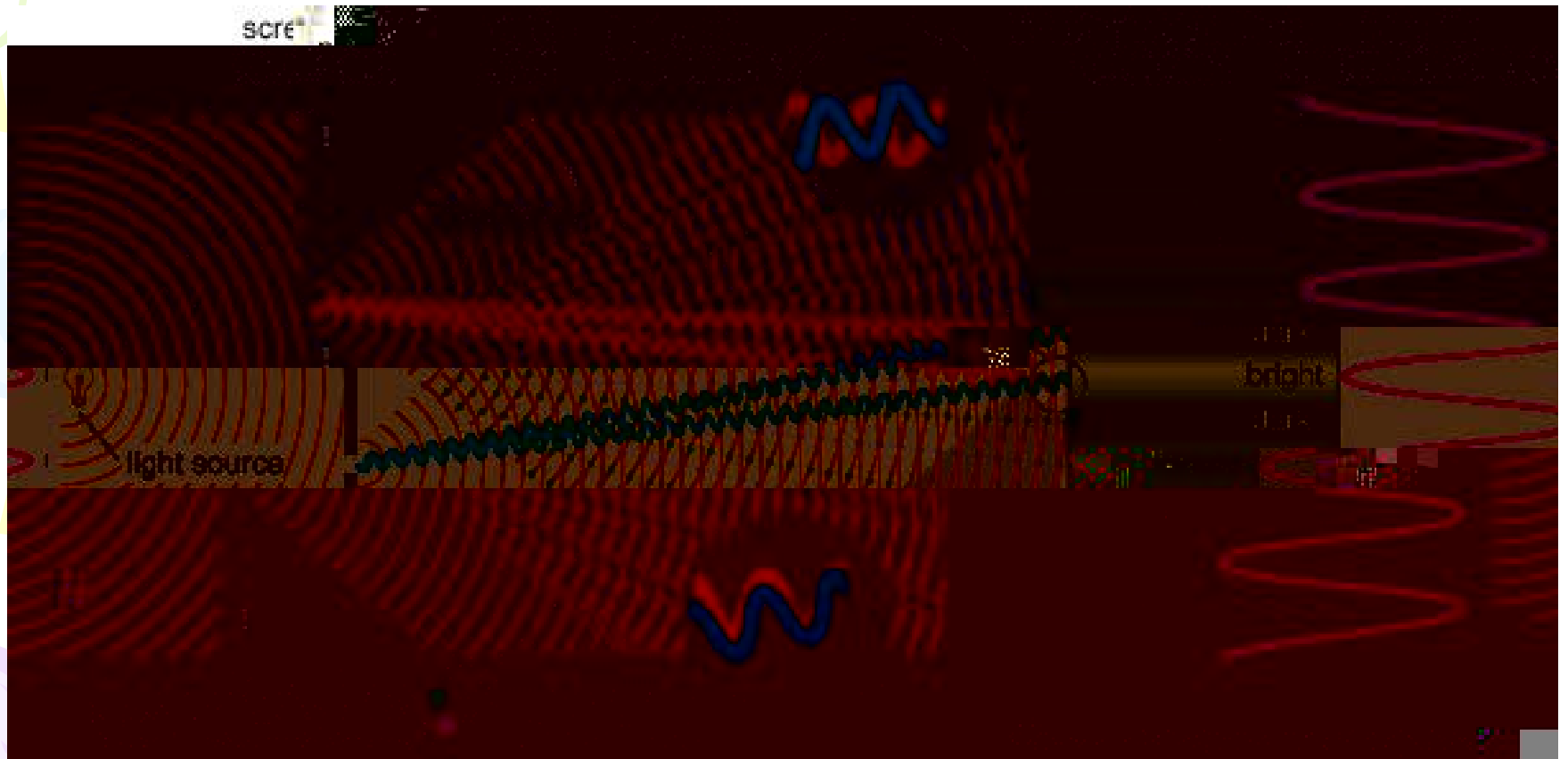
$$(6.14) \quad C_a = |\Delta f_{\parallel} - \Delta f_{\perp}|$$



S.Horiuchi:<<
Fundamentals
of HRTEM>>,
North-Holland,
1994, p.223

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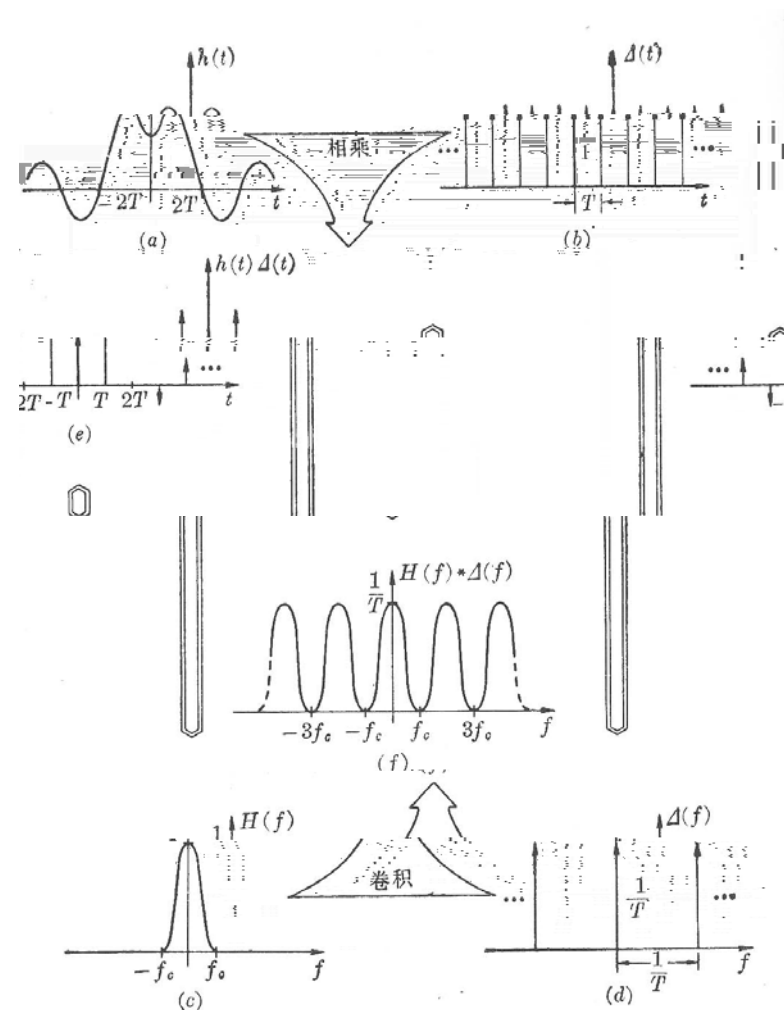
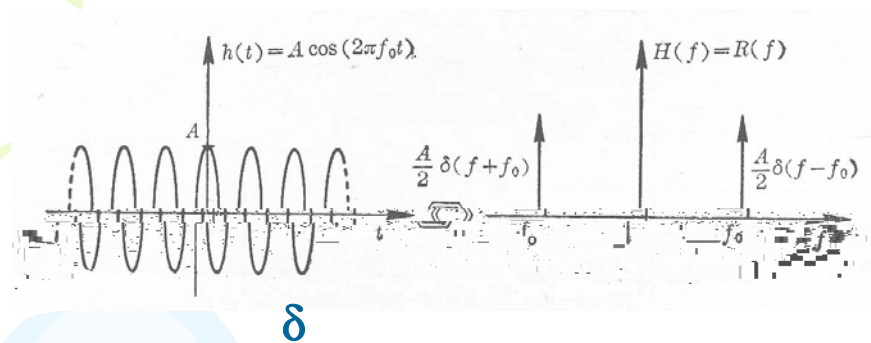


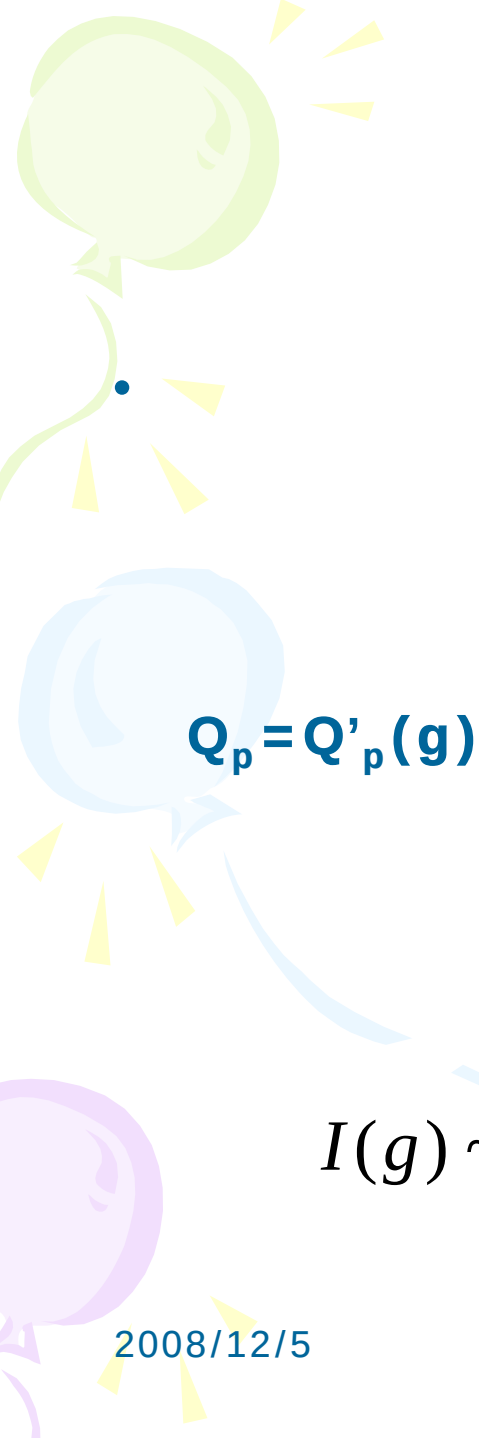


E.O.Brigham: The fast Fourier transform

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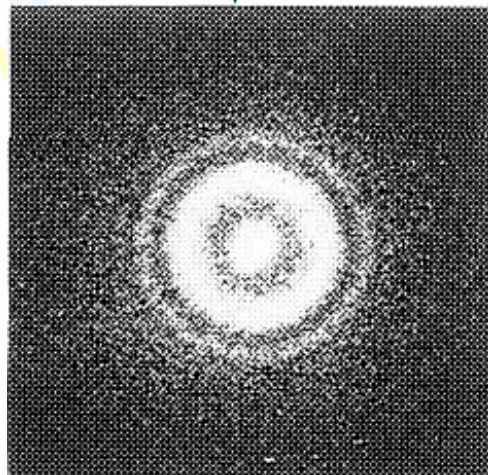
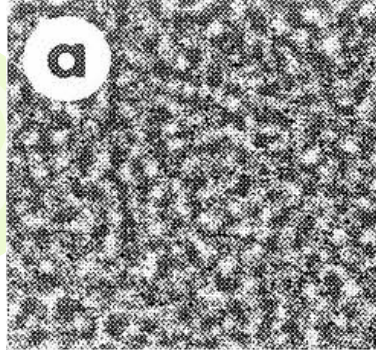




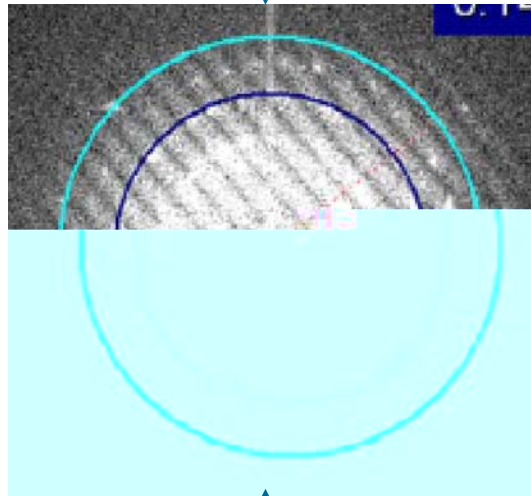
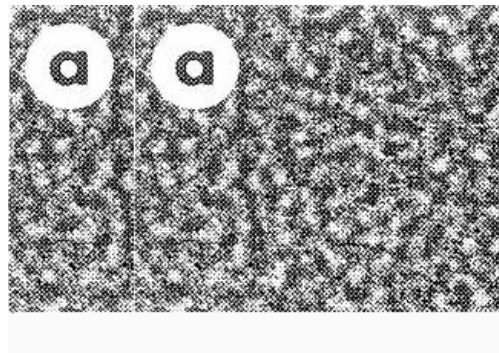
$$Q_p = Q'_p(g) Y(g)$$

$$A \quad E \quad \sin \chi$$

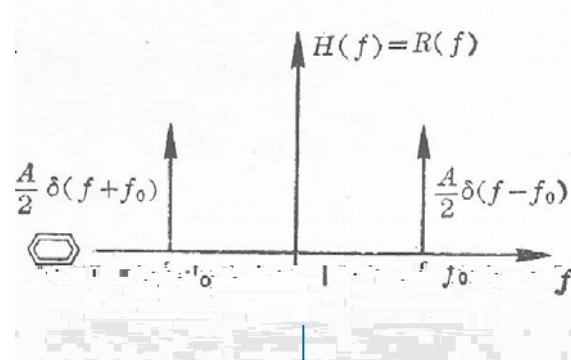
$$I(g) \sim |A(g)|^2 |E(g)|^2 |\sin \chi(g)|^2 |Q_p(g)|^2$$



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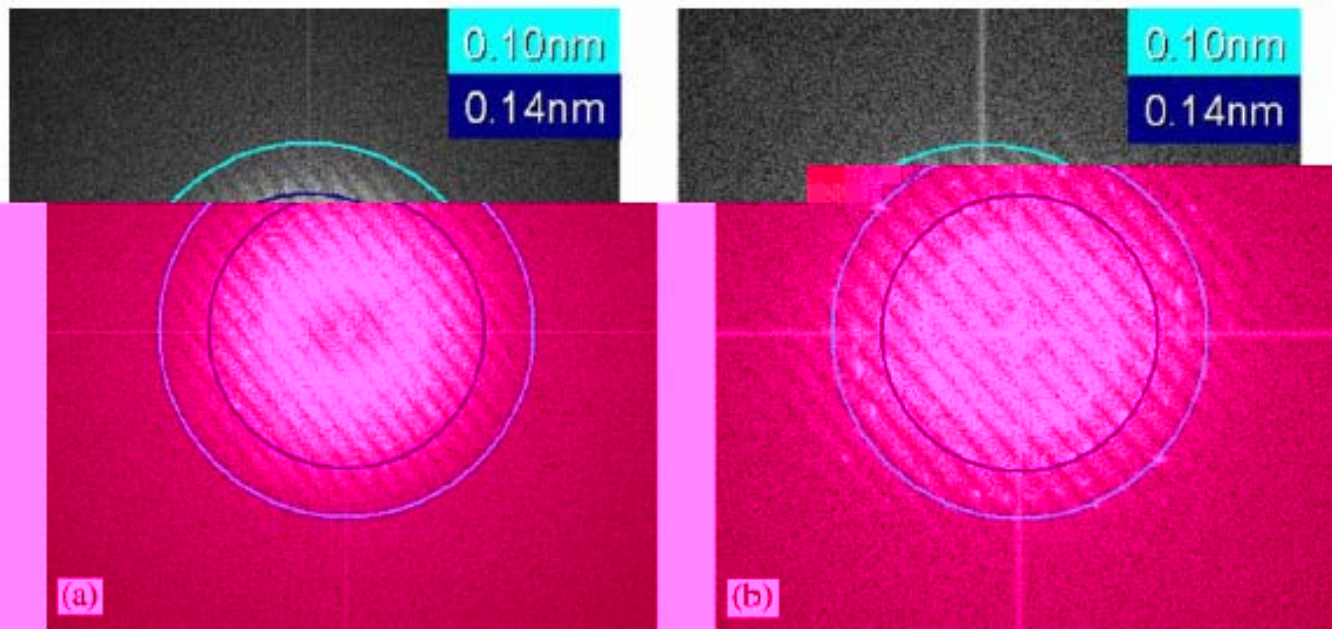
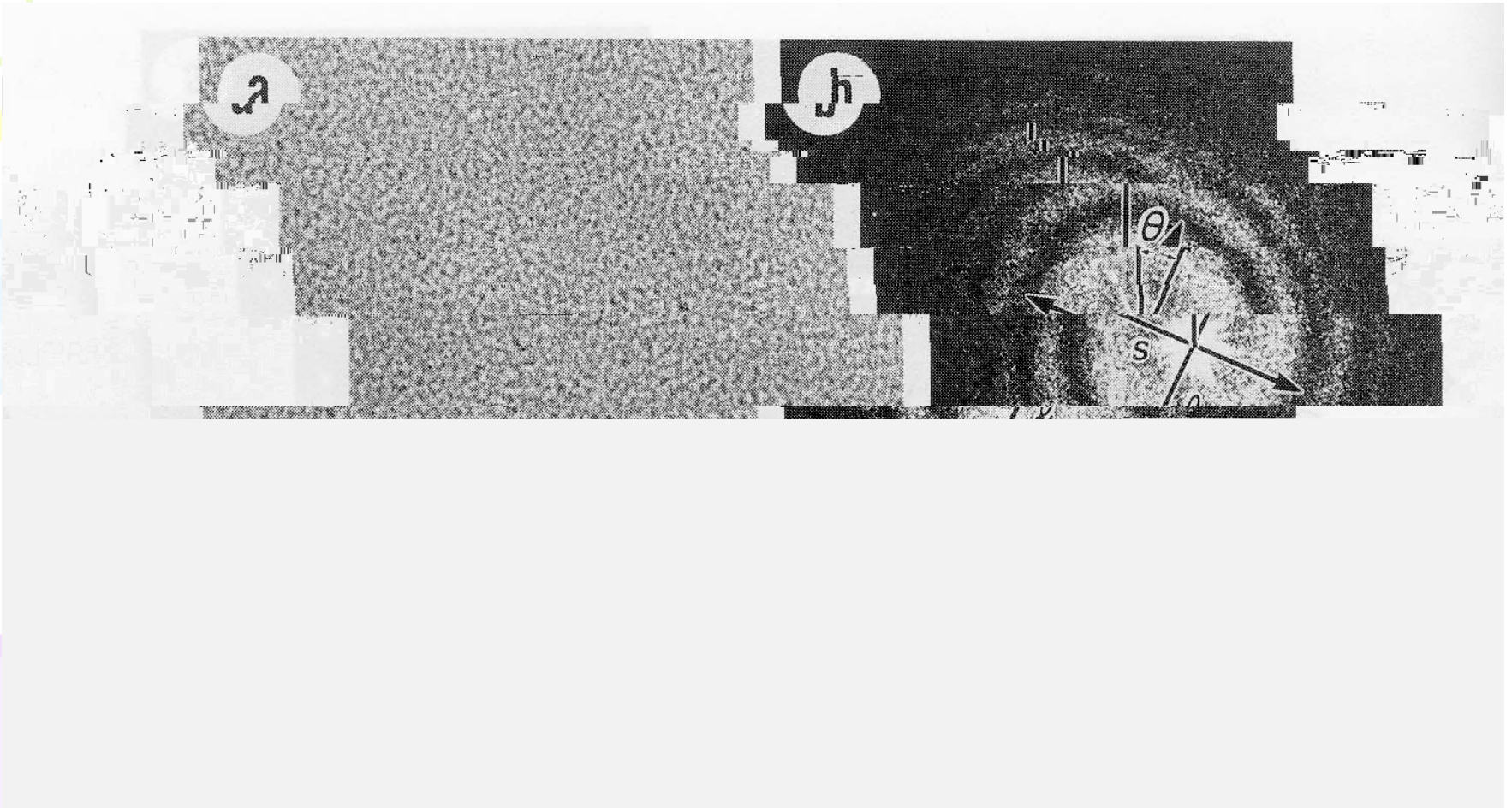
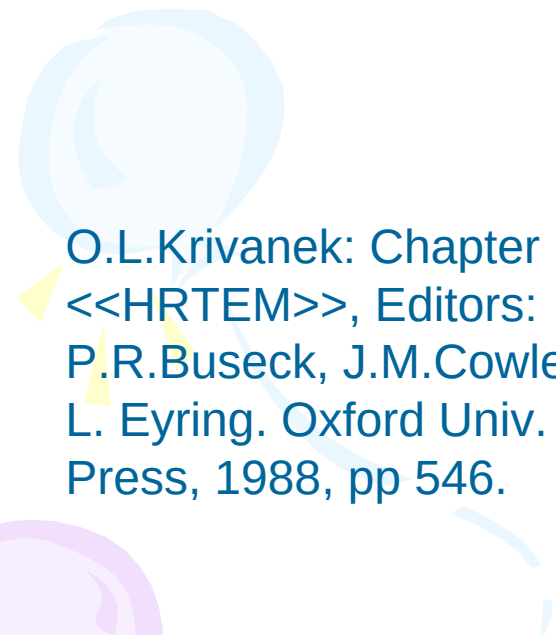


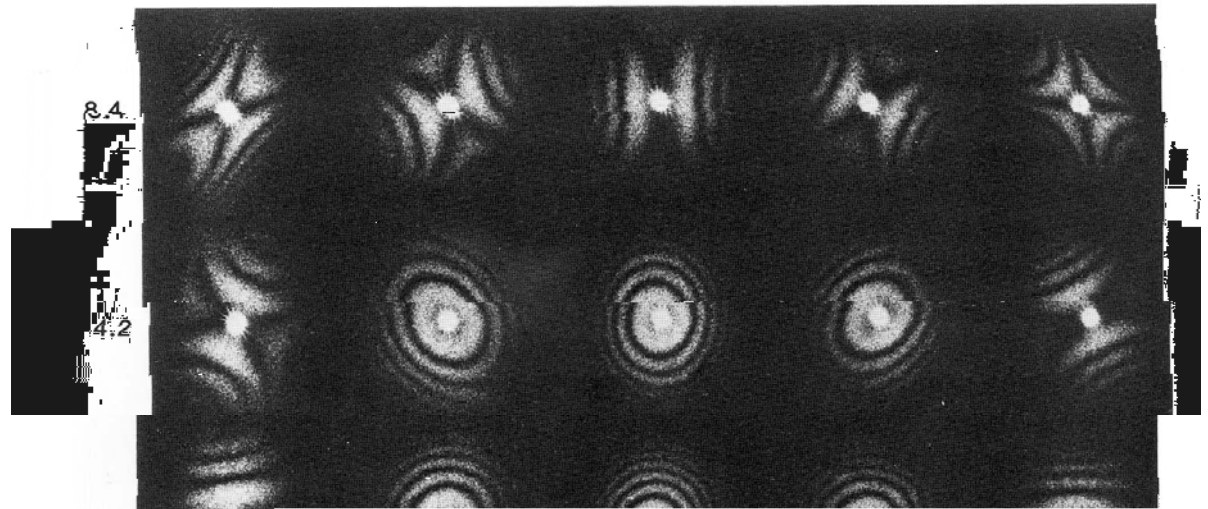
Fig. 2. Two Young fringe images of an amorphous tungsten film, showing the improvement of information limit obtained by the monochromator: (a) monochromator off ($\Delta E = 0.55$ eV) and Cs corrector on ($C_s = 3$ mm), (b) monochromator on ($\Delta E = 0.15$ eV) and Cs corrector on ($C_s = 3$ mm). The dots in the right image are surface reflections from small gold particles in the tungsten film used for calibration. The light blue circle shows the 0.10 nm frequency. The dark blue circle shows the 0.14 nm frequency. The Young fringes show that, without monochromator, the information limit is a little worse than 0.1 nm. With monochromator, the information limit is well below 0.1 nm. The images were taken with 0.3 nA beam current on the CCD, 1 s exposure time, and 0.2 mrad half convergence angle (a) or 2 mrad half convergence angle (b).

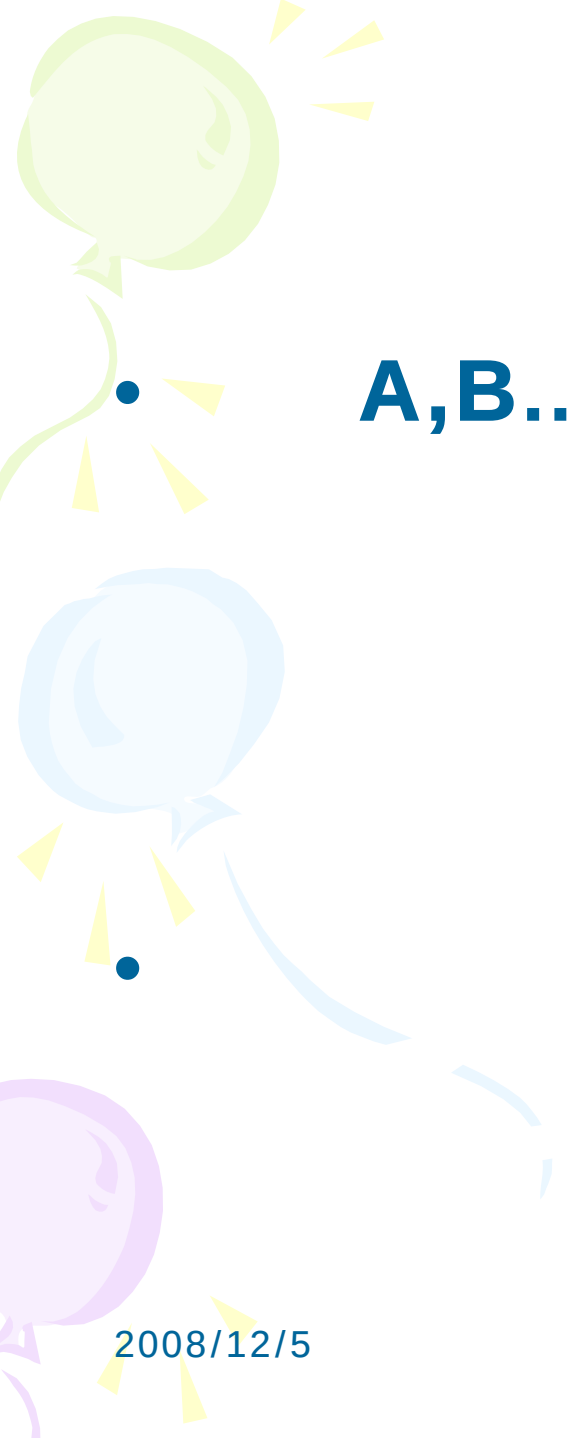


2008/12/16 S. Horiuchi: <<Fundamentals of HRTEM>> North-Holland, 1994, p.224.



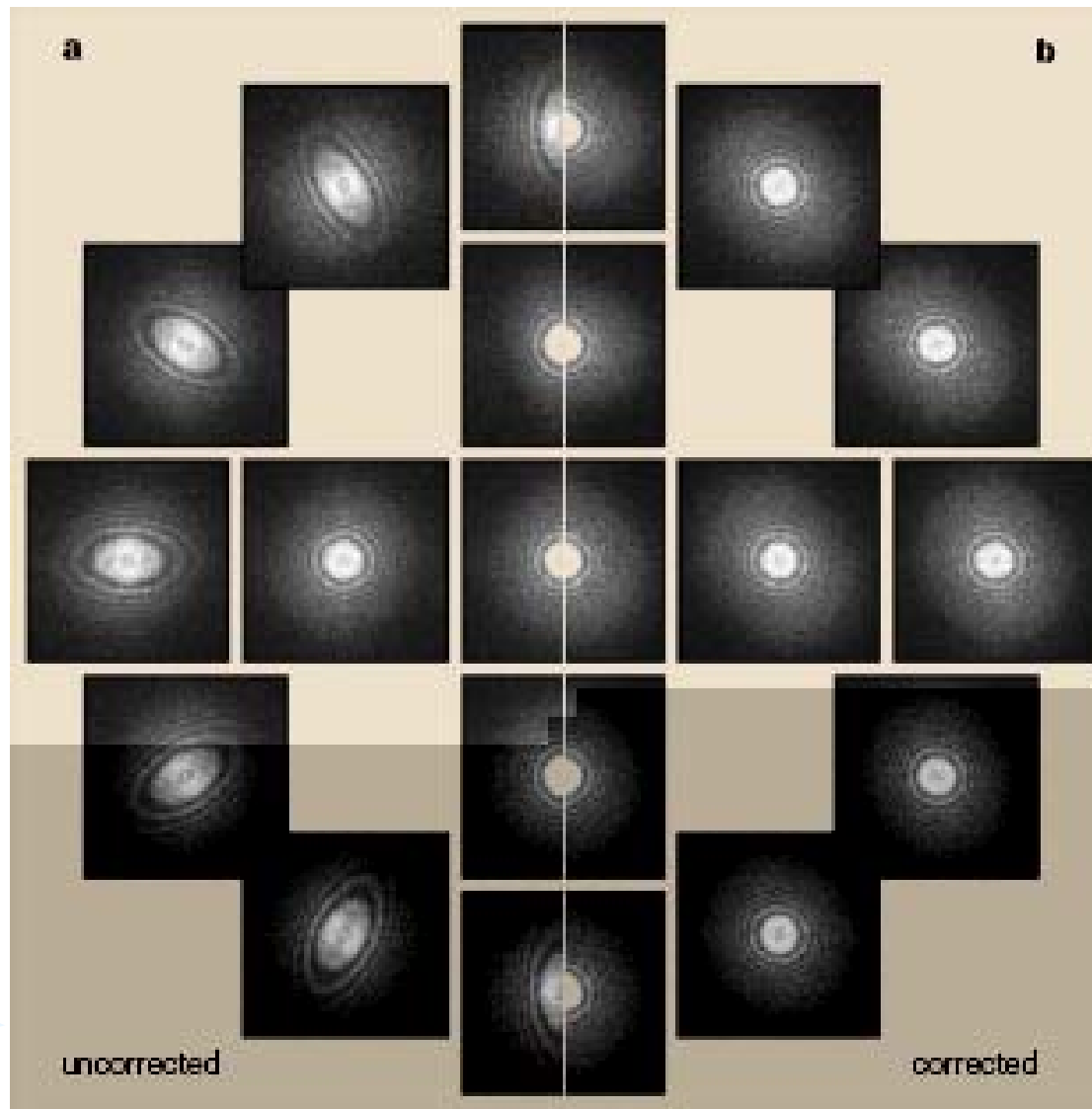
O.L.Krivanek: Chapter 12
<<HRTEM>>, Editors:
P.R.Buseck, J.M.Cowley,
L. Eyring. Oxford Univ.
Press, 1988, pp 546.





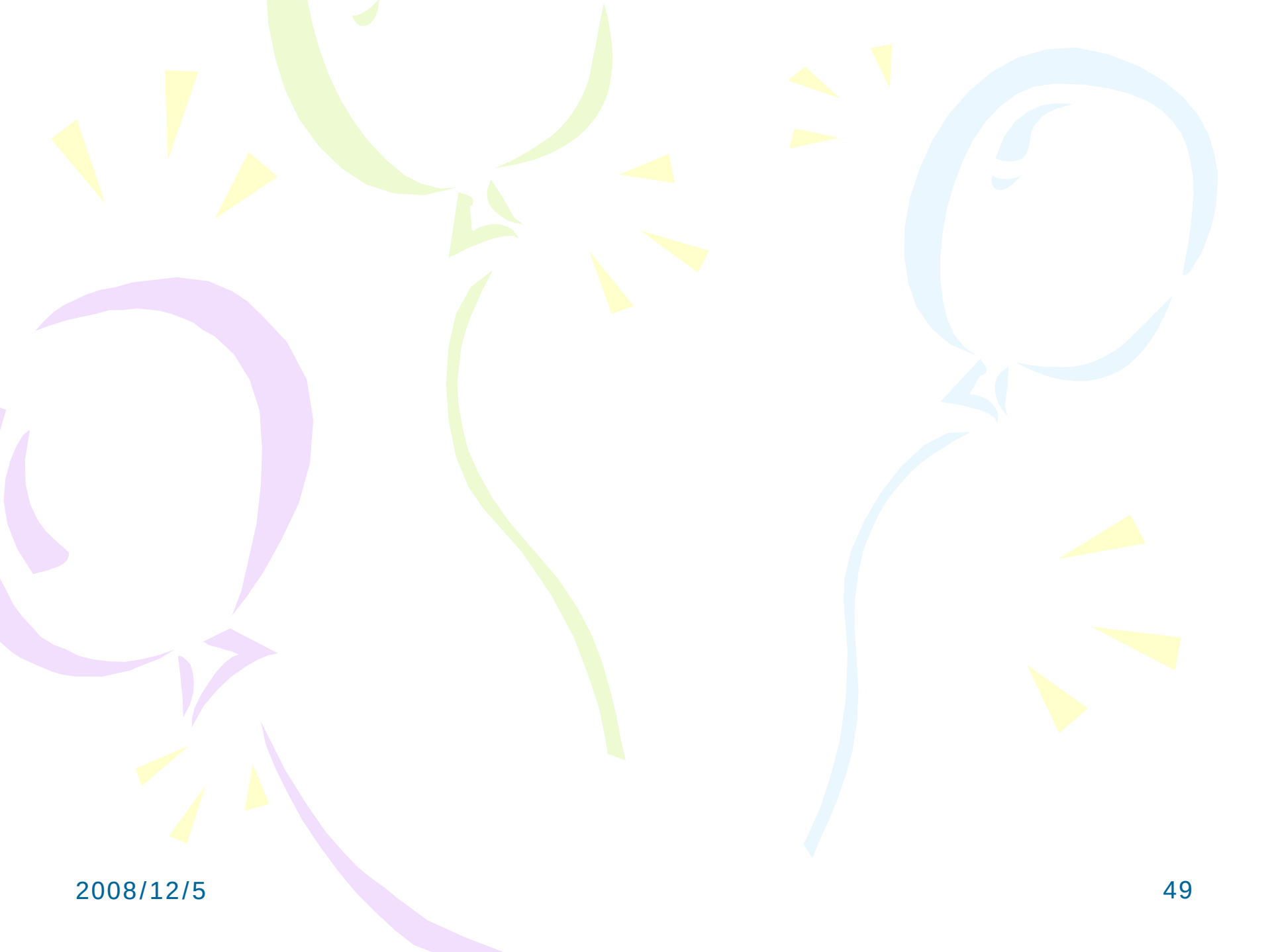
A,B...

C1 A1

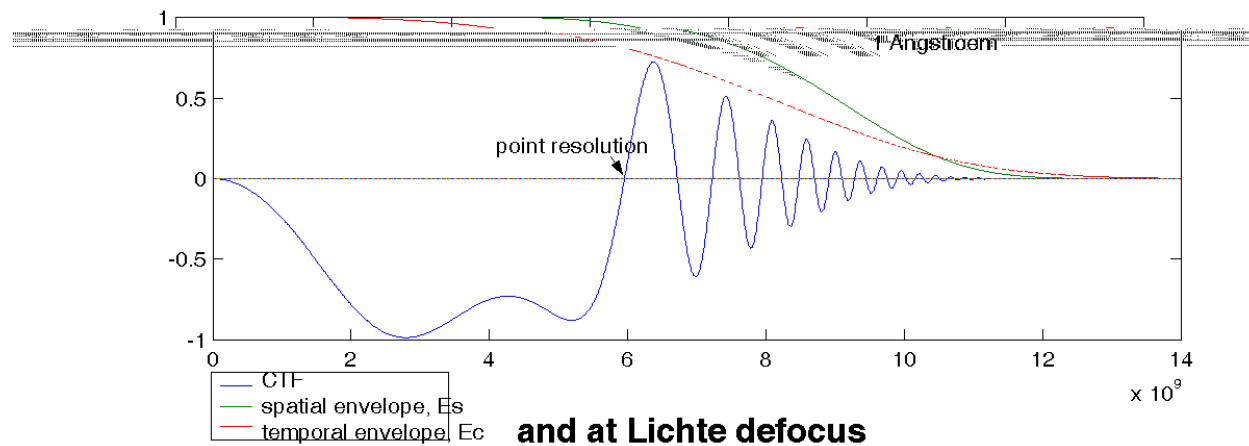


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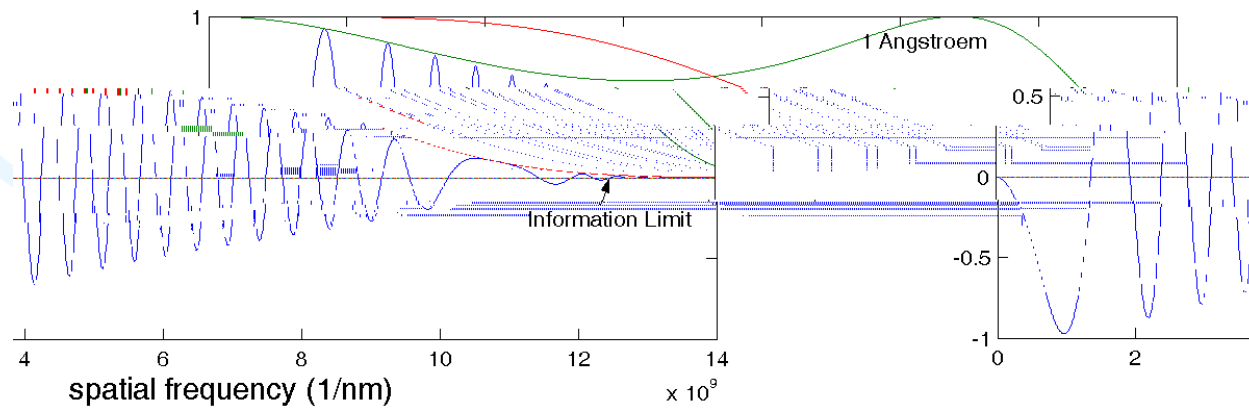
10.8 A-C TEM **M.Haider, S.Uhlemann,**
E.Schwan, H.Rose, B.Kabius and K.Urban : Nature, 392 (1998) 768.

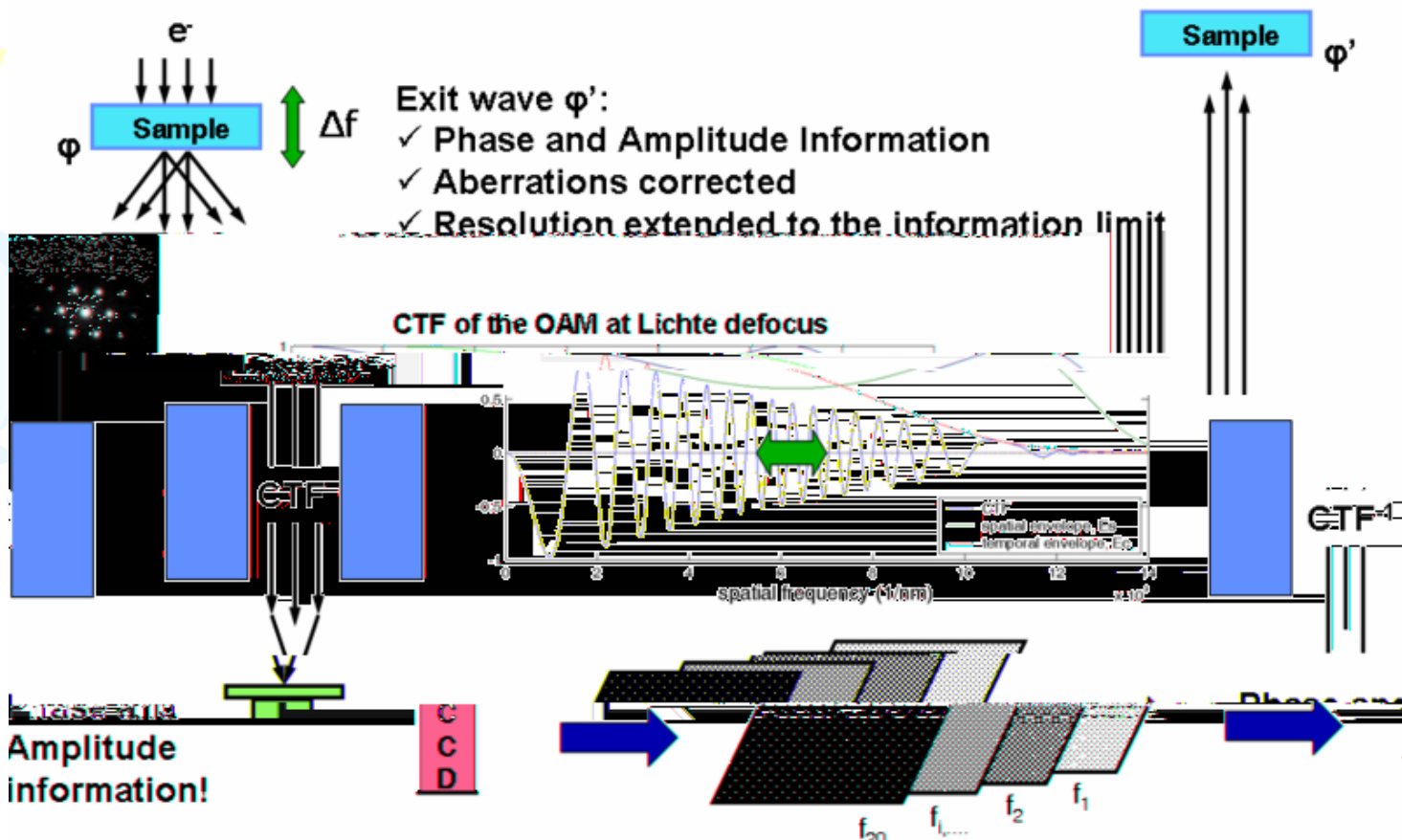


The CTF of the CM300 OAM at Scherzer defocus



and at Lichte defocus





Til Bartel, August 2006

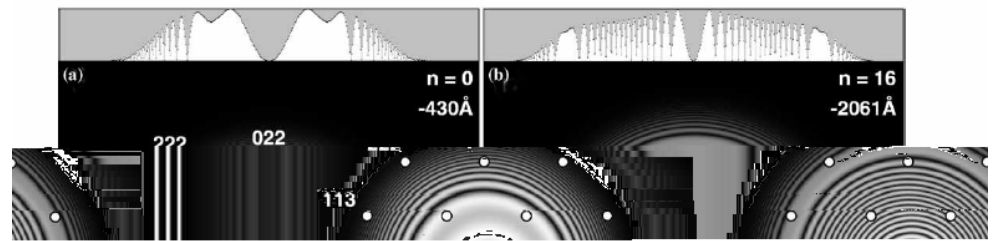
10

W.M.J. Coene, A. Thust, M. Op de Beeck, D. Van Dyck, Ultramicroscopy 64 (1996) 109
A. Thust, W.M.J. Coene, M. Op de Beeck, D. Van Dyck, Ultramicroscopy 64 (1996) 211

[110]
111
220
113
400

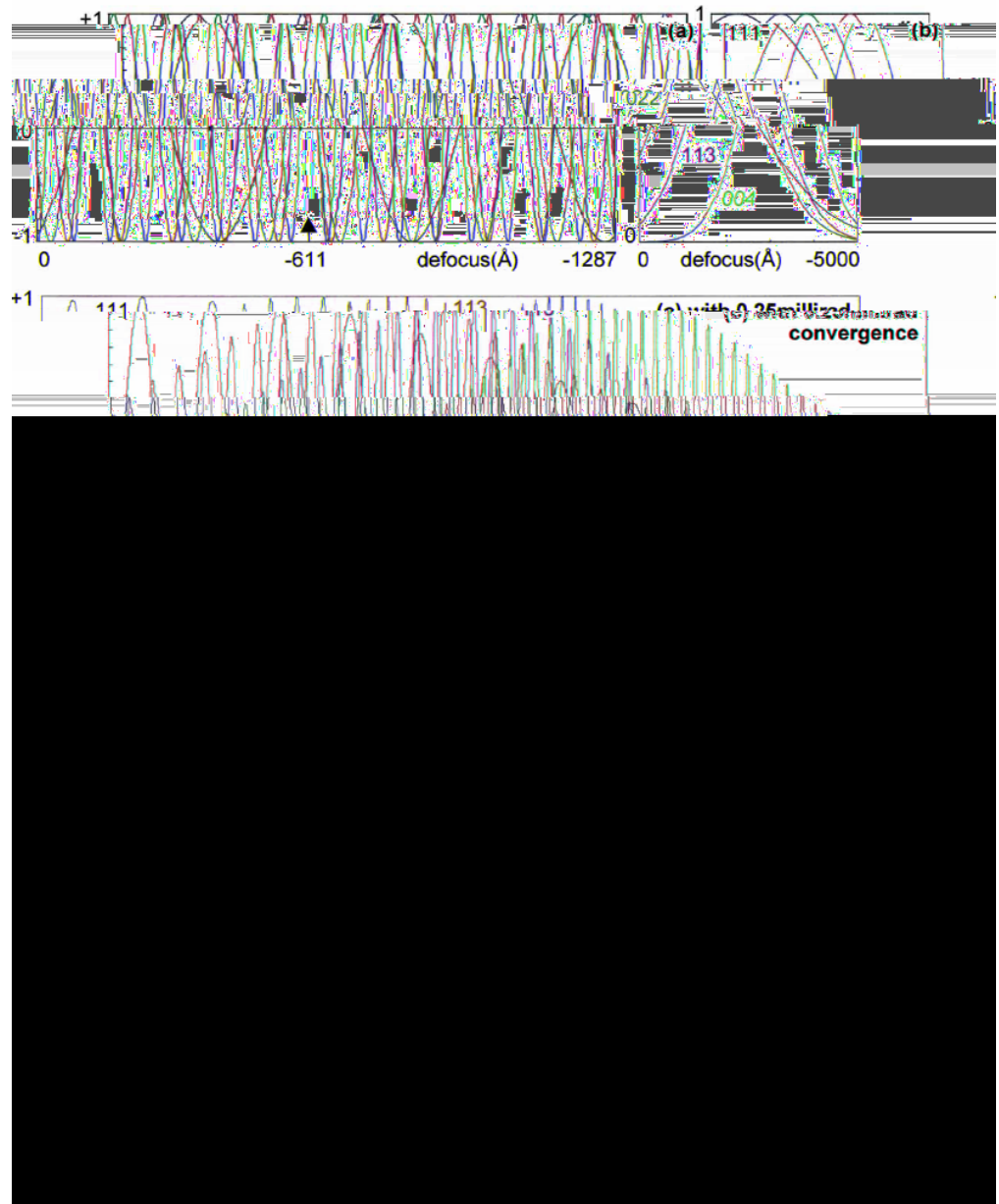
M.A. O'Keefe et al.,
Ultramicroscopy 89 (2001)
215–241
2008/12/5

A-C TEM



M.A. O'Keefe et al.,
Ultramicroscopy 89 (2001)
215–241

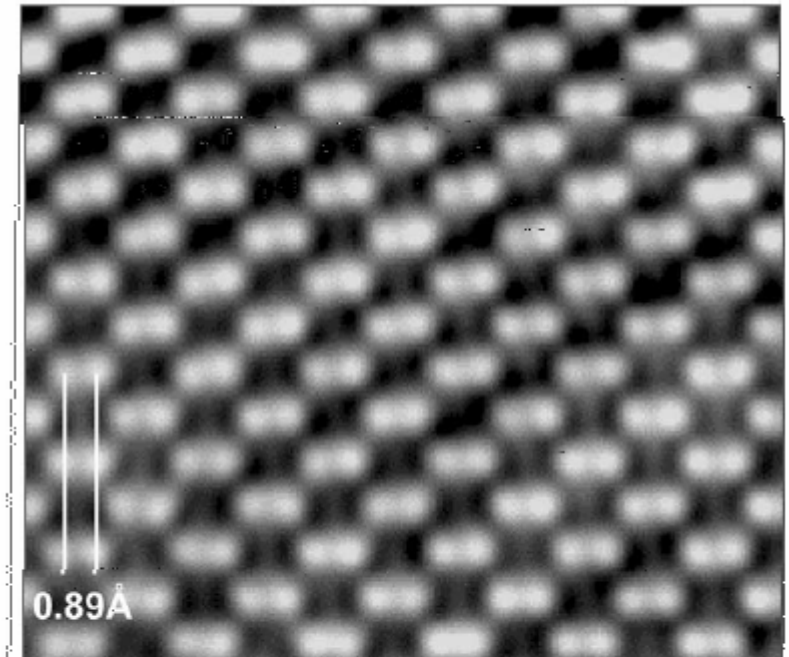
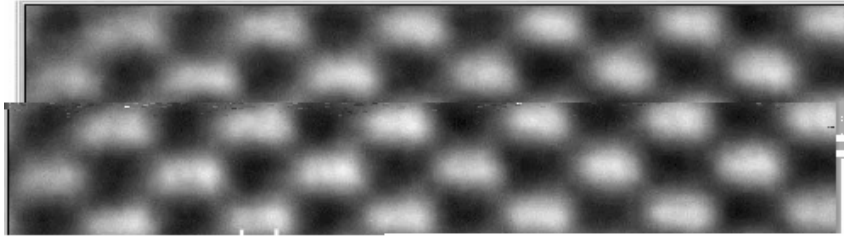
2008/12/5



A-C TEM

53

A_2



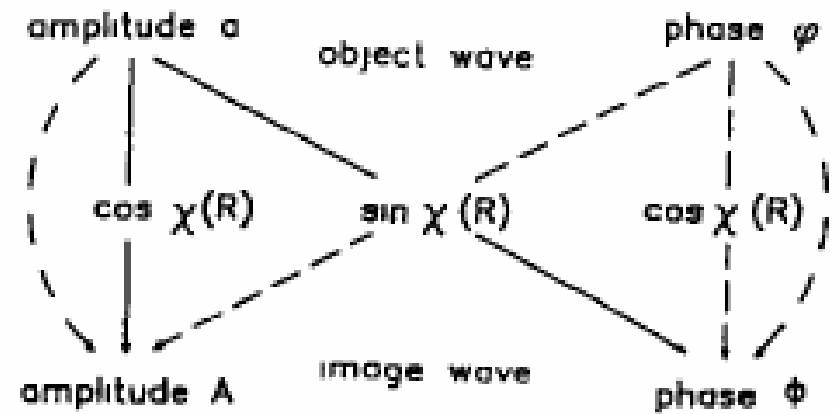
M.A. O'Keefe et al., Ultramicroscopy
89 (2001) 215–241

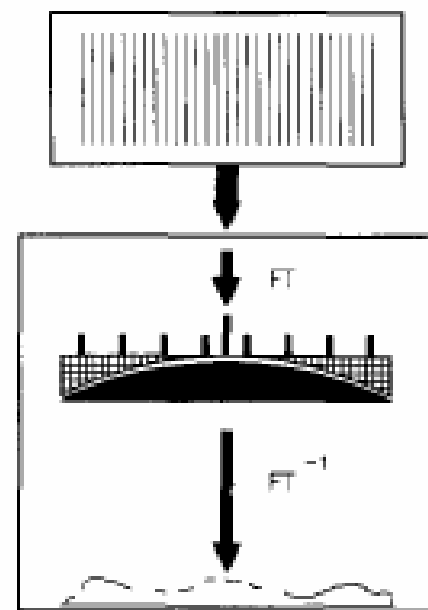
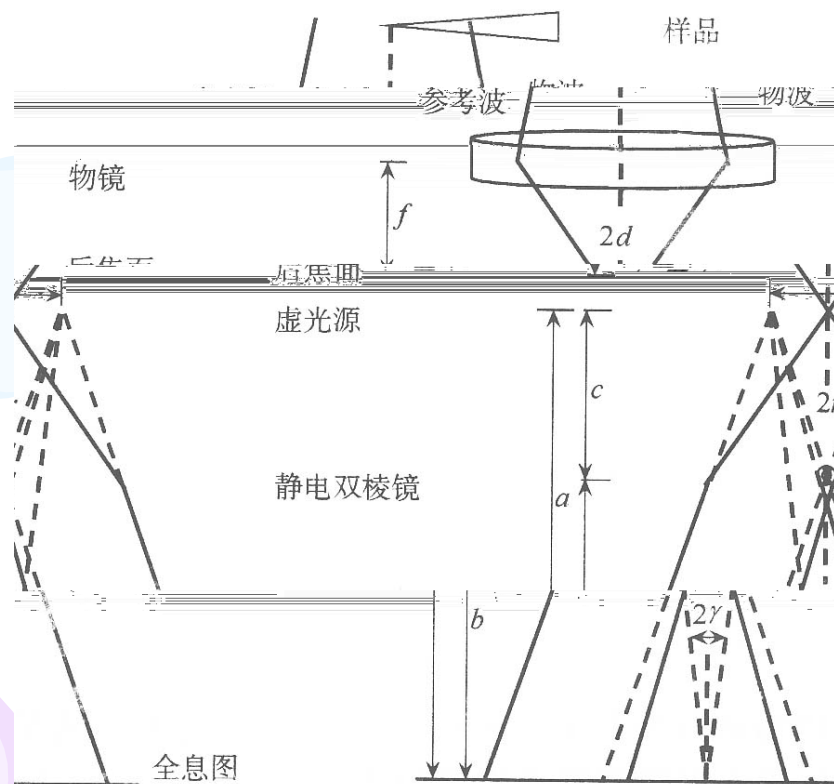
$$q(x,y) = \exp\{-i\sigma\phi(x,y) - \mu(x,y)\},$$

$$q(x,y) = 1 - i\sigma\phi(x,y) - \mu(x,y).$$

$$Q(u,v) = [\delta(u,v) - M(u,v) - i\sigma\Phi(u,v)] \exp\{i\chi\}$$

$$= \delta(u,v) - M(u,v)\cos\chi + \sigma\Phi(u,v)\sin\chi - i\{\sigma\Phi(u,v)\cos\chi\}$$





Hologram
Aberrated image wave

Computer
Fourier spectrum
wave aberration
Correction plate

Display
Aberration-free
object wave

0.0083nm

Ken Harada et al.,
 Proceedings of 8APEM,
 Kazakawa, Japan, pp 90.

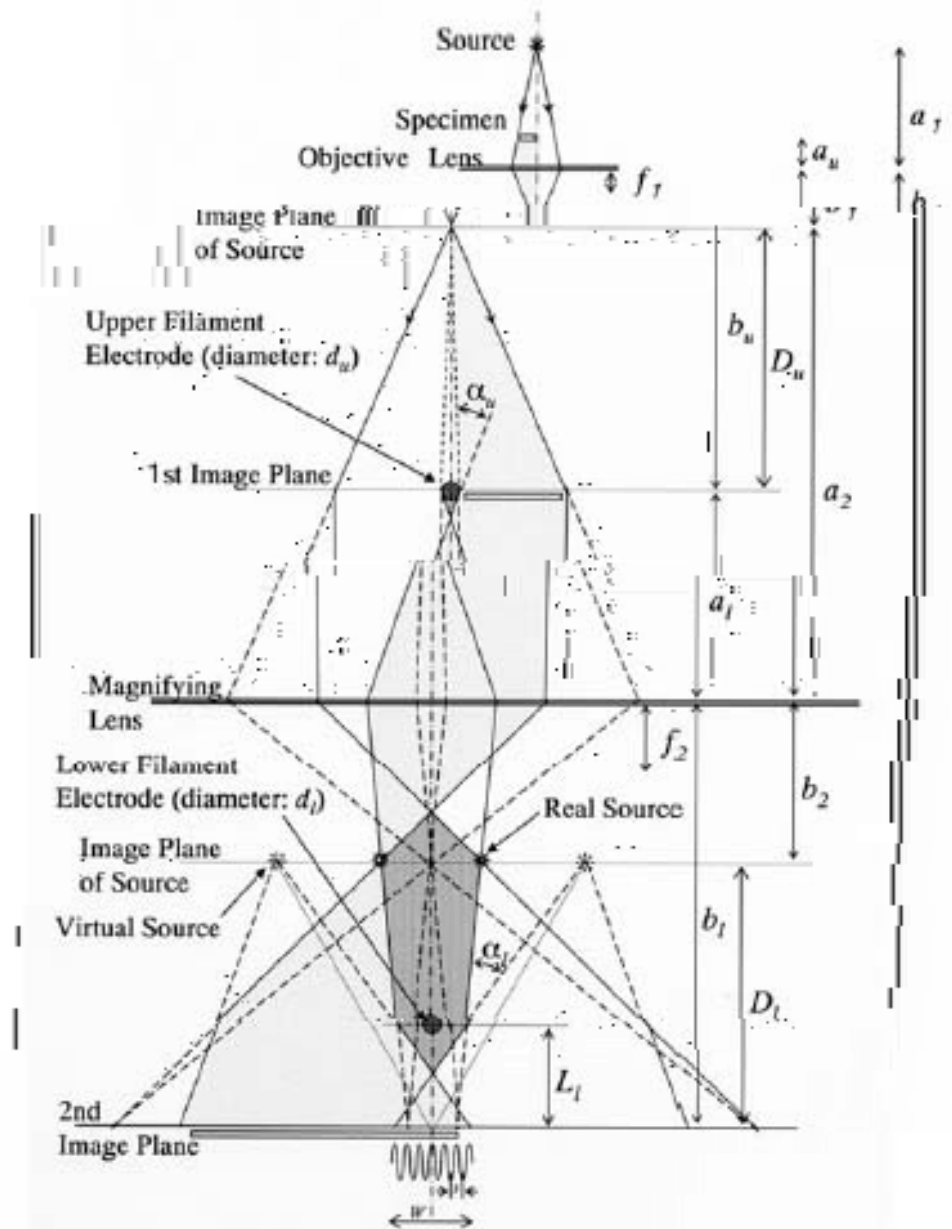
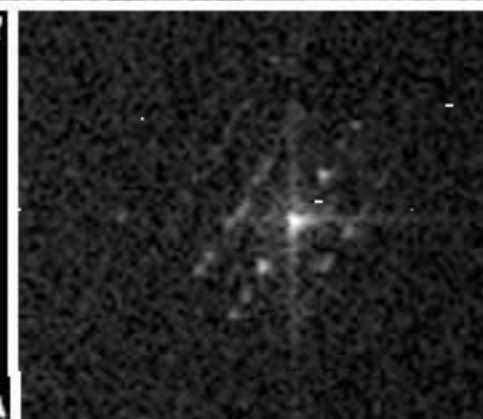
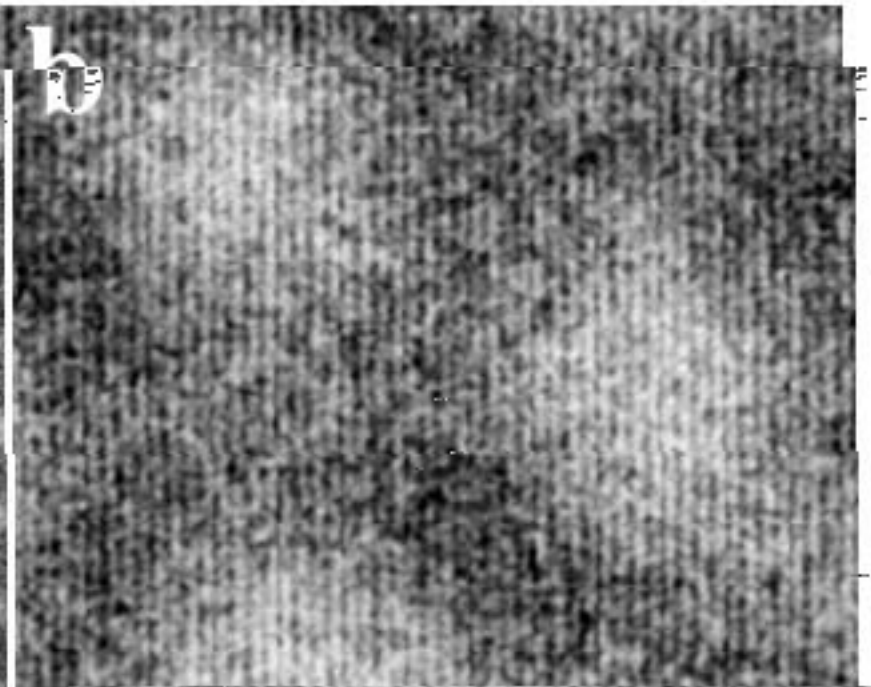
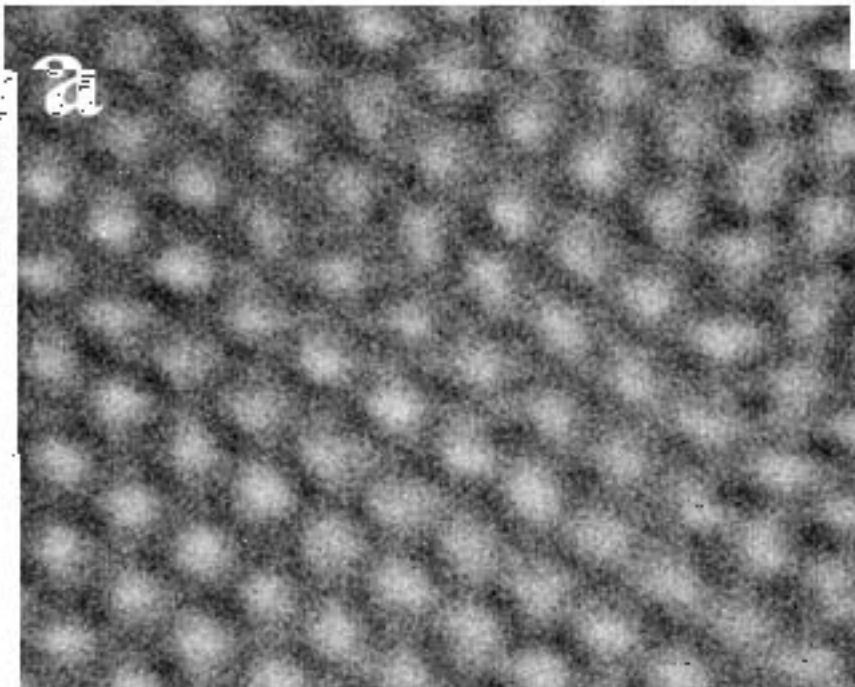
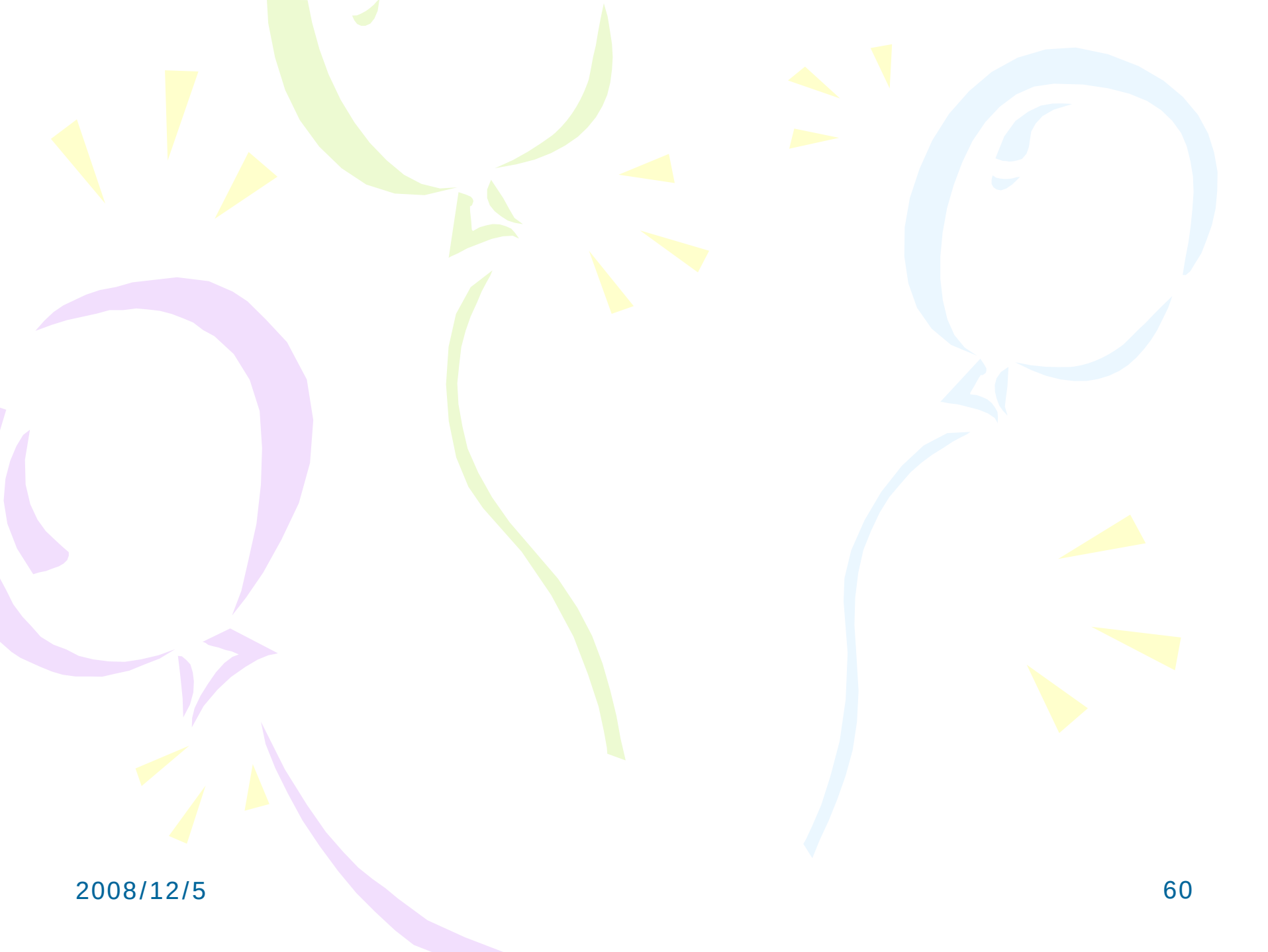
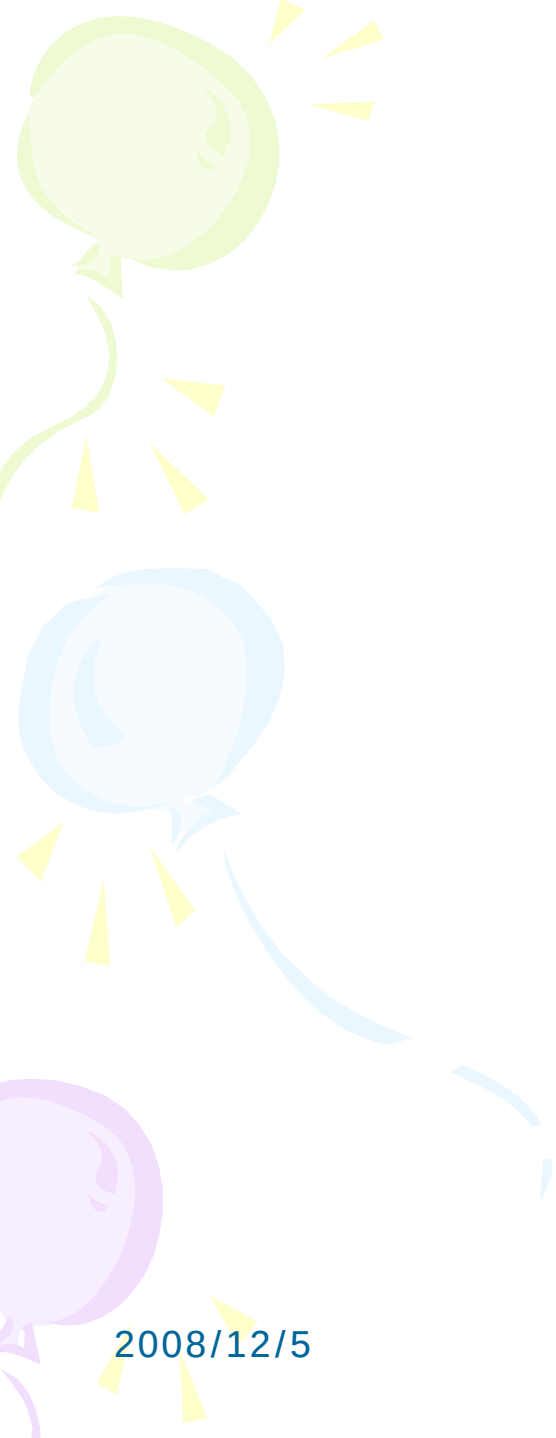


Figure 1. Optical setup of double biprism electron biprism.



Ken Harada et al., Proceedings of 8APEM, Kazakawa, Japan, pp 100.





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A-C TEM

61



- Scherzer 1936

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1948

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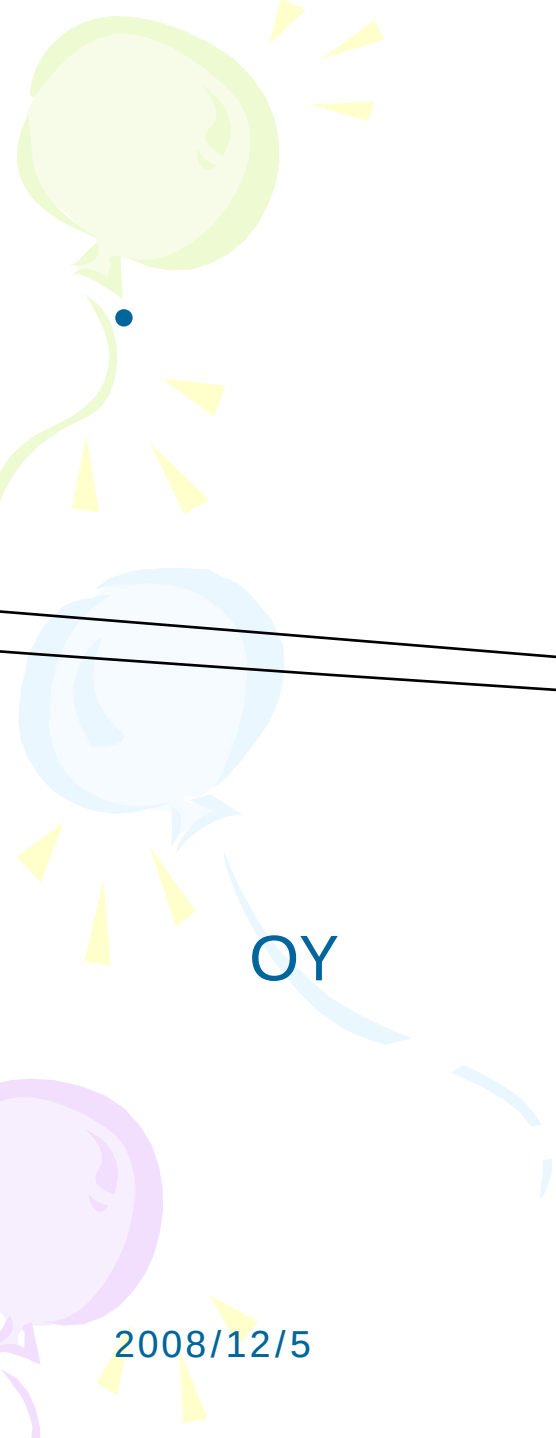
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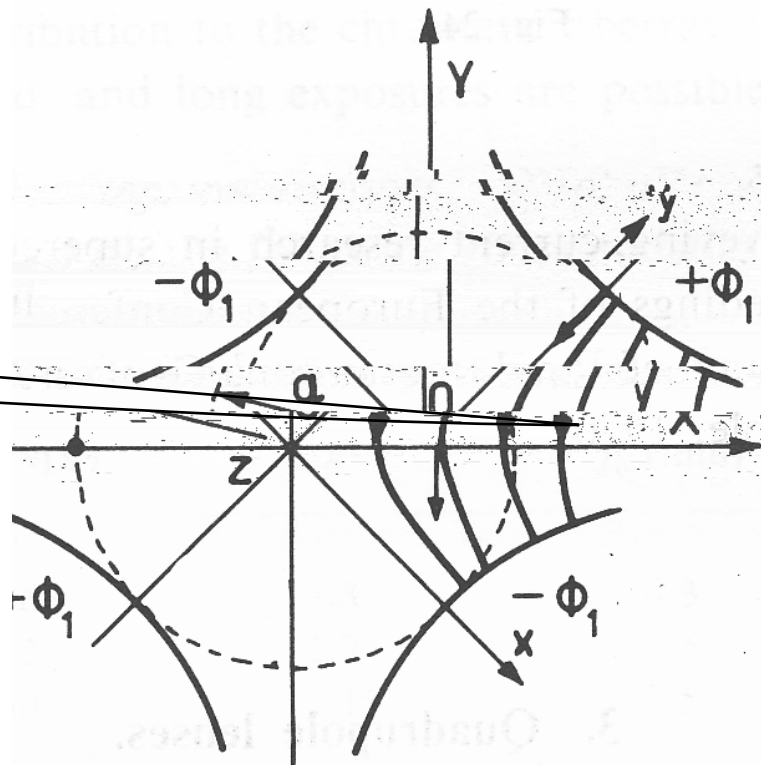
,

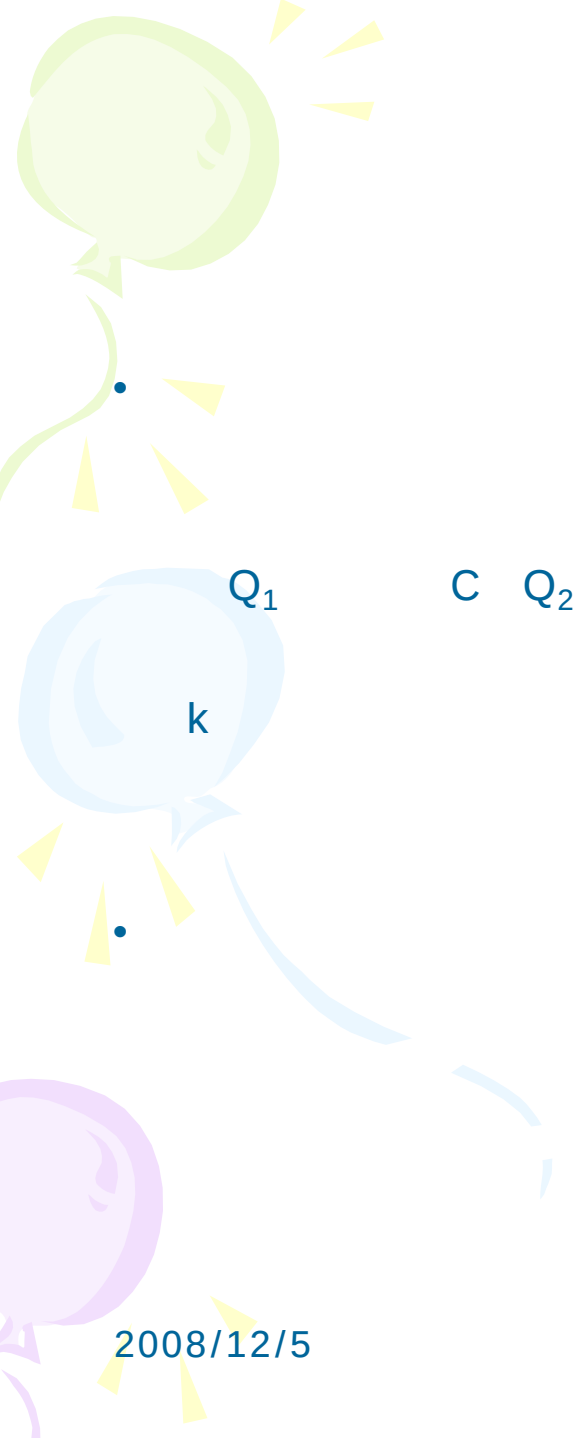
O.Scherzer, (1936) Z.Phys. 101, 23;
(1948) Optik 4, 258



OY

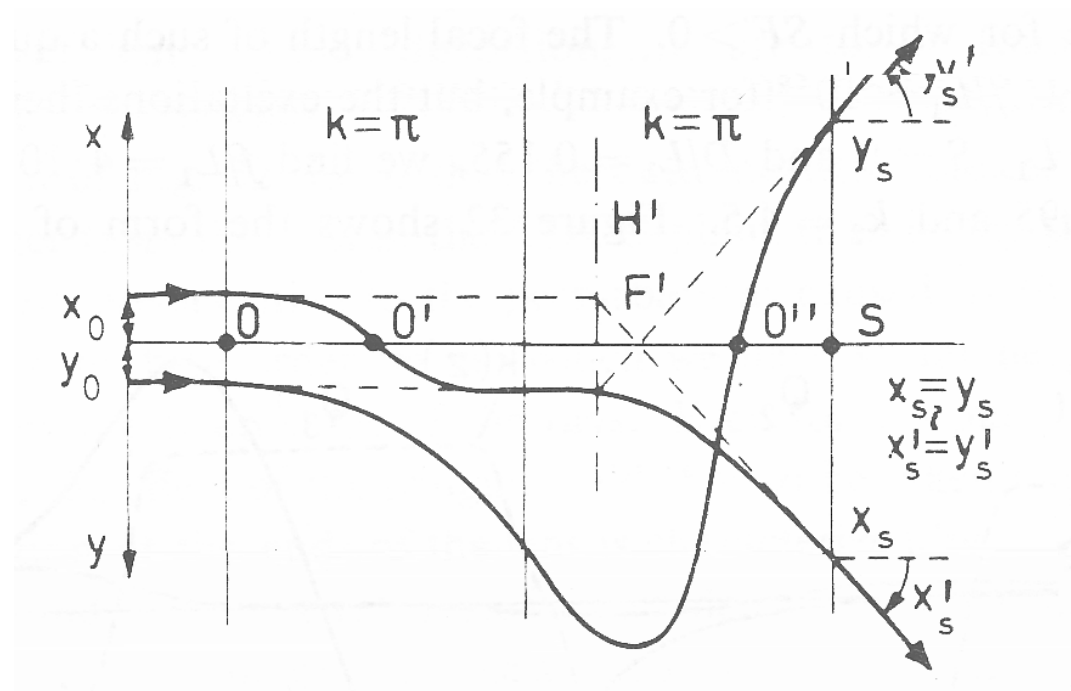
OX



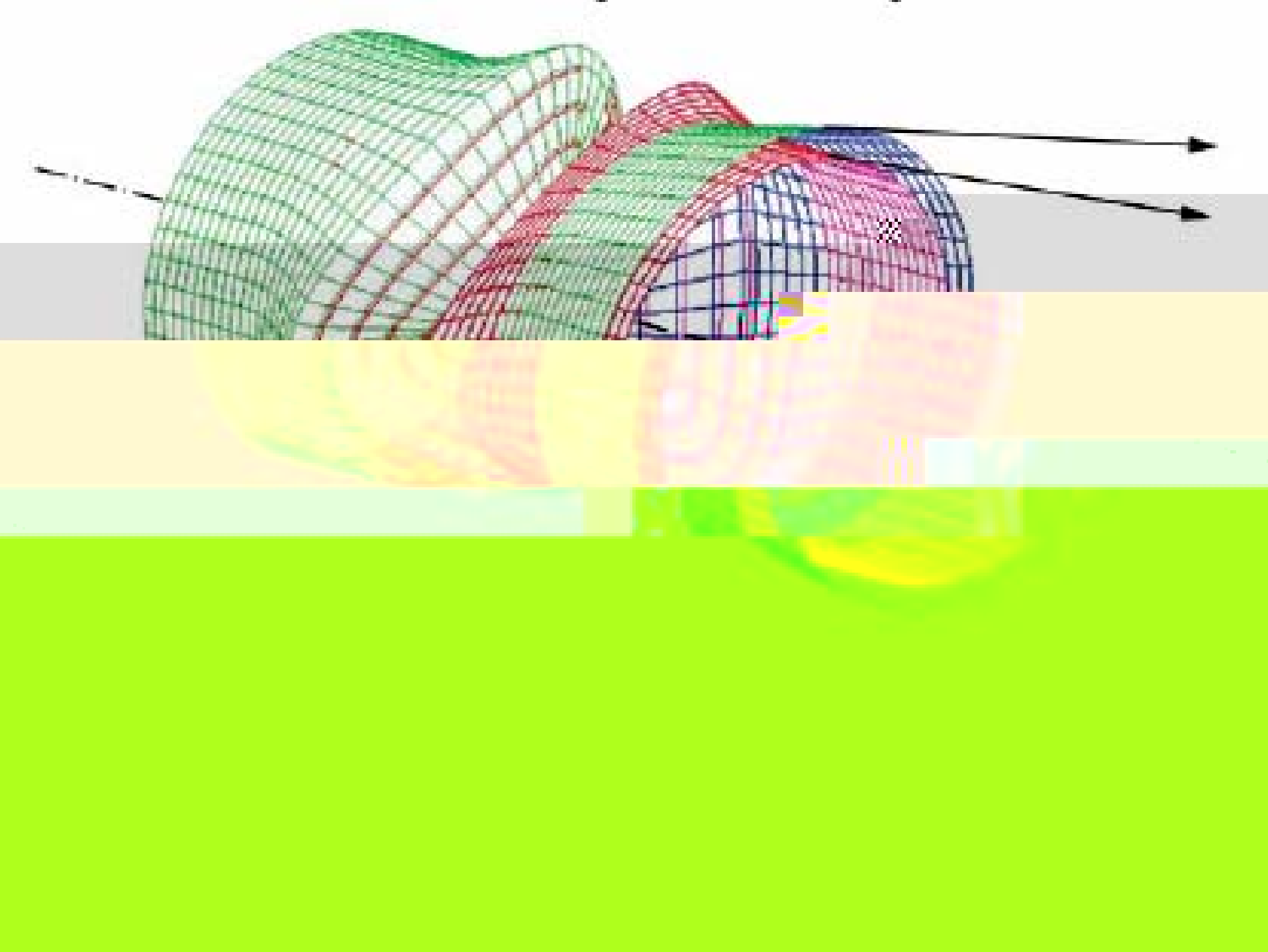


C Q_2

D



A.Septier: Chapter 2, in
<<Electron Microscopy in Material
Science>>, U.Valdre Edited,
(1971) AP, p14-73.



TEM, 1998

Wave aberration coefficients of the corrected microscope, measured at a tilt of $|\tau| = 26$ mrad

Coefficient	Measured value	Standard deviation
C_1	– 570 nm	10 nm
A_1	14 nm/146°	10 nm
A_2	250 nm/ – 20°	60 nm
B_2	55 nm/ – 104°	60 nm
C_3	+ 90 μ m	3 μ m
A_3	5.5 μ m/ – 59°	2 μ m
S_3	1.6 μ m/108°	2 μ m
A_4	86 μ m/154°	60 μ m
B_4	30 μ m/ – 141°	30 μ m
D_4	19 μ m/ – 10°	20 μ m
C_5	+ 6 mm	4 mm
A_5	1 mm/150°	2 mm

Measured wave aberrations for the uncorrected microscope after the alignment

Coefficient	Measured value	Standard deviation
C_1	– 590 nm	10 nm
$ A_1 $	0	10 nm
A_2	0.14 μ m/120°	0.15 μ m
B_2	0.10 μ m/80°	0.15 μ m
C_3	1290 μ m	15 μ m

S.Uhlemann & M.Haider:
Ultramicroscopy 72 (1998) 119.

STEM, 2001

N.Dellby, O.L.Krivanek,
P.D.Nellist, P.E.Batson,
and R.Lupini: J. of EM,
50(3) (2001) 177.

2008/12/5

coefficients measured shortly before recording
in Fig. 3d. **Table 1** Aberration coefficients
the Ronchigram shown

Measured value (nm)	Aberration coefficient
-805.3	C_1
-2.2	$C_{1,2a}$
-2.1	$C_{1,2b}$
-207	$C_{2,1a}$
-102	$C_{2,1b}$
19	$C_{2,3a}$
24	$C_{2,3b}$
-2.6×10^4	C_3
7.1×10^3	$C_{3,2a}$
1.1×10^4	$C_{3,2b}$
0.2×10^3	$C_{3,4a}$
1.8×10^4	$C_{3,4b}$
0.3×10^5	$C_{4,1a}$
2.8×10^5	$C_{4,1b}$
0.3×10^5	$C_{4,3a}$
7.1×10^5	$C_{4,3b}$
4.4×10^5	$C_{4,5a}$
-4.2×10^5	$C_{4,5b}$
6.3×10^7	C_5
5.8×10^6	$C_{5,2a}$
-3.0×10^6	$C_{5,2b}$
-9.8×10^6	$C_{5,4a}$
-3.9×10^7	$C_{5,4b}$
-4.8×10^6	$C_{5,6a}$
1.4×10^6	$C_{5,6b}$

$\pi/4$

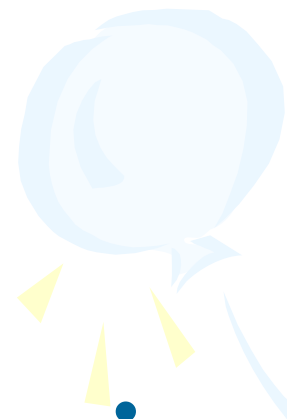
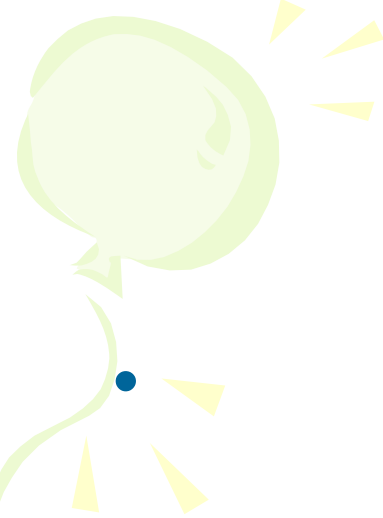
2008

List of the upper limits with respect to the $\pi/4$ criterion of all axial aberrations considering only one particular aberration coefficient

Aberration	80 kV	120 kV	200 kV		300 kV
	80 pm	65 pm	100 pm	50 pm	50 pm
Focus C_1 (nm)	0.40	0.31	1.0	0.25	0.4
Two-fold astigmatism A_1 (nm)	0.40	0.31	1.0	0.25	0.4
Three-fold astigmatism A_2 (nm)	11.50	9.2	60.0	7.5	13
Second-order coma B_2 (nm)	3.80	3.1	20.0	2.5	5.0
Third-order spherical aberr. C_3 (μm)	0.30	0.24	3.2	0.2	0.5
Four-fold astigmatism A_3 (μm)	0.30	0.24	3.2	0.2	0.5
Third-order star aberr. S_3 (μm)	0.07	0.06	0.8	0.05	0.11
Five-fold astigmatism A_4 (μm)	8.2	6.4	16.0	5.0	13.
Fourth-order coma B_4 (μm)	1.65	1.3	3.2	1.0	2.6
Fourth-order three-lobe aberr. D_4 (μm)	1.65	1.3	3.2	1.0	2.6
Fifth-order spher. aberr. C_5 (mm)	0.17	0.13	7.68	0.12	0.4
Six-fold astigmatism A_5 (mm)	0.17	0.13	7.68	0.12	0.4
Fifth-order rosette aberr. R_5 (mm)	0.03	0.02	1.28	0.02	0.06
Fifth-order star aberr. S_5 (mm)	0.03	0.02	1.28	0.02	0.06
Seven-fold astigmatism A_6 (mm)	4.58	3.62	358.4	2.8	11.7
Sixth-order coma B_6 (mm)	0.65	0.52	51.2	0.4	1.7
Sixth-order three-lobe aberr. D_6 (mm)	0.65	0.52	51.2	0.4	1.7
Sixth-order pentacle aberr. F_6 (mm)	0.65	0.52	51.2	0.4	1.7
Seventh-order spher. aberr. C_7 (mm)	104	82.0	15904	62.2	339
Chromatic aberr. C_{cl} (μm)	10.	10.	10.	10.	10.

The summation of the total phase shift when all aberrations are contributing to the upper limit is not included.

M. Haider, H. Muller, S. Uhlemann, J. Zach, U. Loebau, R. Hoeschen: Ultramicroscopy 108 (2008) 167–178



XOZ

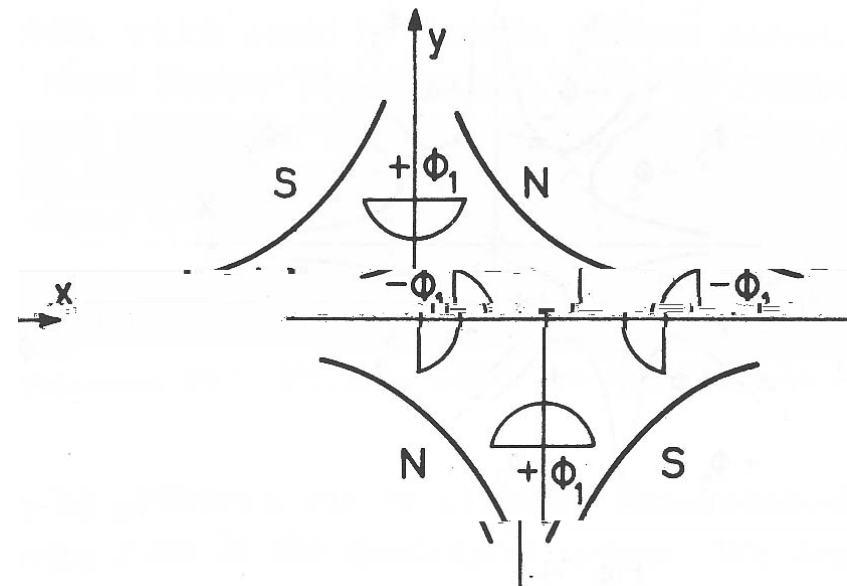
yoz

SEM

TEM

Hieder

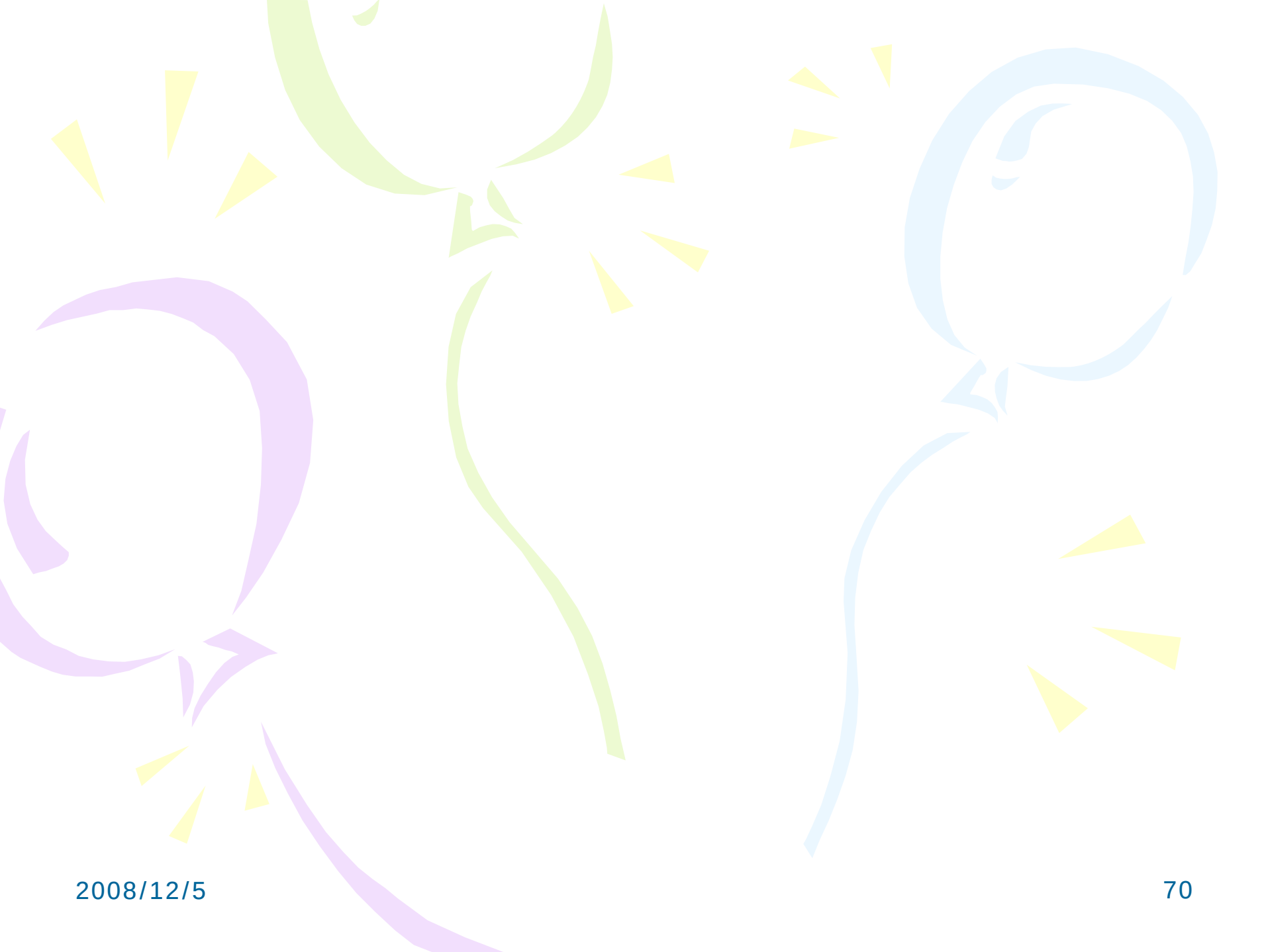
2008-10-15

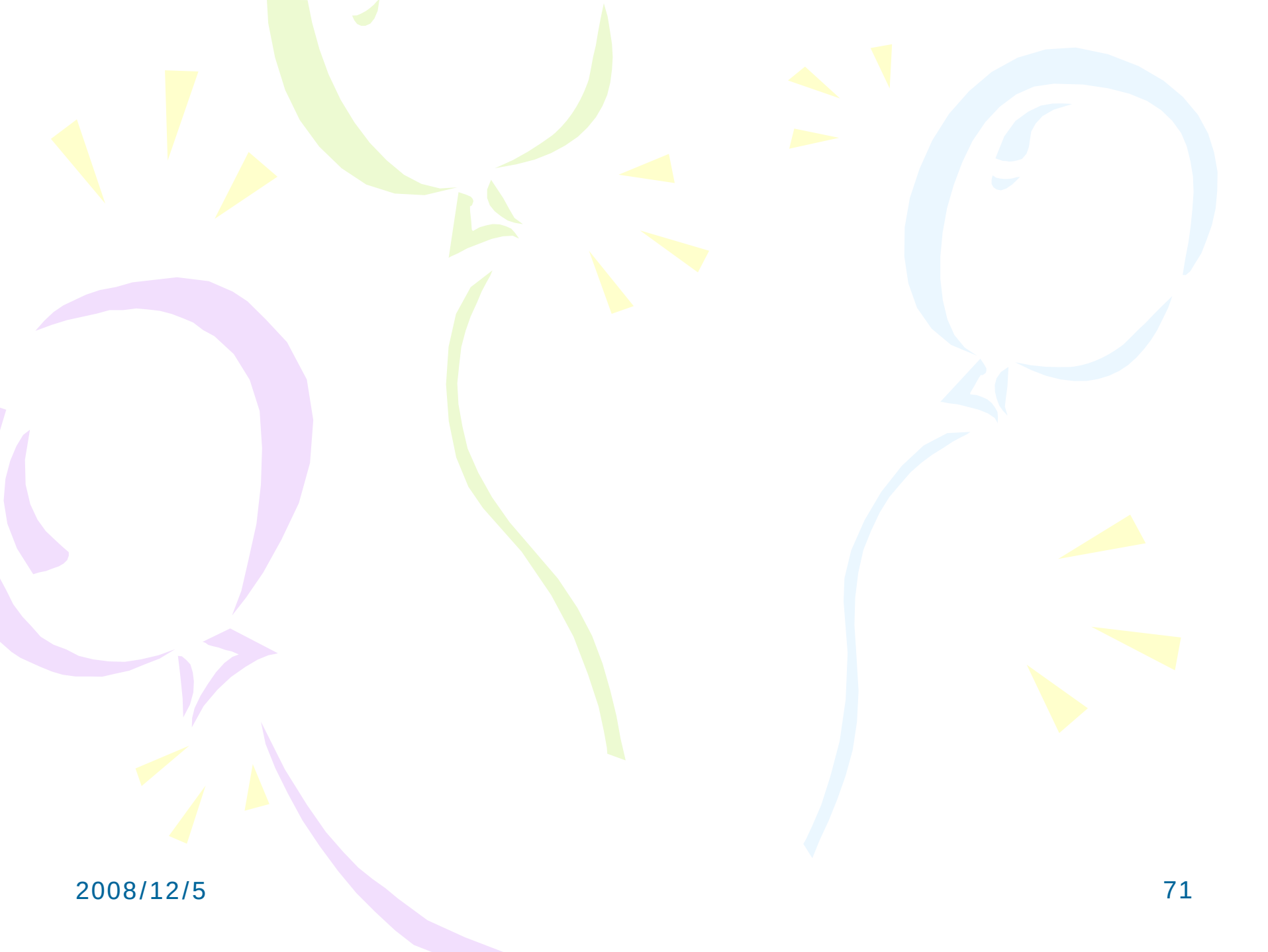


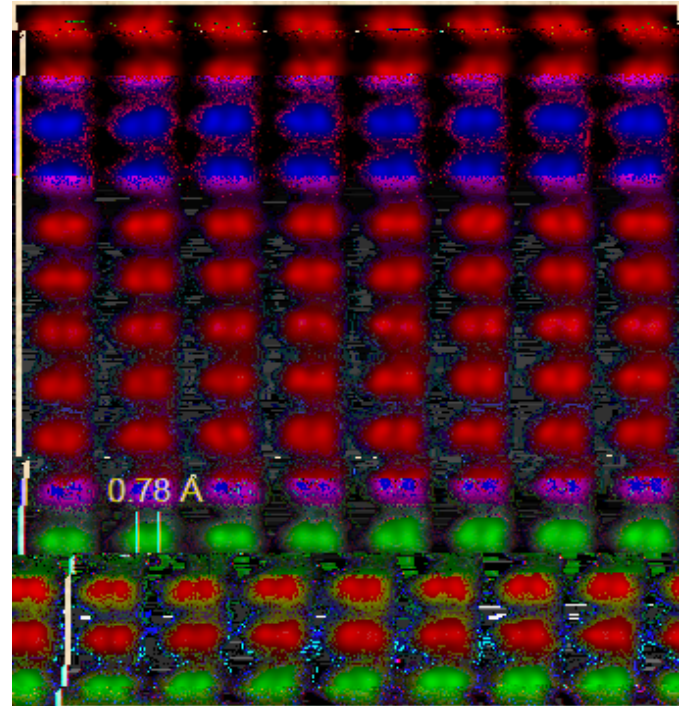
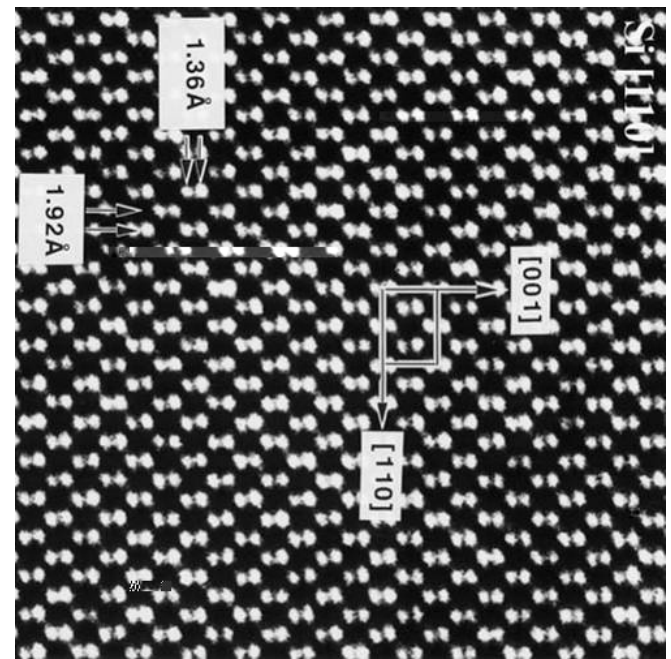
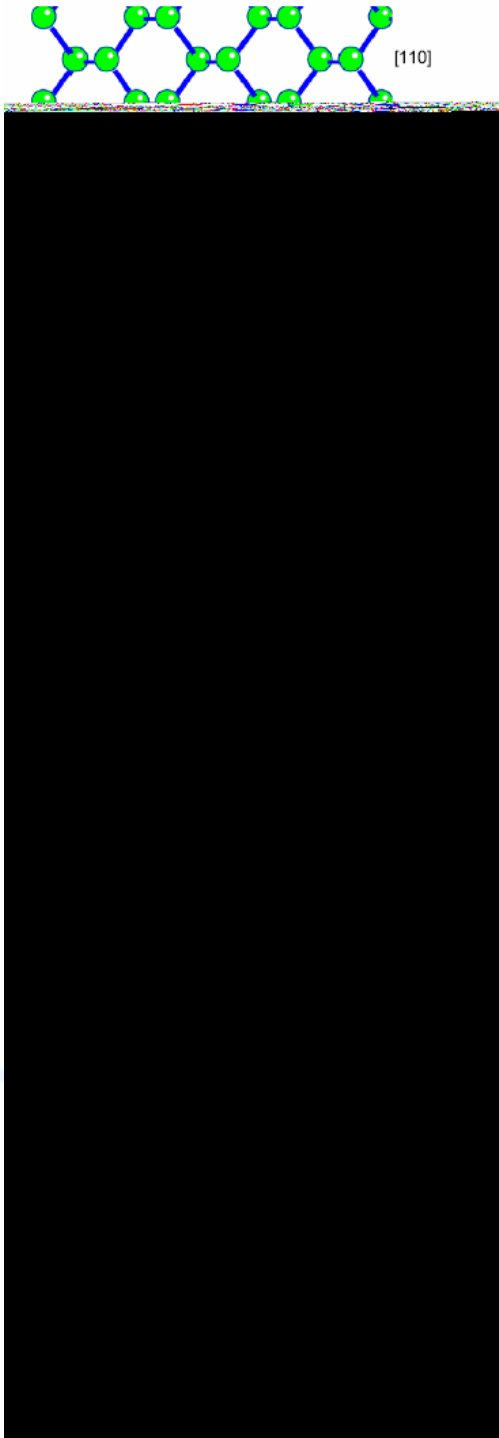
2008/12/5

A-C TEM

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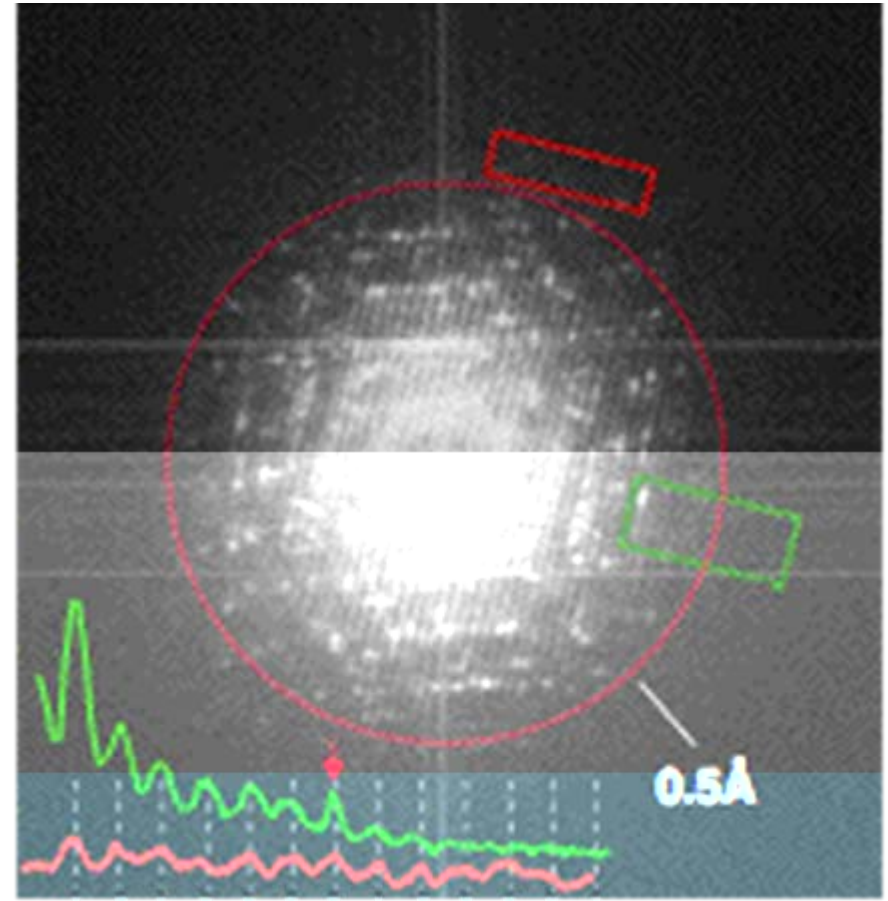
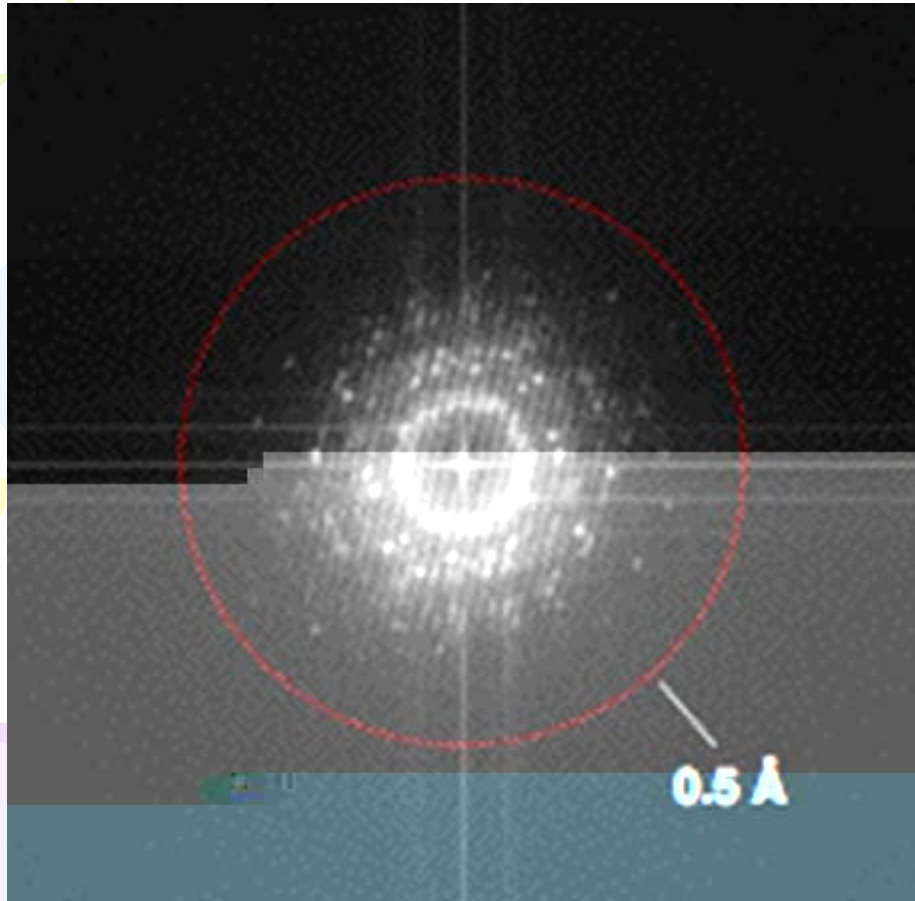


P.D. Nellist et al.,
Science 305,
(2004)1741.

2008/12/5

TEM

0.5



Scherzer

1

0.5

Si

1.11 Å,

116

0.31 Å
Debye-

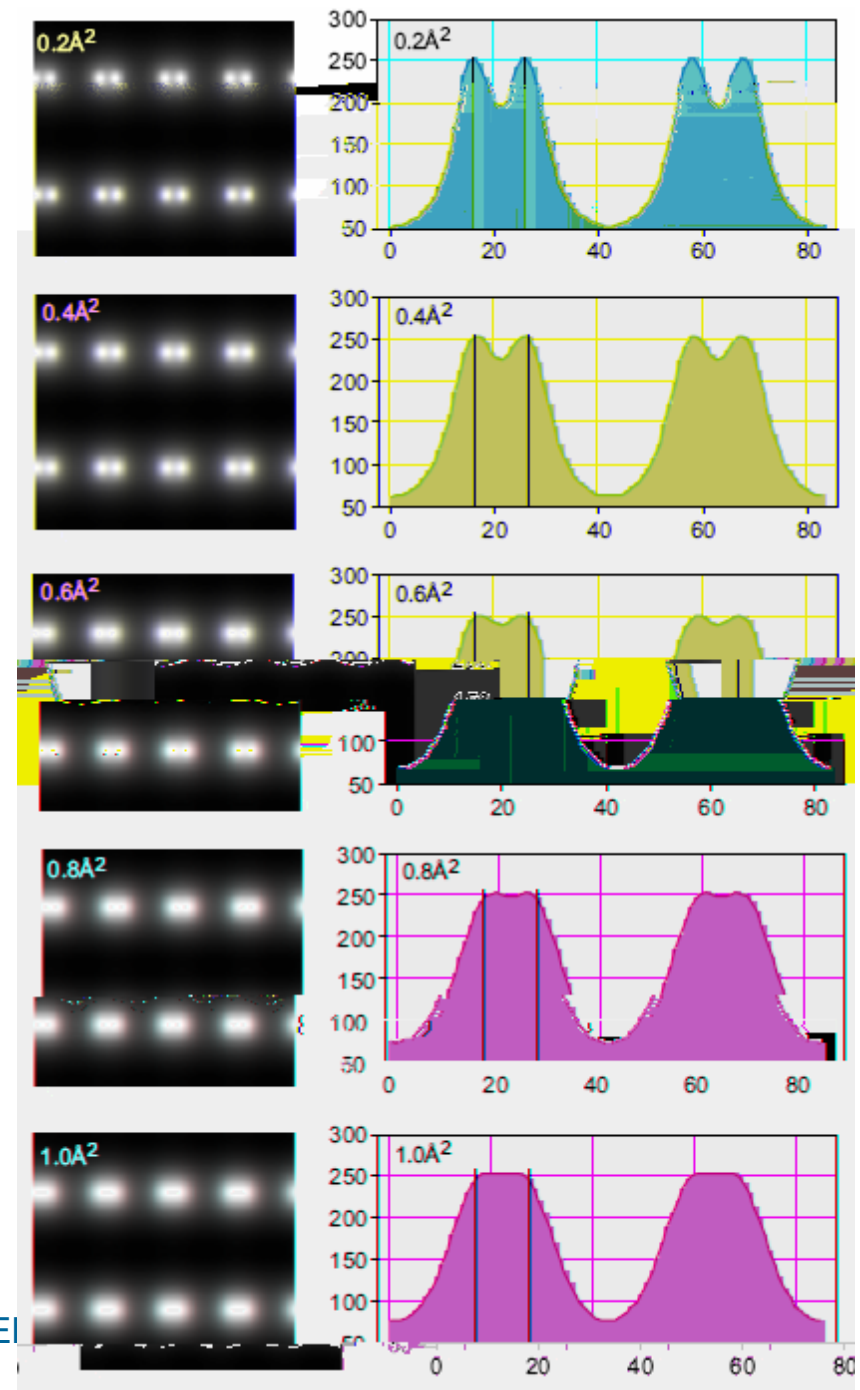
Waller

0.4668 Å², 1.11 Å

0.31 Å

12

2008 M. A. O'Keefe: A-C TEL
Ultramicroscopy 108 (2008)

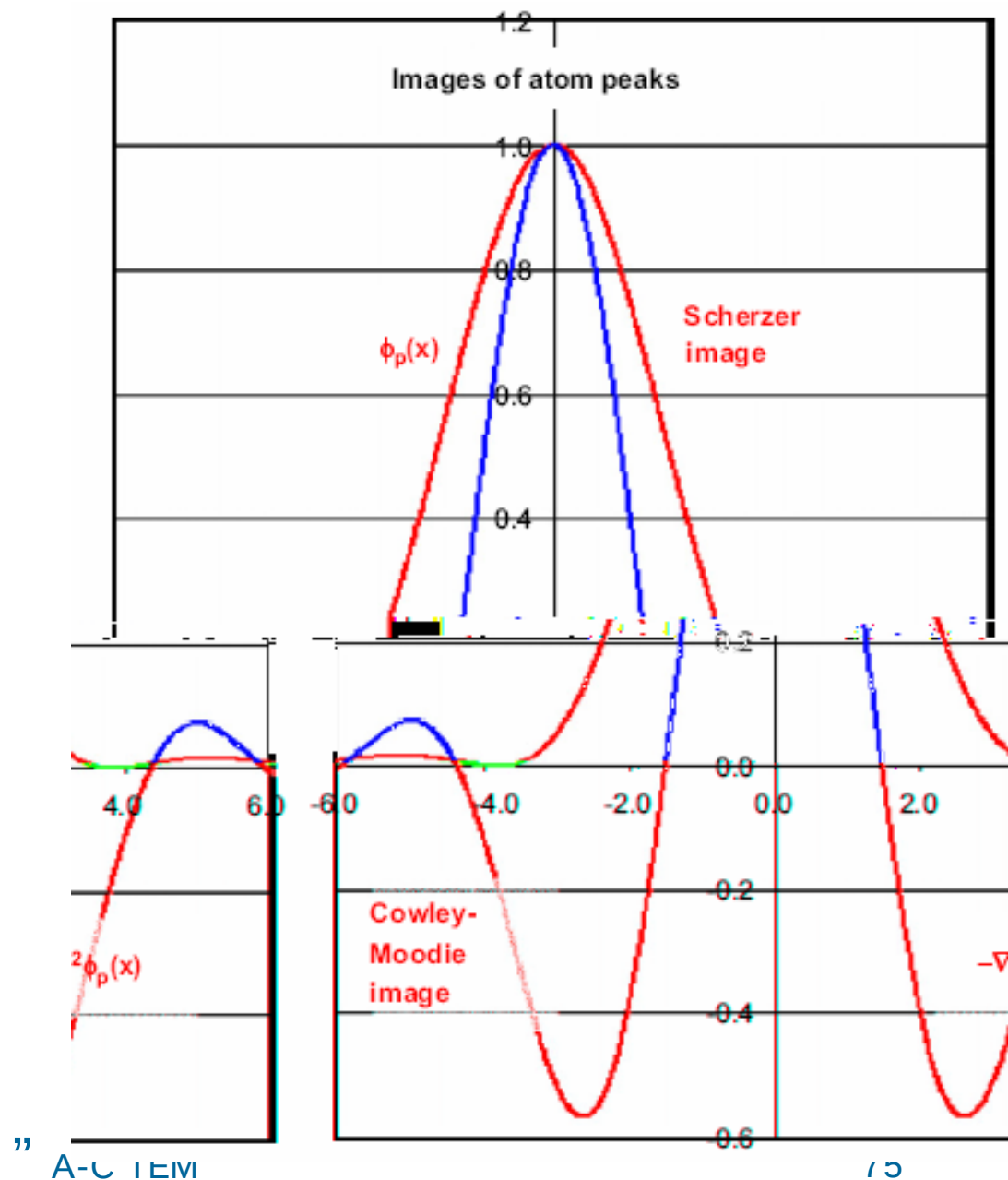


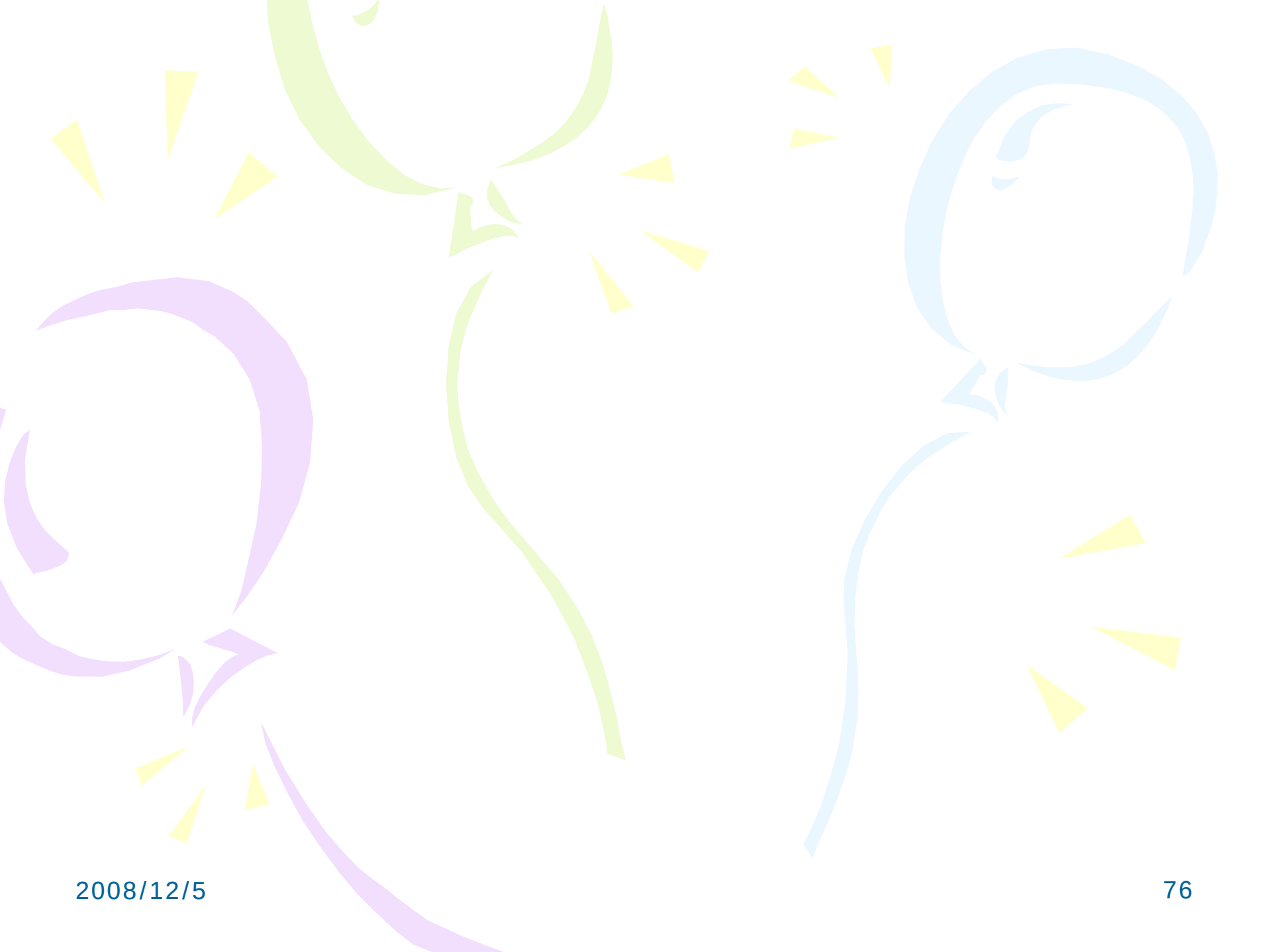
$$I = q \cdot q * \frac{1 - \sigma \lambda H \Delta f \nabla^2 \phi_p(x)}{2\pi}$$

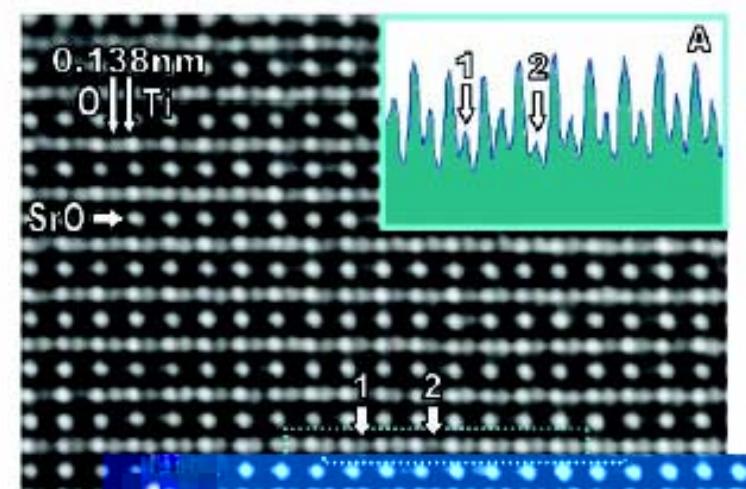
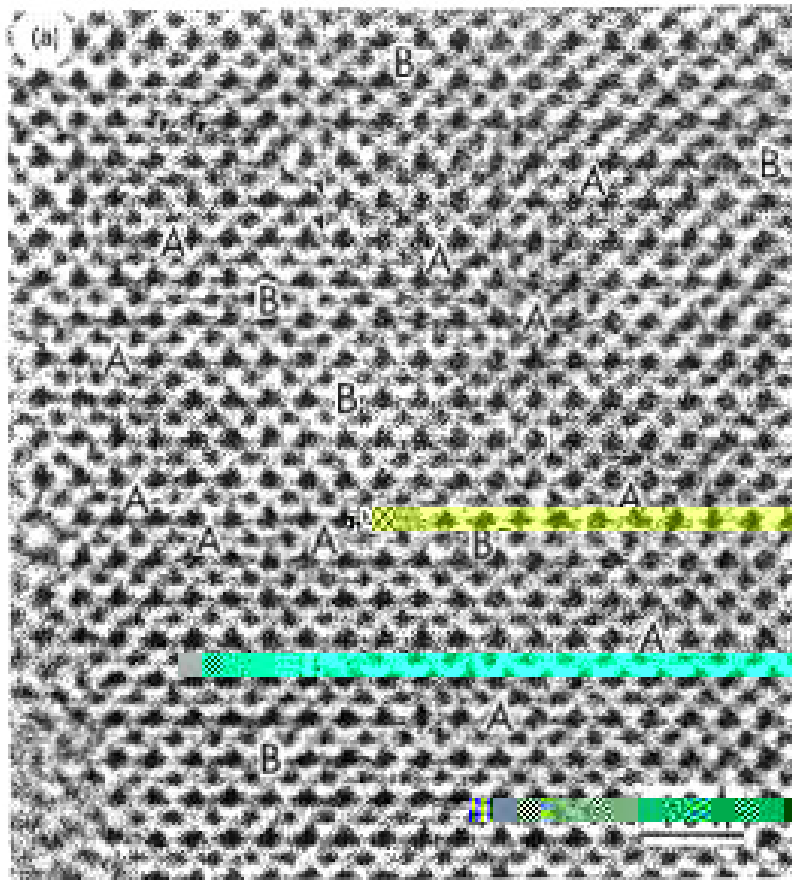
$$f = 0$$

[M.A.O'Keefe:
Ultramicroscopy 108
(2008) 196]

2008/12/5







1500
B.Okai: Jpn. J. Appl. Phys. 31 (1992) L59]

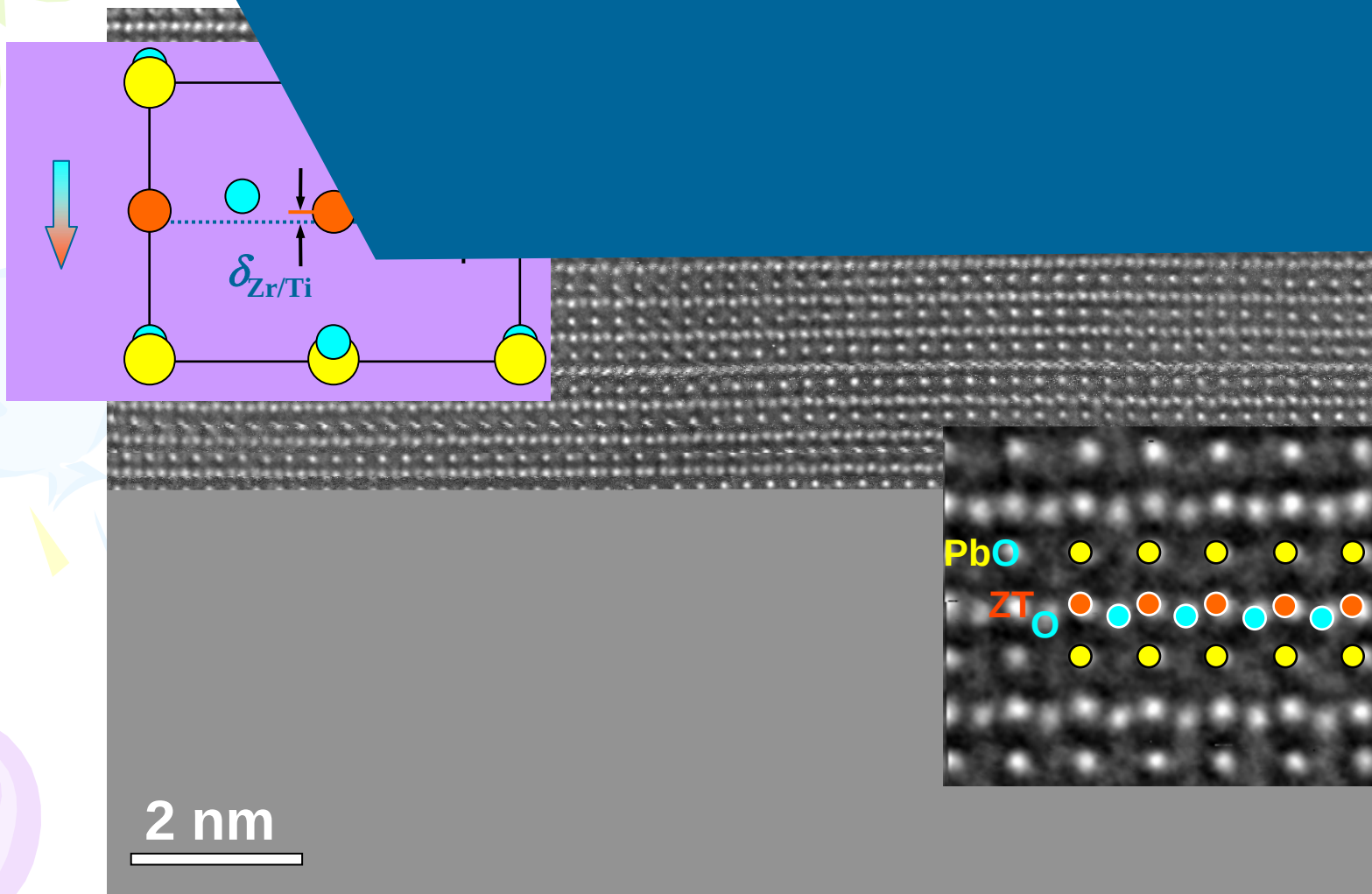
ScTiO₃()

299 (2003) 870]
2008/12/5

A-C TEM

1994 1.1
[S. Horiuchi, Y.Mastui and

[C.L.Jia et al., Science



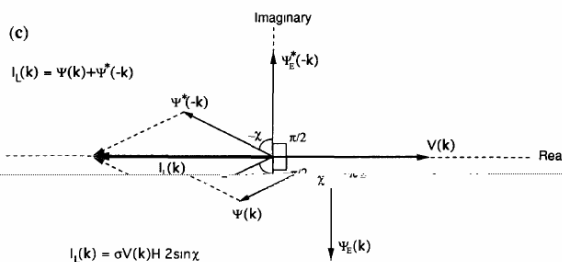
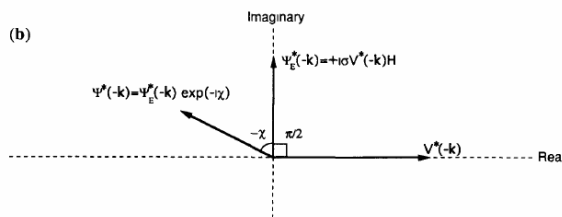
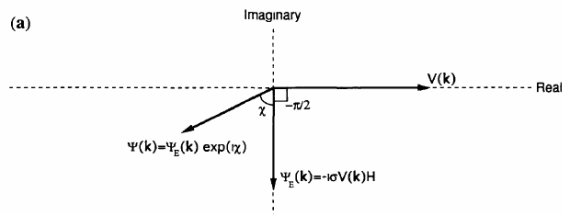
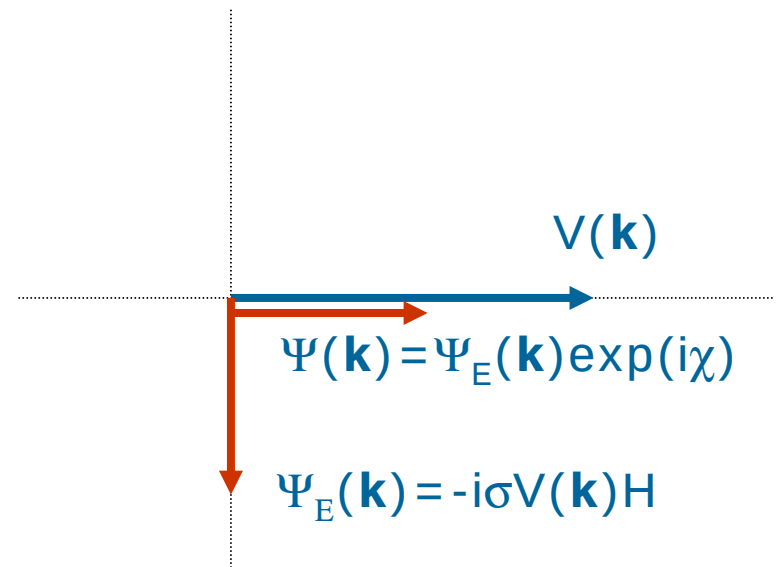


Fig 2 Argand diagrams showing the action of $\sin \chi(k)$ under WPO conditions (a) Formation of the k th image component $\Psi(k)$ The specimen potential component $V(k)$ gives rise to an exit-surface diffracted beam $\Psi_E(k)$ at difference of $-\pi/2$ from $V(k)$ Passage through the objective lens rotates the phase of $\Psi_E(k)$ through an angle of $\chi(k)$ (b) Formation of the second amplitude component contributing to the k th image intensity component (c) Summation of two amplitude components to produce the intensity component $I_k(k)$, which lies along the negative extension of the origin and has an amplitude (length) proportional to $2 \sin \chi(k)$



M.O'Keefe: UltraM, 47(1992) 282

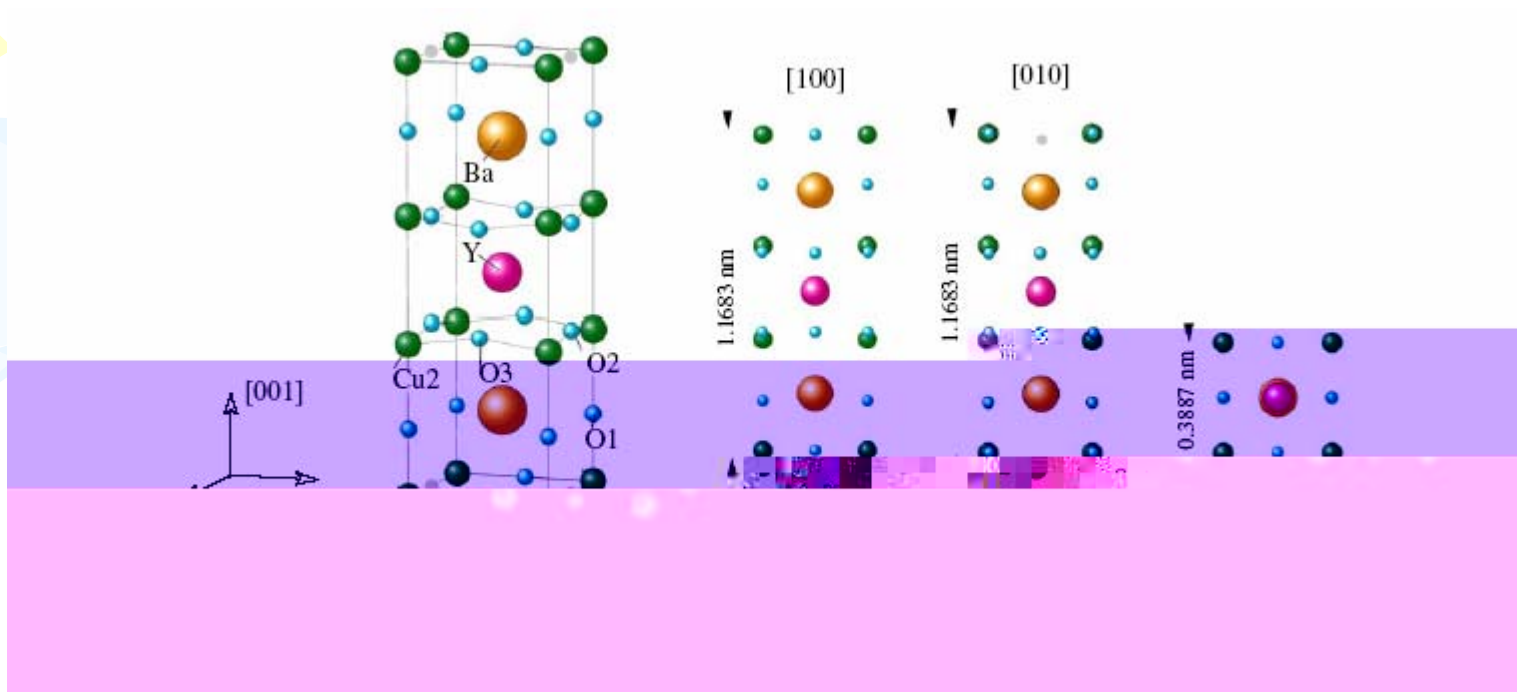
2008/12/5

A-C TEM

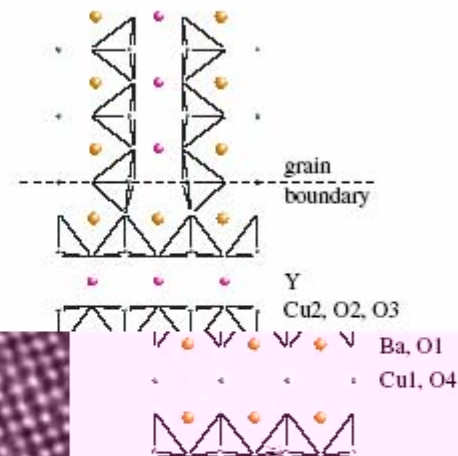
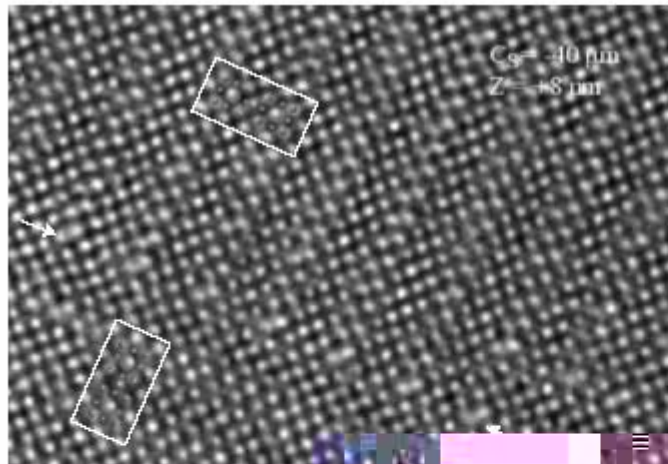
79

The background features several large, thick, curved lines in purple, green, and blue. Interspersed among these are numerous small, yellow, triangular starburst shapes pointing in various directions.

+ / - 6 p m



90°



L. Houben, A. Thust, K. Urban: Ultramicroscopy 106 (2006) 200–214

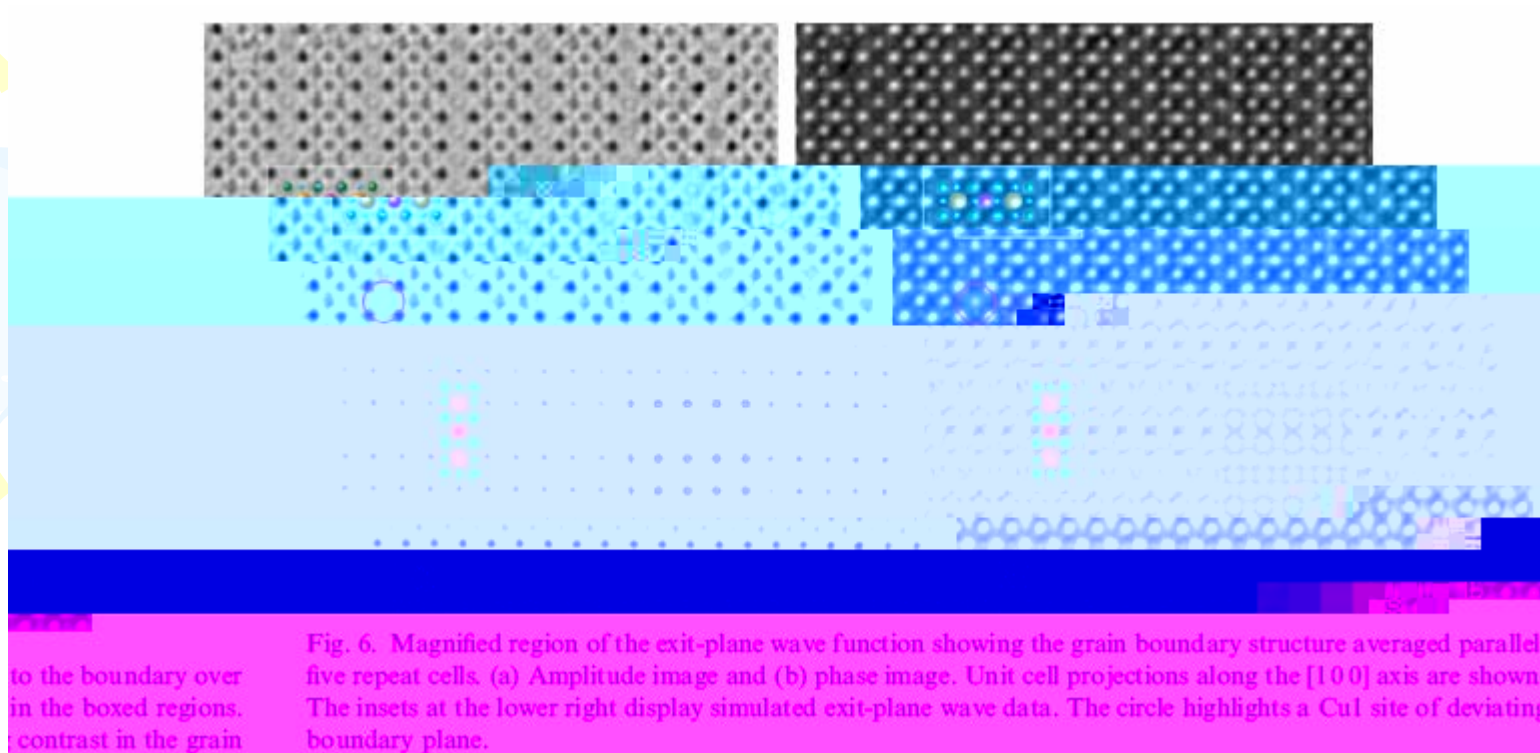
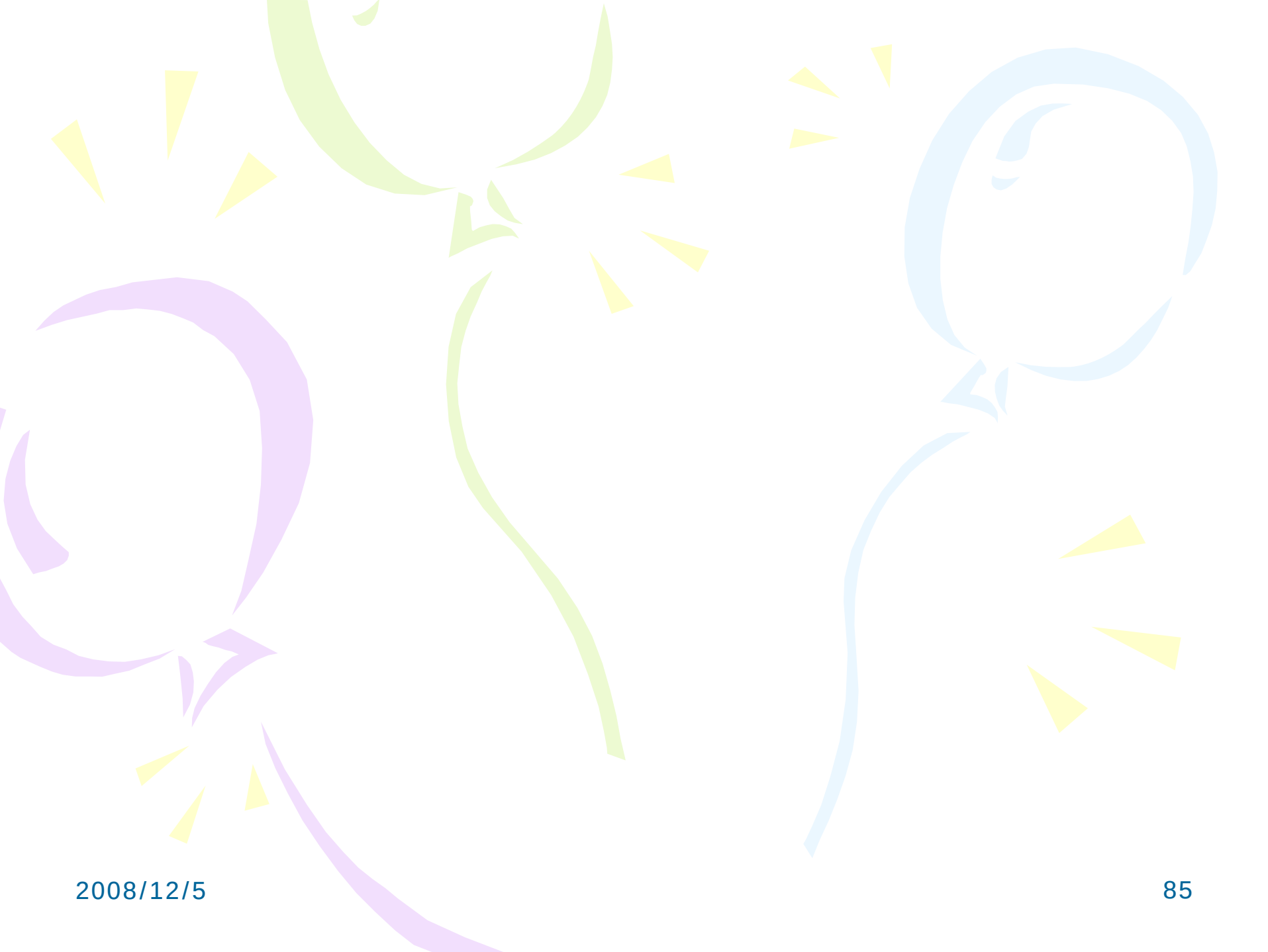
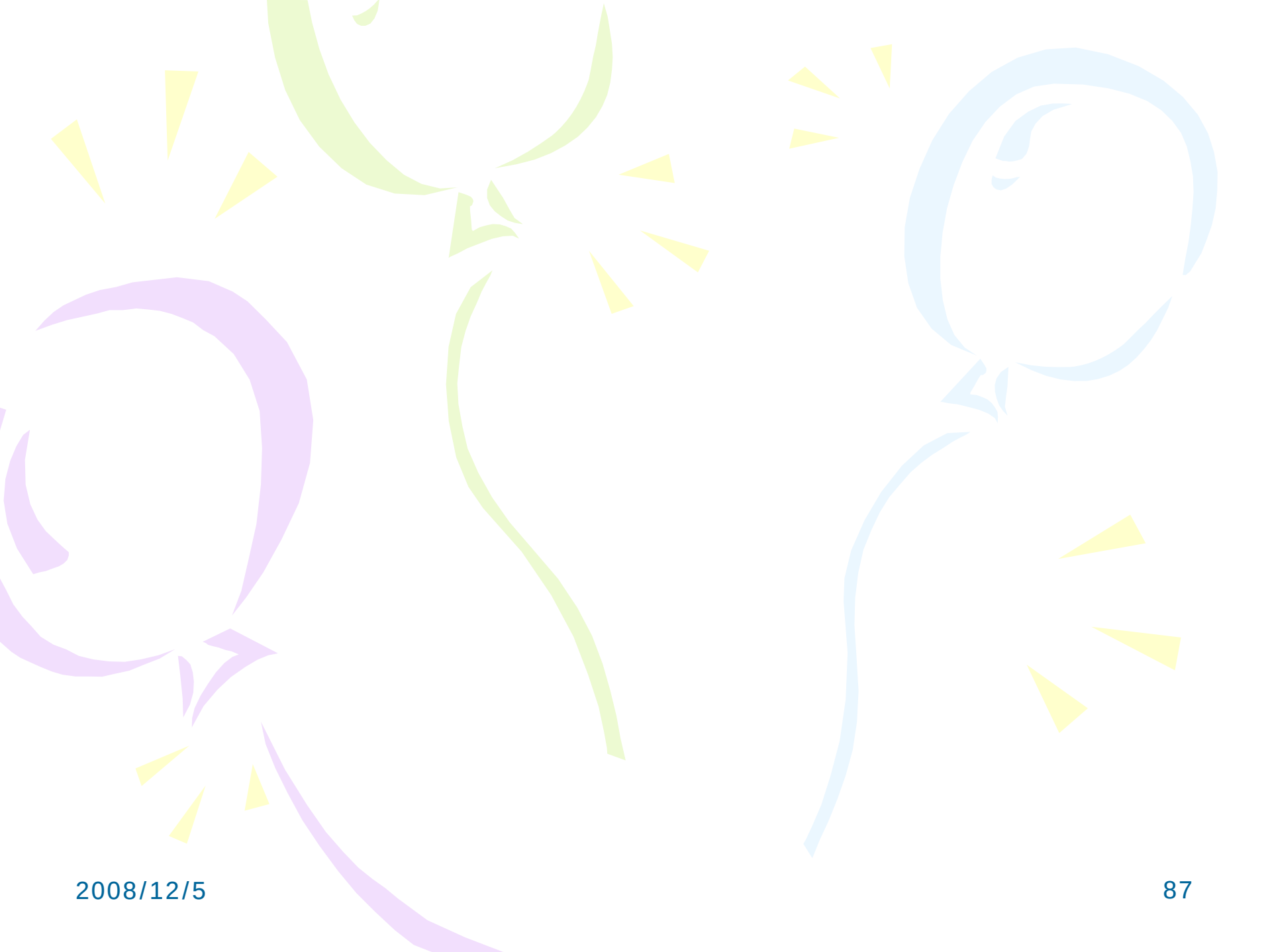


Fig. 6. Magnified region of the exit-plane wave function showing the grain boundary structure averaged parallel to the boundary over five repeat cells. (a) Amplitude image and (b) phase image. Unit cell projections along the [100] axis are shown. The insets at the lower right display simulated exit-plane wave data. The circle highlights a CuI site of deviating contrast in the grain boundary plane.

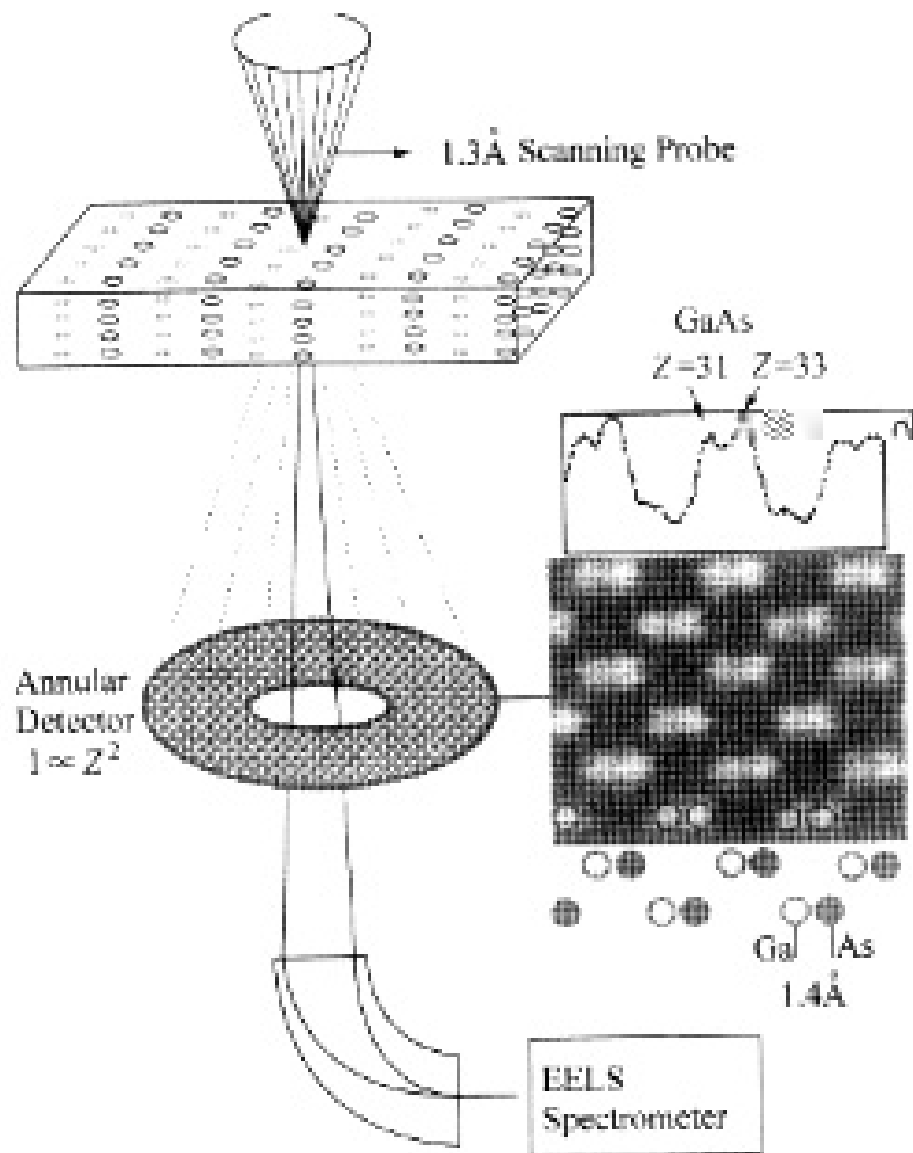
L. Houben, A. Thust, K. Urban: Ultramicroscopy 106 (2006) 200–214







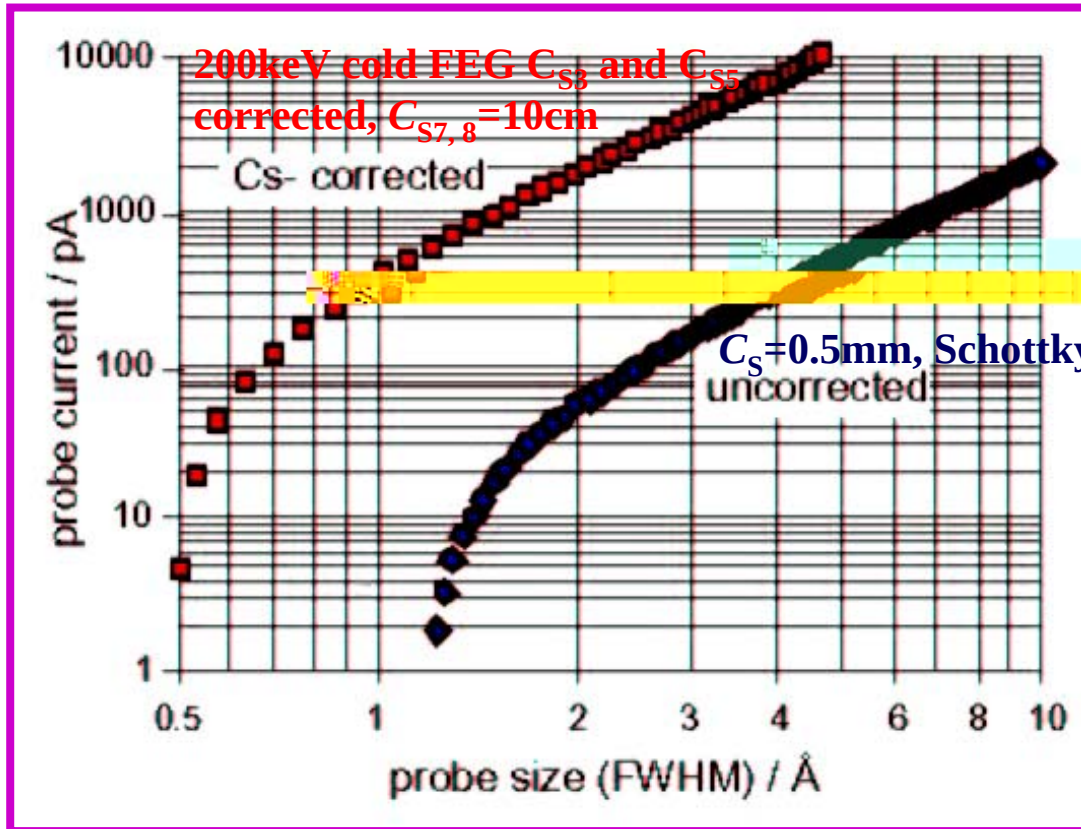
STEM

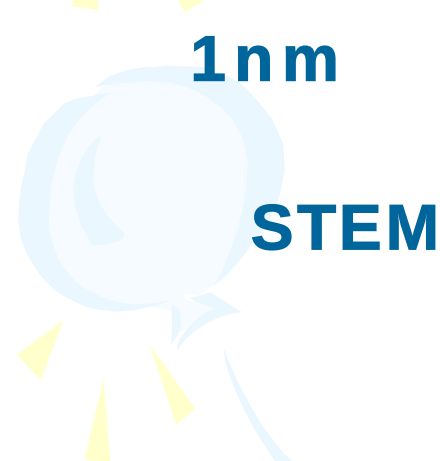
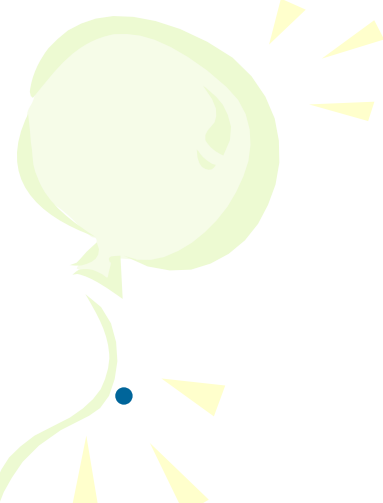


Cs Corrected STEM

Increasing beam current

- For 0.1-0.2 nm beam size, beam current increases 1-2 order.
- It is benefit to EELS analysis with atomic resolution.
- Improve electron lithography.
- Easier radiation damage.





1

1nm

STEM

Nion

4 ~ 6

STEM

10 mrad

4

16

Schottky

10

0.78 nA

• $\text{La}_{0.7}\text{Sr}_{0.3}\text{MnO}_3 / \text{SrTiO}_3$

A 3.1nm
La Mn

C Mn L
Mn

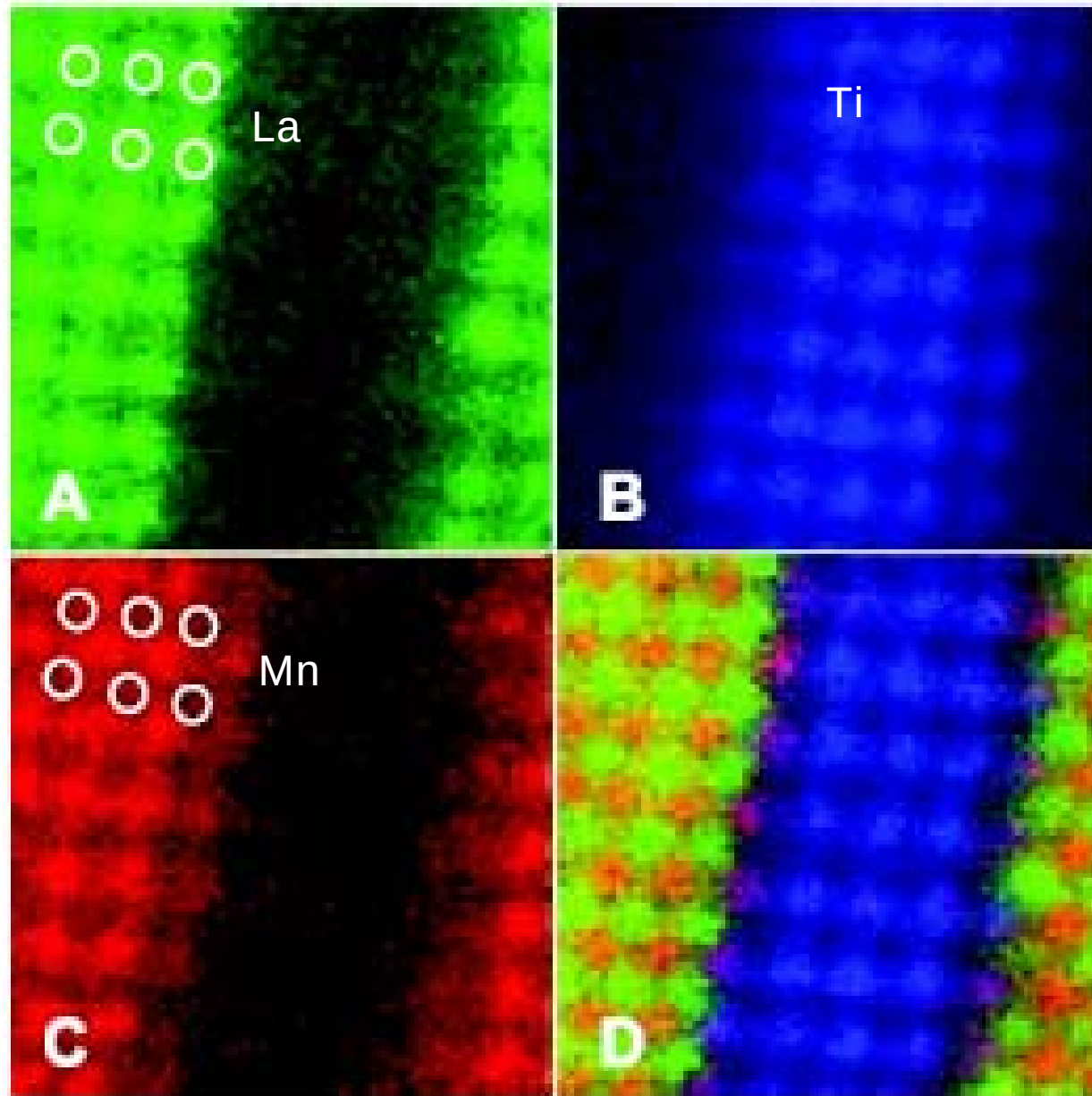
La Mn
La Mn

$1.9\text{ \AA}$ B Ti
L D

Mn La Ti

[D.A.Muller,
L.F.Kourkoutis,
M.Murfitt, J.H.Song,
H.Y.Hwang, J.Silcox,
N.Dellby, and
O.L.Krivanek:
Science 319 (2008)
1073]

2008/12/5



A-C TEM

91

• Ni
 Nb Zr
 XEDX
 Nb

(c)

(c)

(d)

(d)

Zr

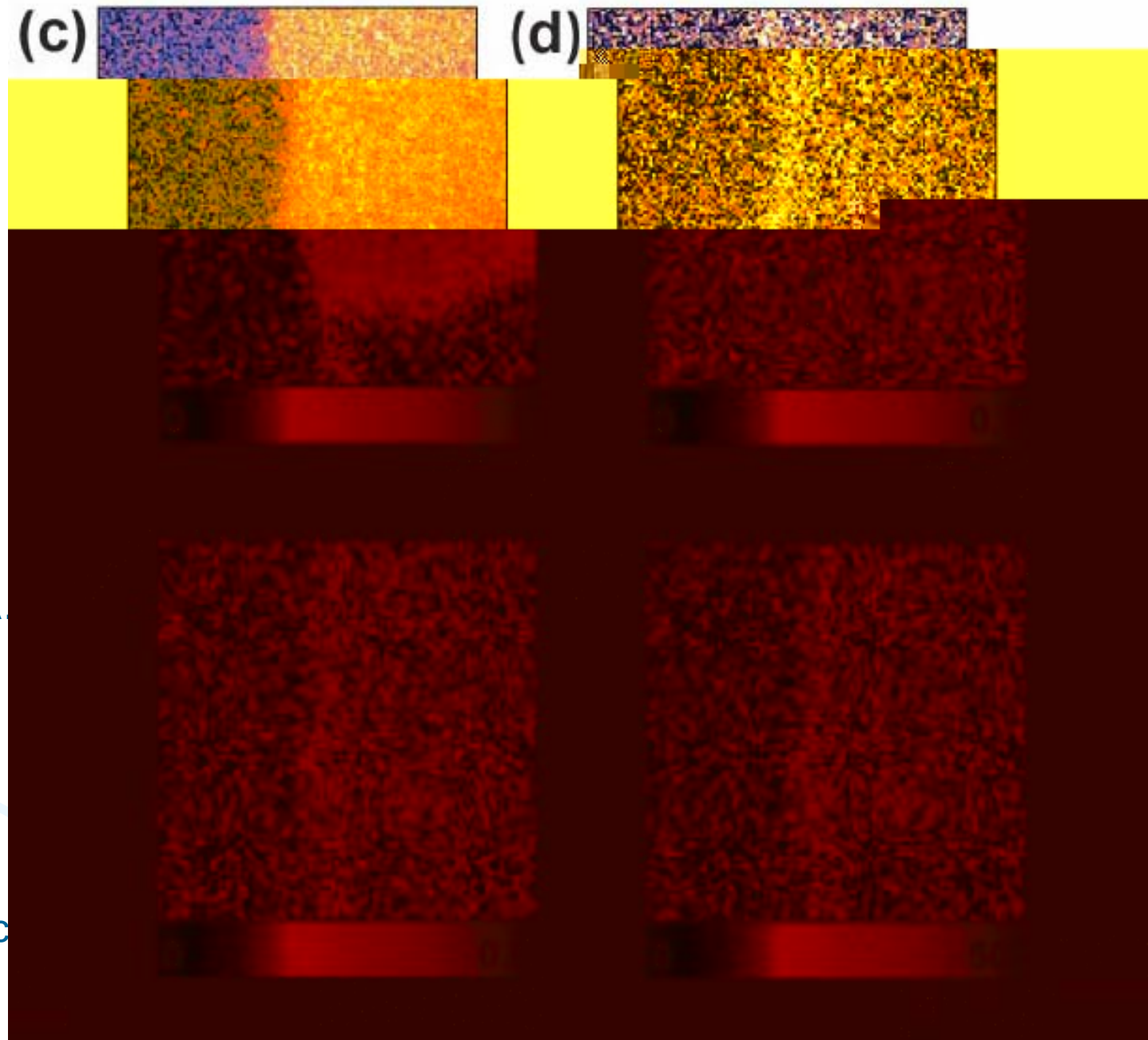
(e)

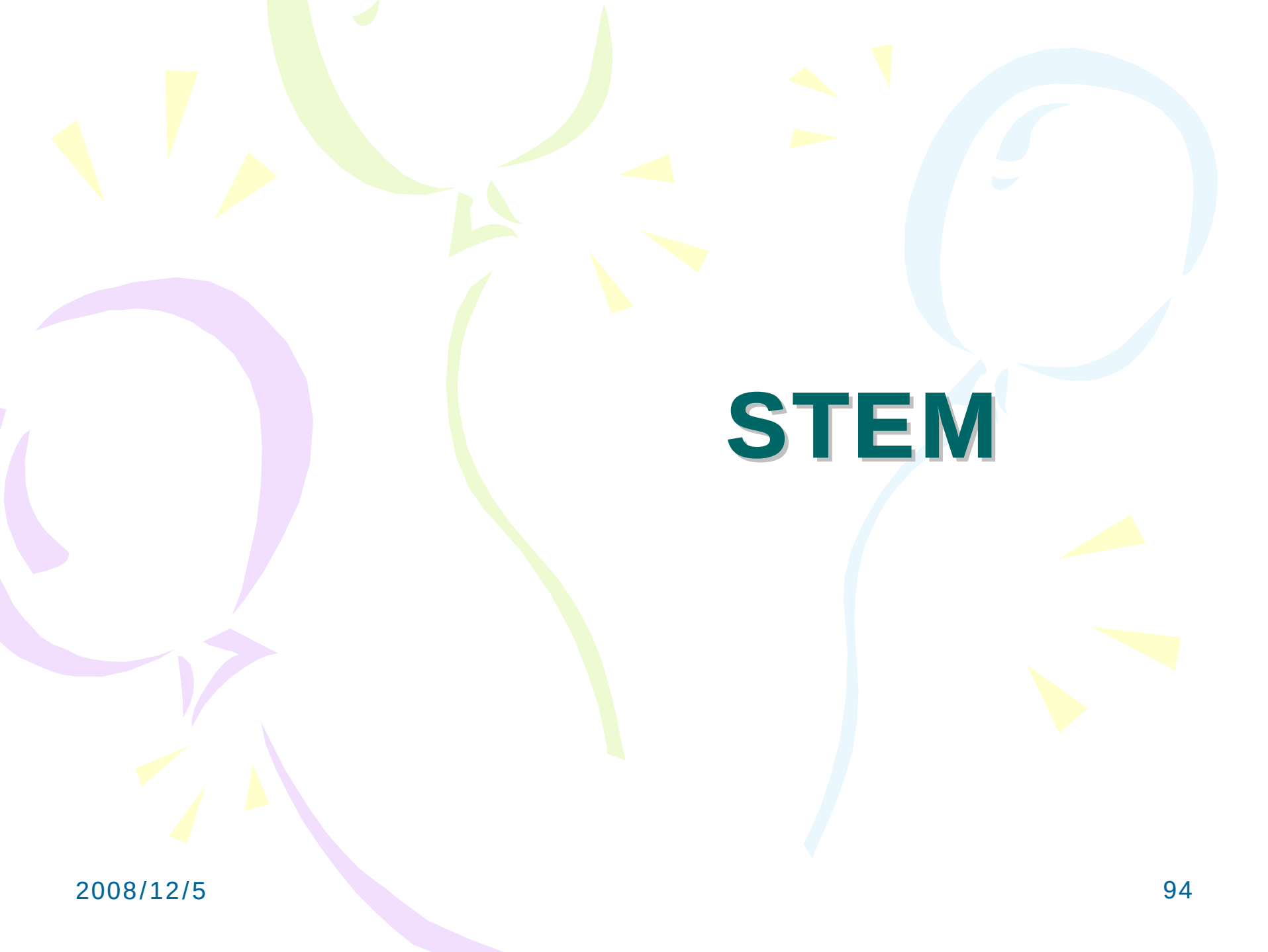
Zr

f

Zr

[M. Watanabe,
 D.W. Ackland, A.
 Burrows, C.J.
 Kiely, D.B.
 Williams, O.L.
 Krivanek, N.
 Dellby, M.F.
 Murfitt, and Z.
 Szilagyi: Microsc
 Microanal. 12,
 (2006) 2515]



The background features several large, flowing, abstract shapes in light green, light purple, and light blue. Interspersed among these are numerous small, yellow, triangular starburst or sun-like shapes, some of which are clustered together. The overall aesthetic is clean, modern, and vibrant.

STEM



AC-STEM

35mrad.

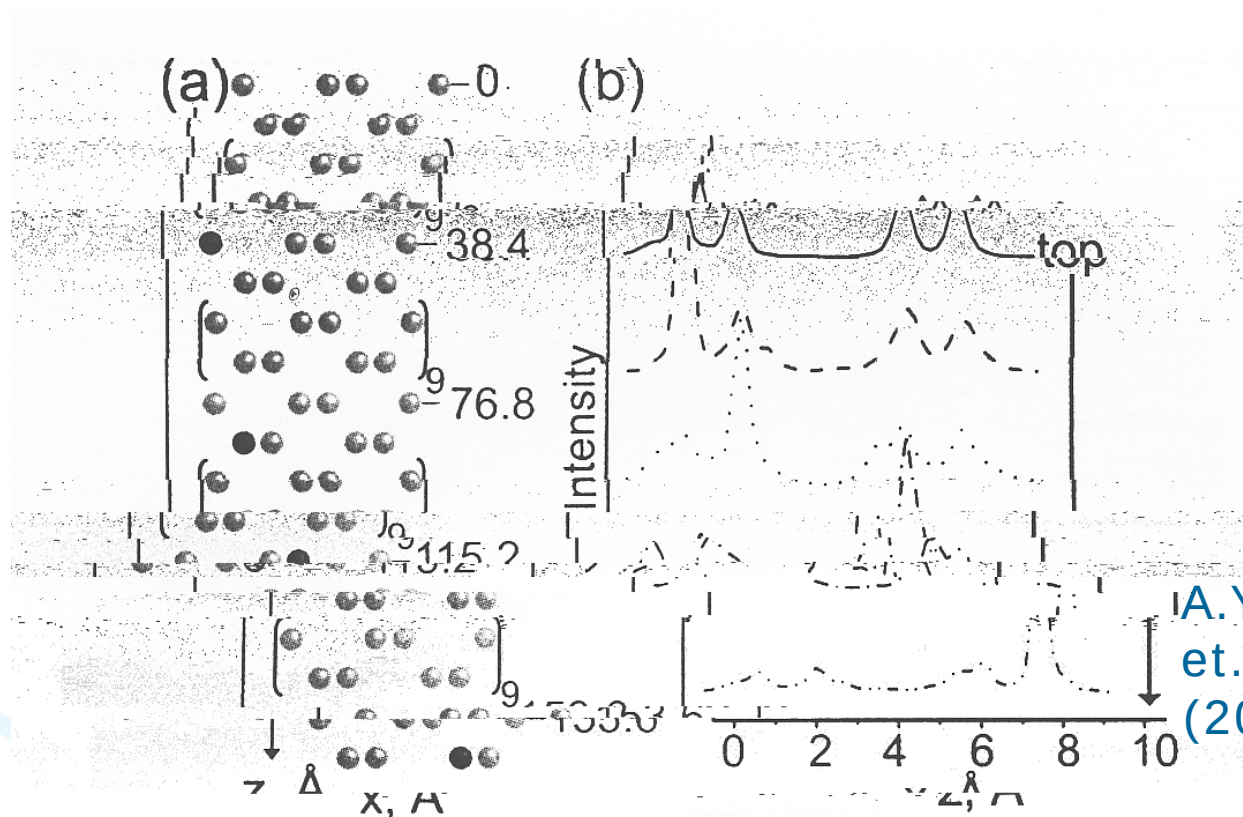
STEM

300

1 nm

50mrad

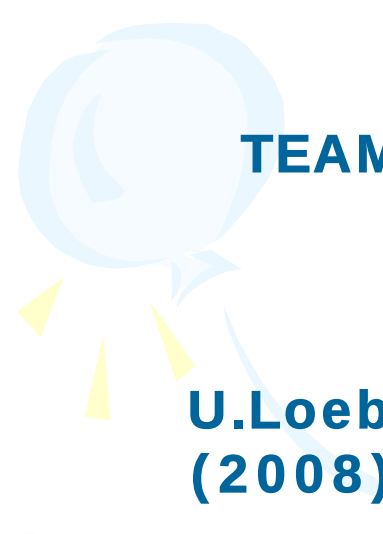
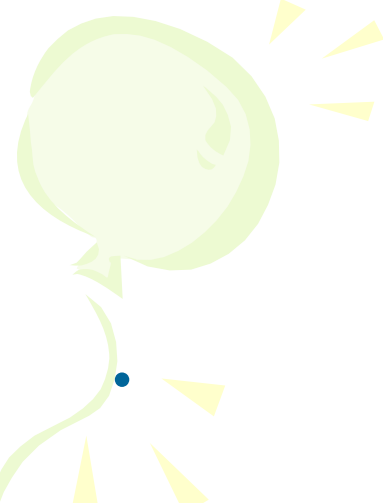
5



A.Y. Borisevich
et.al: J.EM,
(2006) 55, 7.

opped Si crystal with four Bi atoms at different
ay); (b) simulated HAADF image intensity
ee probe with 35 mrad semiangle detector
d. Defocus varies from 0 (top) to 38.4, 76.8,
cutively.

Fig. 3 (a) The model de
depths (Bi, black; Si, gra
scans for an aberration fi
angle from 70 to 300 mrad
115.2 and 153.6 Å, conse



Cs

Cs
f

Sin

TEAM

FEI

0.5 Å

-achromatic

-aplanatic

Achroplanat

Cc / Cs

[M.Haider, H.Muller, S.Uhlemann, J.Zach,

U.Loebau, and R.Hoeschen: Ultramicroscopy 108

(2008) 167] 1

Cc / Cs

200KV

2

1

2008/12/5

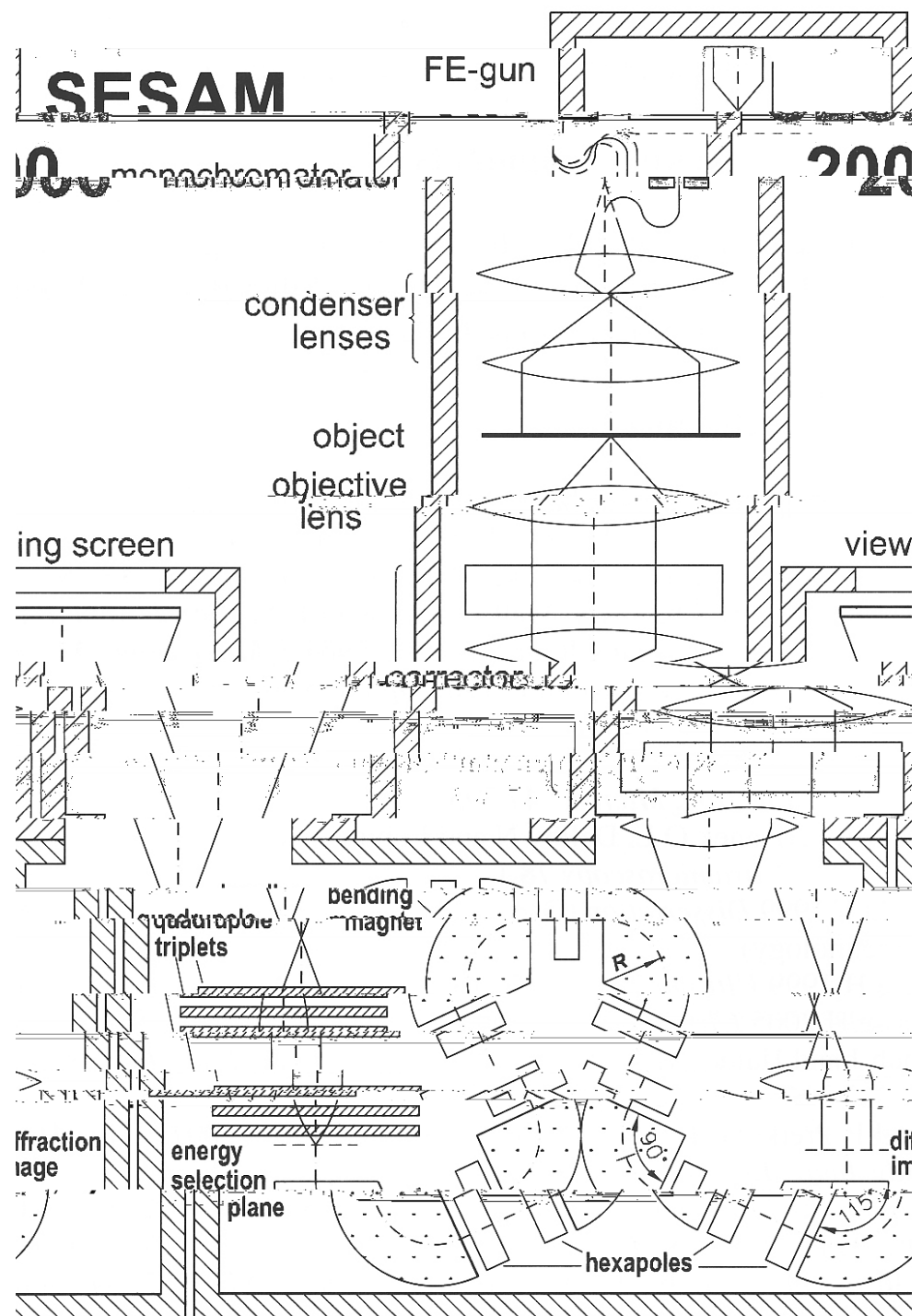
Cc

Cs A-C TEM

Sub-ev-Sub-Å Microscope

H.H.Rose: Sci. Tech. Adv. Mat.,
9 (1008) 14107 (30pp).

2008/12/5



STEM- 2008- NION



